

Hydrophobicity, Hydrophilicity and Silane Surface Modification







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Front Cover Photos: Water rolls off a duck's back. Lotus leaves exhibit superhydrophobicity. Biological systems are dependent on water, but at the same time must control the interaction. In a sense, all living organisms exhibit behaviors that can be described as both hydrophobic and hydrophilic.

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Gelest Hydrophobicity, Hydrophilicity and Silane Surface Modification

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Hydrophobicity, Hydrophilicity and Silane Surface Modification by Barry Arkles

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Silanes and Surface Modification

Silanes are silicon chemicals that possess a hydrolytically sensitive center that can react with inorganic substrates such as glass to form stable covalent bonds and possess an organic substitution that alters the physical interactions of treated substrates.

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Property modifications include: Hydrophobicity Release Dielectric Absorption Orientation Hydrophilicity Charge Conduction	Applications include:Architectural CoatingsWater-RepellentsAnti-stiction Coatings for MEMsMineral Surface TreatmentsFillers for CompositesPigment DispersantsDielectric CoatingsAnti-fog CoatingsRelease CoatingsOptical (LCD) CoatingsBonded PhasesSelf-Assembled Monolayers (SAMs)Crosslinkers for SiliconesNanoparticle Synthesis

In contrast with silanes utilized as coupling agents in adhesive applications, silanes used to modify the surface energy or wettability of substrates under normal conditions do not impart chemical reactivity to the substrate. They are often referred to as non-functional silanes. The main classes of silanes utilized to effect surface energy modification without imparting reactivity are:

Hydrophobic Silanes

Methyl Linear Alkyl Branched Alkyl Fluorinated Alkyl Aryl Dipodal

Hydrophilic Silanes

Polar Hydroxylic Ionic Charge inducible/charge switchable Embedded Hydrophilicity Masked

►►► Gelest, Inc.

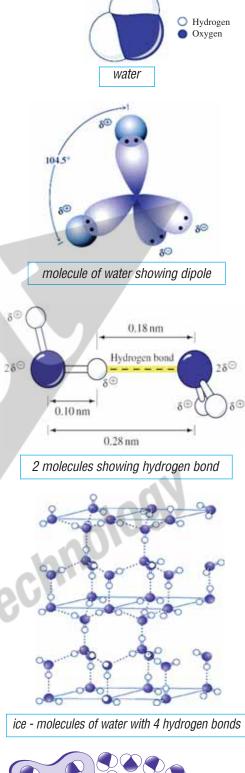
Water, Hydrophobicity and Hydrophilicity

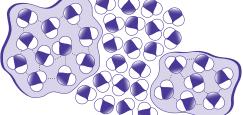
Hydrophobic and **Hydrophilic** are frequently used descriptors of surfaces. A surface is hydrophobic if it tends *not to* adsorb water or be wetted by water. A surface is hydrophilic if it tends *to* adsorb water or be wetted by water. More particularly, the terms describe the interaction of the boundary layer of a solid phase with liquid or vapor water. Silanes can be used to modify the interaction of boundary layers of solids with water with a high degree of control, effecting variable degrees of hydrophobicity or hydrophilicity.

Since the interaction of water with surfaces is frequently used to define surface properties, a brief review of its structure and properties can be helpful. Although the structure of water is a subject of early discussion in the study of physical sciences, it is interesting to note that the structure of liquid water is still not solved and, even so, most technologists lose appreciation of what is known about its structure and properties.

The quantum calculation of the structure of an isolated H₂O molecule has evolved to the currently accepted model which demonstrates a strong dipole, but no lone electron pairs associated with sp³ hybridized orbitals of oxygen. This model of isolated H₂O conforms most closely to the vapor state and extrapolation often leads to the conclusion that water is a collection of individual molecules which associate with each other primarily through dipole interactions. The polar nature of water, with its partial positive and partial negative dipole, explains why bulk water readily dissolves many ionic species and interacts with ionic surfaces. The difference between isolated vapor phase water and bulk liquid water is much more extreme than can be accounted for by a model relying only on dipole interaction. The properties of bulk liquid water are strongly influenced by hydrogen bond interactions. In the liquid state, in spite of 80% of the electrons being concerned with bonding, the three atoms of a water molecule do not stay together as discrete molecules. The hydrogen atoms are constantly exchanging between water molecules in a protonation-deprotonation process. Both acids and bases catalyze hydrogen exchange and, even when at its slowest rate of exchange (at pH 7), the average residence time of a hydrogen atom is only about a millisecond. In the liquid state, water molecules are bound to each other by an average of three hydrogen bonds. Hydrogen bonds arise when a hydrogen that is covalently bound to an oxygen in one molecule of water nears another oxygen from another water molecule. The electrophilic oxygen atom "pulls" the hydrogen closer to itself. The end result is that the hydrogen is now shared (unequally) between the oxygen to which it is covalently bound and the electrophilic oxygen to which it is attracted (O-H···O). Each hydrogen bond has an average energy of 20 kJ/mol. This is much less than an O-H covalent bond, which is 460 kJ/mol. Even though an individual hydrogen bond is relatively weak, the large number of hydrogen bonds that exist in water which pull the molecules together have a significant role in giving water its special bulk properties. In ice, water molecules are highly organized with four hydrogen bonds. Liquid water is thought to be a combination of domains of molecules with 3-4 hydrogen bonds separated by domains with 2-3 hydrogen bonds, subject to constant turnover - the *flickering cluster model*.

This brief description of water is provided in order to give the insight that whenever a solid surface interacts with bulk water it is interacting with a soft matter structure, not simply a collection of individual molecules. Surface interactions with water must compete with a variety of internal interactions of liquid phase water: van der Waals forces, dipole interactions, hydrogen bonding and proton exchange.





liquid water - flickering cluster model regions of molecules with 3-4 hydrogen bonds separated by regions with 2-3 hydrogen bonds (not shown: out of plane hydrogen bonds)

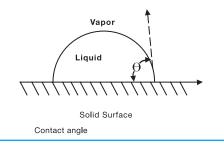
Wettability and Contact Angle

A surface is said to be wetted if a liquid spreads over the surface evenly without the formation of droplets. When the liquid is water and it spreads over the surface without the formation of droplets, the surface is said to be hydrophilic. In terms of energetics, this implies that the forces associated with the interaction of water with the surface are greater than the cohesive forces associated with bulk liquid water. Water droplets form on hydrophobic surfaces, implying that cohesive forces associated with bulk water are greater than the forces associated with the interaction of water with the surface. Practically, hydrophobicity and hydrophilicity are relative terms. A simple quantitative method for defining the relative degree of interaction of a liquid with a solid surface is the contact angle of a liquid droplet on a solid substrate. If the contact angle of water is less than 30°, the surface is designated hydrophilic since the forces of interaction between water and the surface nearly equal the cohesive forces of bulk water and water does not cleanly drain from the surface. If water spreads over a surface and the contact angle at the spreading front edge of the water is less than 10°, the surface is often designated as superhydrophilic provided that the surface is not absorbing the water, dissolving in the water or reacting with the water. On a hydrophobic surface, water forms distinct droplets. As the hydrophobicity increases, the contact angle of the droplets with the surface increases. Surfaces with contact angles greater than 90° are designated as hydrophobic. The theoretical maximum contact angle for water on a smooth surface is 120°. Micro-textured or micro-patterned surfaces with hydrophobic asperities can exhibit apparent contact angles exceeding 150° and are associated with superhydrophobicity and the "lotus effect".

Hydrophobic-"poor wetting"



Contact Angle Defines Wettability



Contact Angle of Water on Smooth Surfaces

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heptadecafluorodecyltrimethoxysilane*	115°
poly(tetrafluoroethylene)	108-112°
poly(propylene)	108°
octadecyldimethylchlorosilane*	110°
octadecyltrichlorosilane*	102-109°
tris(trimethylsiloxy)-	10.49
silylethyldimethylchlorosilane	104°
octyldimethylchlorosilane*	104°
dimethyldichlorosilane*	95-105°
butyldimethylchlorosilane*	100°
trimethylchlorosilane*	90-100°
poly(ethylene)	88-103°
poly(styrene)	94°
poly(chlorotrifluoroethylene)	90°
human skin	75-90°
diamond	87°
graphite	86°
silicon (etched)	86-88°
talc	50-55°
chitosan	80-81°
steel	70-75°
methacryloxypropyltrimethoxysilane	70°
gold, typical (see gold, clean)	66°
intestinal mucosa	50-60°
glycidoxypropyltrimethoxysilane*	49°
kaolin	42-46°
platinum	40°
silicon nitride	28-30°
silver iodide	17°
soda-lime glass	<15°
gold, clean	<10°
*Note: Contact angles for silanes refer to smoo surfaces.	oth treated

Hydrophilic-"good wetting"

Ordinary Surface-"typical wetting"

Critical Surface Tension and Adhesion

While the contact angle of water on a substrate is a good indicator of the relative hydrophobicity or hydrophilicity of a substrate, it is not a good indicator for the wettability of the substrate by other liquids. Critical surface tension is associated with the wettability or release properties of a solid. It serves as a better predictor of the behavior of a solid with a range of liquids.

Liquids with a surface tension below the critical surface tension (γ_c) of a substrate will wet the surface, i.e., show a contact angle of 0 ($\cos\theta_e = 1$). The critical surface tension is unique for any solid and is determined by plotting the cosine of the contact angles of liquids of different surface tensions and extrapolating to 1. The contact angle is given by Young's equation:

$\gamma_{sv} - \gamma_{sl} = \gamma_{lv} \cdot \cos\theta_{el}$

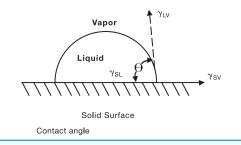
where γ_{sl} = interfacial surface tension, γ_{lv} = surface tension of liquid.

Hydrophilic behavior is generally observed by surfaces with critical surface tensions greater than 45 dynes/cm. As the critical surface tension increases, the expected decrease in contact angle is accompanied with stronger adsorptive behavior and with increased exotherms associated with the adsorption.

Hydrophobic behavior is generally observed by surfaces with critical surface tensions less than 35 dynes/cm. At first, the decrease in critical surface tension is associated with oleophilic behavior, i.e. the wetting of the surfaces by hydrocarbon oils. As the critical surface tensions decrease below 20 dynes/cm, the surfaces resist wetting by hydrocarbon oils and are considered oleophobic as well as hydrophobic.

Silane treatment has allowed control of thixotropic activity of silica and clays in paint and coating applications. In the reinforcement of thermosets and thermoplastics with glass fibers, one approach for optimizing reinforcement is to match the critical surface tension of the silylated glass surface to the surface tension of the polymer in its melt or uncured condition. This has been most helpful in resins with no obvious functionality such as polyethylene and polystyrene. Immobilization of cellular organelles, including mitochondria, chloroplasts, and microsomes, has been effected by treating silica with alkylsilanes of C_8 or greater substitution.

Contact Angle Defines Wettability



Critical surface tensions

	γ_{c}
	dynes/cm
neptadecafluorodecyltrichlorosilane	12.0
poly(tetrafluoroethylene)	18.5
octadecyltrichlorosilane	20-24
methyltrimethoxysilane	22.5
nonafluorohexyltrimethoxysilane	23.0
vinyltriethoxysilane	25 05 5
paraffin wax	25.5
ethyltrimethoxysilane	27.0
propyltrimethoxysilane	28.5
glass, soda-lime (wet)	30.0
poly(chlorotrifluoroethylene)	31.0
poly(propylene)	31.0
poly(propylene oxide)	32
polyethylene	33.0
trifluoropropyltrimethoxysilane	33.5
3-(2-aminoethyl)-aminopropyltrimethoxysilane	33.5
poly(styrene)	34
p-tolyltrimethoxysilane	34
cyanoethyltrimethoxysilane	34
aminopropyltriethoxysilane	35
polymethylmethacrylate	39
polyvinylchloride	39
phenyltrimethoxysilane	40.0
chloropropyltrimethoxysilane	40.5
mercaptopropyltrimethoxysilane	41
glycidoxypropyltrimethoxysilane	42.5
poly(ethyleneterephthalate)	43
poly(ethylene oxide)	43-45
copper (dry)	44
aluminum (dry)	45
ron (dry)	46
nylon 6/6	45-6
glass, soda-lime (dry)	47
silica, fused	78
titanium dioxide (anatase)	91
ferric oxide	107
tin oxide	111
Note: Critical surface tensions for silanes refer to smooth surfaces.	treated

How does a Silane Modify a Surface?

Most of the widely used organosilanes have one organic substituent and three hydrolyzable substituents. In the vast majority of surface treatment applications, the alkoxy groups of the trialkoxysilanes are hydrolyzed to form silanol-containing species. Reaction of these silanes involves four steps. Initially, hydrolysis of the three labile groups occurs. Condensation to oligomers follows. The oligomers then hydrogen bond with OH groups of the substrate. Finally, during drying or curing, a covalent linkage is formed with the substrate with concomitant loss of water. Although described sequentially, these reactions can occur simultaneously after the initial hydrolysis step. At the interface, there is usually only one bond from each silicon of the organosilane to the substrate surface. The two remaining silanol groups are present either in condensed or free form. The R group remains available for covalent reaction or physical interaction with other phases.

Silanes can modify surfaces under anhydrous conditions consistent with monolayer and vapor phase deposition requirements. Extended reaction times (4-12 hours) at elevated temperatures (50°-120°C) are typical. Of the alkoxysilanes, only methoxysilanes are effective without catalysis. The most effective silanes for vapor phase deposition are cyclic azasilanes.

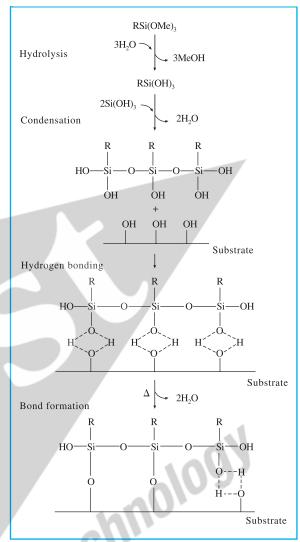
Hydrolysis Considerations

Water for hydrolysis may come from several sources. It may be added, it may be present on the substrate surface, or it may come from the atmosphere. The degree of polymerization of the silanes is determined by the amount of water available and the organic substituent. If the silane is added to water and has low solubility, a high degree of polymerization is favored. Multiple organic substitution, particularly if phenyl or tertiary butyl groups are involved, favors formation of stable monomeric silanols.

The thickness of a polysiloxane layer is also determined by the concentration of the siloxane solution. Although a monolayer is generally desired, multilayer adsorption results from solutions customarily used. It has been calculated that deposition from a 0.25% silane solution onto glass could result in three to eight molecular layers. These multilayers could be either interconnected through a loose network structure, or intermixed, or both, and are, in fact, formed by most deposition techniques. The orientation of functional groups is generally horizontal, but not necessarily planar, on the surface of the substrate.

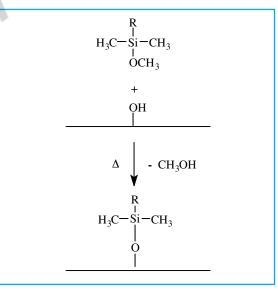
The formation of covalent bonds to the surface proceeds with a certain amount of reversibility. As water is removed, generally by heating to 120° C for 30 to 90 minutes or evacuation for 2 to 6 hours, bonds may form, break, and reform to relieve internal stress.

Hydrolytic Deposition of Silanes



B. Arkles, CHEMTECH, 7, 766, 1977

Anhydrous Deposition of Silanes



Selecting A Silane for Surface Modification -Inorganic Substrate Perspective

Factors influencing silane surface modification selection include:

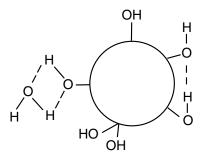
Concentration of surface hydroxyl groups Type of surface hydroxyl groups Hydrolytic Stability of the bond formed Physical dimensions of the substrate or substrate features

Surface modification is maximized when silanes react with the substrate surface and present the maximum number of accessible sites with appropriate surface energies. An additional consideration is the physical and chemical properties of the interphase region. The interphase can promote or detract from total system properties depending on its physical properties such as modulus or chemical properties such as water/hydroxyl content.

Hydroxyl-containing substrates vary widely in concentration and type of hydroxyl groups present. Freshly fused substrates stored under neutral conditions have a minimum number of hydroxyls. Hydrolytically derived oxides aged in moist air have significant amounts of physically adsorbed water which can interfere with coupling. Hydrogen bonded vicinal silanols react more readily with silane coupling agents, while isolated or free hydroxyls react reluctantly.

Silanes with three alkoxy groups are the usual starting point for substrate modification. These materials tend to deposit as polymeric films, effecting total coverage and maximizing the introduction of organic functionality. They are the primary materials utilized in composites, adhesives, sealants, and coatings. Limitations intrinsic in the utilization of a polylayer deposition are significant for nano-particles or nano-composites where the interphase dimensions generated by polylayer deposition may approach those of the substrate. Residual (non-condensed) hydroxyl groups from alkoxysilanes can also interfere in activity. Monoalkoxy-silanes provide a frequently used alternative for nano-featured substrates since deposition is limited to a monolayer.

If the hydrolytic stability of the oxane bond between the silane and the substrate is poor or the application is in an aggressive aqueous environment, dipodal silanes often exhibit substantial performance improvements. These materials form tighter networks and may offer up to 10⁵x greater hydrolysis resistance making them particularly appropriate for primer applications.





Water droplets on a (heptadecafluoro-1,1,2,2-tetrahydrodecyl)trimethoxysilane-treated silicon wafer exhibit high contact angles, indicative of the low surface energy. Surfaces are both hydrophobic and resist wetting by hydrocarbon oils. (water droplets contain dye for photographic purposes).

Silane	Effectiveness	on	Inorganics

	SUBSTRATES
EXCELLENT	Silica
ENCELLENT	Quartz
A	Glass
	Aluminum (AlO(OH))
	Alumino-silicates (e.g. clays)
	Silicon
GOOD	Copper
dood	Tin (SnO)
1	Talc
	Inorganic Oxides (e.g. Fe_2O_3 , TiO_2 , Cr_2O_3)
	Steel, Iron
	Asbestos
	Nickel
	Zinc
	Lead
SLIGHT	Marble, Chalk (CaCO ₃)
↑	Gypsum (CaSO ₄)
	Barytes (BaSO ₄)
POOR	Graphite
	Carbon Black

Estimates for Silane Loading on Siliceous Fillers

Average Particle Size	Amount of Silane
	(minimum of monolayer coverage)
<1 micron	1.5%
1-10 microns	1.0%
10-20 microns	0.75%
>100 microns	0.1% or less

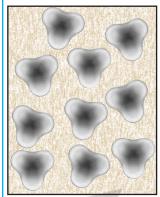
Hydrophobic Silane Surface Treatments

Factors which contribute to the ability of an organosilane to generate a hydrophobic surface are its organic substitution, the extent of surface coverage, residual unreacted groups (both from the silane and the surface) and the distribution of the silane on the surface.

Aliphatic hydrocarbon substituents or fluorinated hydrocarbon substituents are the hydrophobic entities which enable silanes to induce surface hydrophobicity. Beyond the simple attribute that in order to generate a hydrophobic surface the organic substitution of the silane must be nonpolar, more subtle distinctions can be made. The hydrophobic effect of the organic substitution can be related to the free energy of transfer of hydrocarbon molecules from an aqueous phase to a homogeneous hydrocarbon phase. For non-polar entities, van der Waals interactions are predominant factors in interactions with water and such interactions compete with hydrogen bonding in ordering of water molecules. Van der Waals interactions for solid surfaces are primarily related to the instantaneous polarizeability of the solid which is proportional to the dielectric constant or permittivity at the primary UV absorption frequency and the refractive index of the solid. Entities which present sterically closed structures that minimize van der Waals contact are more hydrophobic than open structures that allow van der Waals contact. Thus, in comparison to polyethylene, polypropylene and polytetrafluoroethylene are more hydrophobic. Similarly methyl-substituted alkylsilanes and fluorinated alkylsilanes provide better hydrophobic surface treatments than linear alkyl silanes.

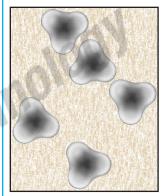
Surfaces to be rendered hydrophobic usually are polar with a distribution of hydrogen bonding sites. A successful hydrophobic coating must eliminate or mitigate hydrogen bonding and shield polar surfaces from interaction with water by creating a non-polar interphase. Hydroxyl groups are the most common sites for hydrogen bonding. The hydrogens of hydroxyl groups can be eliminated by oxane bond formation with an organosilane. The effectiveness of a silane in reacting with hydroxyls impacts hydrophobic behavior not only by eliminating the hydroxyls as water adsorbing sites, but also by providing anchor points for the nonpolar organic substitution of the silane which shields the polar substrates from interaction with water.

Strategies for silane surface treatment depend on the population of hydroxyl groups and their accessibility for bonding. A simple conceptual case is the reaction of organosilanes to form a monolayer. If all hydroxyl groups are capped by the silanes and the surface is effectively shielded, a hydrophobic surface is achieved. Practically, not all of the hydroxyl groups may react leaving residual sites for hydrogen bonding. Further, there may not be enough anchor points on the surface to allow the organic substituents to effectively shield the substrate. Thus the substrate reactive groups of the silane, the conditions of deposition, the ability of the silane to form monomeric or polymeric layers and the nature of the organic substitution all play a role in rendering a surface hydrophobic. The minimum requirements of hydrophobicity and economic restrictions for different applications further complicate selection.



complete coverage

incomplete hydroxyl reaction



few bonding opportunities

 $= (CH_3)_3Si = trimethylsilyl$

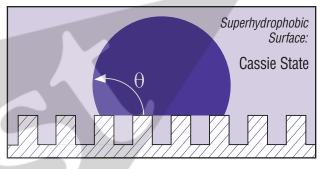
Hypothetical Trimethylsilylated Surfaces

Pyrogenic silica has 4.4-4.6 OH/nm². Typically less than 50% are reacted. Other substrates have fewer opportunities for reaction. Hydrophobicity is frequently associated with oleophilicity, the affinity of a substance for oils, since nonpolar organic substitution is often hydrocarbon in nature and shares structural similarities with many oils. The hydrophobic and oleophilic effect can be differentiated and controlled. At critical surface tensions of 20-30, surfaces are wetted by hydrocarbon oils and are water repellent. At critical surface tensions below 20, hydrocarbon oils no longer spread and the surfaces are both hydrophobic and oleophobic. The most oleophobic silane surface treatments have fluorinated long-chain alkyl silanes and methylated medium chain alkyl silanes.

Superhydrophobic surfaces are those surfaces that present apparent contact angles that exceed the theoretical limit for smooth surfaces, i.e. >120°. The most common examples of super-hydrophobicity are associated with surfaces that are rough on a sub-micron scale and contact angle measurements are composites of solid surface asperities and air denoted the *Cassie state*. Perfectly hydrophobic surfaces (contact angles of 180°) have been prepared by hydrolytic deposition of methylchlorosilanes as microfibrillar structures.

Hydrophobicity vs Water Permeability

Although silane and silicone derived coatings are in general the most hydrophobic, they maintain a high degree of permeability to water vapor. This allows coatings to breathe and reduce deterioration at the coating interface associated with entrapped water. Since ions are not transported through non-polar silane and silicone coatings, they offer protection to composite structures ranging from pigmented coatings to rebar reinforced concrete.





Automotive side windows are treated with fluoroalkylsilanes to provide self-cleaning properties. Water beads remove soil as they are blown over the glass substrate during acceleration.

Hydrophilic Silane Surface Treatments

The vast majority of surfaces are hydrophilic and water is omnipresent in the environment, yet the precise nature of interaction of water with specific surfaces is largely unknown. Water adsorption may be uniform or in isolated patches. It may be driven by a number of different physical and chemical processes. The adsorption of water by a surface may be assisted or retarded by other adsorbents present in the environment. The purpose of applying a hydrophilic surface treatment is to control the nature and extent of interaction of water with a surface.

The controlled interaction of water with substrates can offer various degrees of hydrophilicity ranging from physi-sorption to chemi-sorption and centers for ioninteraction. The utility of hydrophilic surfaces varies widely. Anti-fog coatings exploit high surface energies to flatten water droplets rather than allowing them to form light-scattering droplets. In biological systems hydrophilic surfaces can reduce nonspecific bonding of proteins. Hydrophilic coatings with hydrogen bonding sites allow formation of tightly adherent layers of water with high lubricity in biological systems and the ability to resist oil adsorption in anti-graffiti coatings. They can also be used to disperse particles in aqueous coat-

Anti-fog coatings applied to one side of a visor can be prepared from combinations of polyalkylene oxide functional silanes and film-forming hydrophilic silanes.



Heats of Immersion in Water, mJ/m ²			
titanium dioxide talc aminopropyltriethoxysilane* silicon dioxide glass vinyltris(methoxyethoxy)silane* mercaptopropyltrimethoxysilane* graphite polytetrafluoroethylene	225-250 220-260 230-270 210-225 200-205 110-190 80-170 32-35 24-25		
*Data for silane treated surfaces in this table is primarily from B. Marciniec et al, Colloid & Polymer Science, <i>261</i> , 1435, 1983 recalculated for surface area.			

ings and oil-in-water emulsions. Hydrophilic coatings with ionic sites form antistatic coatings, dye receptive surfaces and can generate conductive or electrophoretic pathways. Thick films can behave as polymeric electrolytes in battery and ion conduction applications.

In general, surfaces become more hydrophilic in the series: non-polar < polar, no hydrogen-bonding < polar, hydrogen-bonding < hydroxylic, < ionic. The number of sites and the structure and density of the interphase area also have significant influence on hydrophilicity.

Much of the discussion of hydrophobicity centers around high contact angles and their measurement. As a corollary, low or 0° contact angles of water are associated with hydrophilicity, but practically the collection of consistent data is more difficult. Discriminating between surfaces with a 0° contact angle is impossible. The use of heat of immersion is a method that generates more consistent data for solid surfaces, provided they do not react with, dissolve or absorb the tested liquid. Another important consideraton is whether water adsorbed is "free" or "bound." Free water is water that is readily desorbed under conditions of less than 100% relative humidity. If water remains bound to a substrate under conditions of less than 100% relative humidity, the surface is considered hygroscopic. Another description of hygroscopic water is a boundary layer of water adsorbed on a surface less than 200nm thick that cannot be removed without heating. A measure of the relative hygroscopic nature of surfaces is given by the water activity, the ratio of the fugacity, or escaping tendency, of water from a surface compared to the fugacity of pure water.

The hydrophilicity of a surface as measured or determined by contact angle is subject to interference by loosely bound oils and other contaminants. Heats of immersion and water activity measurements are less subject to this interference. Measurements of silane-modified surfaces demonstrate true modification of the intrinsic surface properties of substrates. If the immobilized hydrophilic layer is in fact a thin hydrogel film, then swelling ratios at equilibrium water absorbtion can provide useful comparative data.

Hydrophilic Silane Surface Treatments (continued)

Controlling hydrophilic interaction with silane surface treatments is accomplished by the selection of a silane with the appropriate hydrophilic substitution. The classes of substitution are:

- Polar, Non-Hydrogen Bonding
- Polar, Hydrogen-Bonding
- Hydroxylic
- Ionic-Charged



Aortic stents are coated to promote hydrophilicity, coupling to polymers and drug delivery systems.

The selection of the class of hydrophilic subsitution is dependent on the application. If it is sufficient for water to spread evenly over a surface to form a thin film that washes away and dries off quickly without leaving 'drying spots', then a polar aprotic silane is preferred. If a coating is desired that reduces non-specific binding of proteins or other biofoulants, then a polar hydrogenbonding material such as a polyether functional silane is preferred. A very different application for a polar non-hydroxylic materials is thin film proton conduction electrolytes. Lubricious coatings are usually hydroxylic since they require a restrained adsorbed phase of water. Antistatic coatings are usually charged or charge-inducible as are ion-conductive coatings used in the construction of thin-film batteries. A combination of hydrophilicity and hydrophobicity may be a requirement in coatings which are used as primers or in selective adsorption applications such as chromatography. Formulation limitations may require that hydrophilicity is latent and becomes unmasked after application.

Factors affecting the intrinsic hydrolytic stability of silane treated surfaces are magnified when the water is drawn directly into the interface. Even pure silicon dioxide is ultimately soluble in water (at a level of 2-6ppm), but the kinetics, low concentration for saturation and phase separation, make this a negligible consideration in most applications. The equilibrium constant for the rupture of a Si-O-Si bond by water to two Si-OH bonds is estimated at 10⁻³. Since at minimum 3 Si-O-Si bonds must be simultaneously broken under equilibrium conditions to dissociate an organosilane from a surface, in hydrophobic environments the long-term stability is a minor consideration. Depending on the conditions of exposure to water of a hydrophilic coating, the long-term stability can be an important consideration. Selection of a dipodal, polypodal or other network forming silane as the basis for inducing hydrophilicity or as a component in the hydrophilic surface treatment is often obligatory.

interaction	description	surface example	measurement - parameter
low	superhydrophobic oleophobic lipophobic	fluorocarbon	contact angle
	oleophilic lipophilic hydrophobic	hydrocarbon	water-sliding angle critical surface tension
moderate	polar hydrophilic	polymer oxide surface	heat of immersion
	hygroscopic	polyhydroxylic	water activity
strong	hydrogel film		equilibrium water absorption swell

Range of Water Interaction with Surfaces

Reacting with the Substrate

Leaving Groups

The reaction of an organofunctional silane with a surface bearing hydroxyl group results in a substitution reaction at silicon and the formation of the silvlated surface where the silicon is covalently attached to the surface via an oxygen linkage. This connection may be formed directly or in the presence of water through a reactive silanol intermediate. In general the reactivity of hydroxylated surfaces with organofunctional silanes decreases in the order: $Si-NR_2 > Si-Cl >$ $Si-NH-Si > Si-O_2CCH_3 > Si-OCH_3 > Si-OCH_2CH_3$. An analysis of the relevant bond energies indicates that the formation of the Si-O-surface bond is the driving force for the reaction under dry and aprotic conditions. Secondary factors contributing to the reactivity of organofunctional silanes with a surface are the volatility of the byproducts, the ability of the byproduct to hydrogen bond with the hydroxyls on the surface, the ability of the byproduct to catalyze further reactions, e.g. HCl or acetic acid, and the steric bulk of the groups on the silicon atom.

Although they are not the most reactive organosilanes, the methoxy and ethoxysilanes are the most widely used organofunctional silanes for surface modification. The rea-sons for this include the fact that they are easily handled and the alcohol byproducts are non-corrosive and volatile. The methoxysilanes are capable of reacting with substrates under dry, aprotic conditions, while the less reactive ethoxysilanes require catalysis for suitable reactivity. The low toxicity of ethanol as a byproduct of the reaction favors the ethoxysilanes in many commercial applications. The vast majority of organofunctional silane surface treatments are performed under conditions in which water is a part of the reaction medium, either directly added or contributed by adsorbed water on the substrate or atmospheric moisture. Enabling

Bond Dissociation EnergiesBondDissociation Energy
(kcal/mole)Me_3Si-NMe_298Me_3Si-N(SiMe_3)_2109Me_3Si-Cl117Me_3Si-OMe123Me_3Si-OEt122

136

Me₃Si-OSiMe₃

	Common Leaving Groups				
	Туре	Advantage	Disadvantage		
	dimethylamine	reactive, volatile byproduct	toxic		
1	hydrogen chloride	reactive, volatile byproduct	corrosive		
	silazane (NH ₃)	volatile	limited availability		
	methoxy	moderate reactivity, neutral byproduct	moderate toxicity		
	ethoxy	low toxicity	lower reactivity		

Special Topics

Dipodal Silanes

Functional dipodal silanes and combinations of nonfunctional dipodal silanes with functional silanes have significant impact on substrate bonding, hydrolytic stability and mechanical strength of many composites systems. They possess enabling activity in many coatings, particularly primer systems and aqueous immersion applications. The effect is thought to be a result of both the increased crosslink density of the interphase and a consequence of the fact that the resistance to hydrolysis of dipodal materials (with the ability to form six bonds to a substrate) is estimated at close to 100,000 times greater than conventional coupling agents (with the ability to form only three bonds to a substrate).

Both because dipodal silanes may not have functional groups identical to conventional coupling agents or because of economic considerations, conventional coupling agents are frequently used in combination with a non-functional dipodal silanes. In a typical application a dipodal material such as bis(triethoxysilyl)ethane (SIB1817.0) is combined at a 1:5 to 1:10 ratio with a traditional coupling agent. It is then processed in the same way as the traditional silane coupling agent.

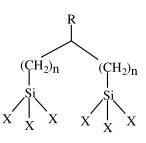
Effect of dipodal -SiCH₂CH₂Si- on the bond strength of a crosslinkable ethylene-vinyl acetate primer formulation

	Wet adhesion to metals (N/cm)	
Primer on metal 10% in <i>i</i> -PrOH	Titanium	Cold-rolled steel
No silane	Nil	Nil
Methacryloxypropylsilane	0.25	7.0
Methacryloxypropylsilane + 10% dipodal	10.75	28.0
		(cohesive failure)
90° peel strength after 2 h in 80°C water.		

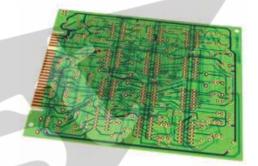
P. Pape et al, in Silanes and Other Coupling Agents, ed. K. Mittal, 1992, VSP, p105



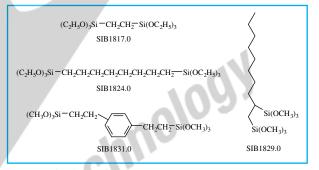
Hydrophobic coatings applied to antennas inhibit the formation of adsorbed water layers which become dielectric layers that absorb signals and cause high losses. If the water is in beads, the energy will be slightly diffracted because the water droplets have dimensions much less than a wavelength at these frequencies.



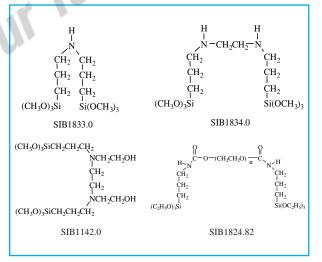
Multilayer printed circuit boards use dipodal silanes to maintain the integrity of the bond between metal and resins by reducing interfacial water adsorption.



Hydrophobic Dipodal Silanes



Hydrophilic Dipodal Silanes



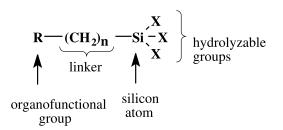
(215) 547-1015 FAX: (2

FAX: (215) 547-2484

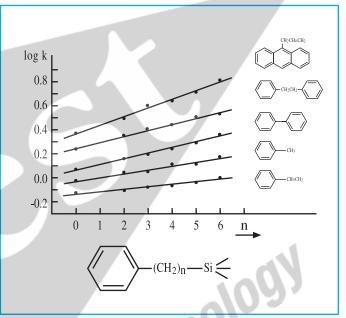
Linker Length

An important factor in controlling the effectiveness and properties of a coupled system is the linker between the organic functionality and the silicon atom. The linker length imposes a number of physical property and reactivity limitations. The desirability of maintaining the reactive centers close to the substrate are most important in sensor applications, in heterogeneous catalysis, fluorescent materials and composite systems in which the interfacing components are closely matched in modulus and coefficient of thermal expansion. On the other hand, inorganic surfaces can impose enormous steric constraints on the accessibility of organic functional groups in close proximity. If the linker length is long the functional group has greater mobility and can extend further from the inorganic substrate. This has important consequences if the functional group is expected to react with a single component in a multi-component organic or aqueous phases found in homogeneous and phase transfer catalysis, biological diagnostics or liquid chromatography. Extended linker length is also important in oriented applications such as self-assembled monolayers (SAMs). The typical linker length is three carbon atoms, a consequence of the fact that the propyl group is synthetically accessible and has good thermal stability.

Silanes with short linker length

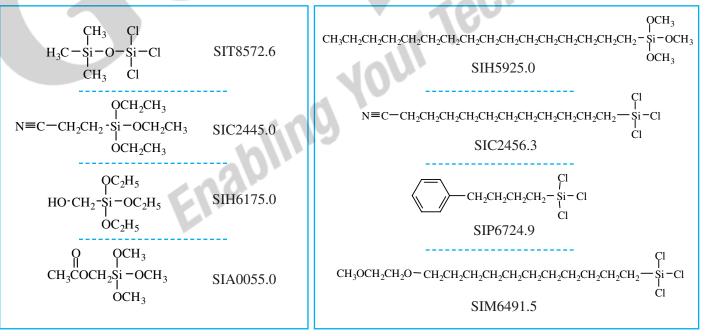


Effect of linker length on the separation of aromatic hydrocarbons



T. Den et al, in "Silanes, Surfaces, Interfaces" D. Leyden ed., 1986 p403.

Silanes with extended linker length



Partition, Orientation and Self-Assembly in Bonded Phases

Chromatography

Octadecyl, cyanopropyl and branched tricocyl silanes provide bonded phases for liquid chromatography. Reverse-phase thin-layer chromatography can be accomplished by treating plates with dodecyltrichlorosilane.

Liquid Crystal Displays

The interphase can also impose orientation of the bulk phase. In liquid crystal displays, clarity and permanence of image are enhanced if the display can be oriented parallel or perpendicular to the substrate. The use of surfaces treated with octadecyl(3-(trimethoxysilyl)propyl) ammonium chloride (perpendicular) or methylaminopropyltrimethoxysilane (parallel) has eliminated micromachining operations The oriented crystalline domains often observed in reinforced nylons have also been attributed to orientation effects of the silane in the interphase.

Self-Assembled Monolayers (SAMs)

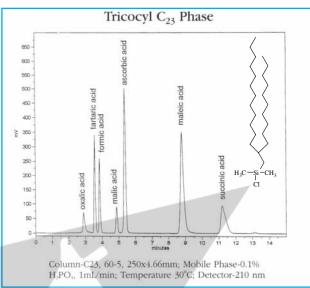
A Self-Assembled Monolayer (SAM) is a one molecule thick layer of material that bonds to a surface in an ordered way as a result of physical or chemical forces during a deposition process. Silanes can form SAMs by solution or vapor phase deposition processes. Most commonly, chlorosilanes or alkoxysilanes are used and once deposition occurs a chemical (oxane) bond forms with the surface rendering a permanent modification of the substrate. Applications for SAMs include micro-contact printing, soft lithography, dip-pen nanolithography, anti-stiction coatings and orientation layers involved in nanofabrication of MEMs, fluidic microassemblies, semiconductor sensors and memory devices.

Common long chain alkyl silanes used in the formation of SAMs are simple hydrocarbon, fluoroalkyl and end-group substituted silanes. Silanes with one hydrolyzeable group maintain interphase structure after deposition by forming a single oxane bond with the substrate. Silanes with three hydrolyzeable groups form siloxane (silsesquioxane) polymers after

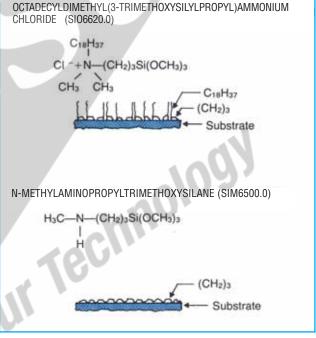
deposition, bonding both with each other as well as the substrate. For non-oxide metal substrates, silyl hydrides may be used, reacting with the substrate by a dehydrogenative coupling.

The perpendicular orientation of silanes with C_{10} or greater length can be utilized in micro-contact printing and other soft lithography methods. Here the silane may effect a simple differential adsorption, or if functionalized have a direct sensor effect.

Normal Phase HPLC of Carboxylic Acids with a C₂₃-Silane Bonded Phase

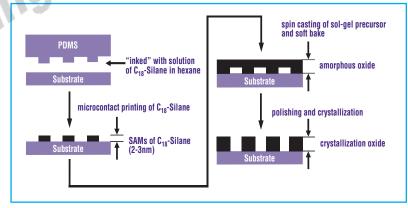


Orientation effects of silanes for passive LCDs









Modification of Metal Substrates

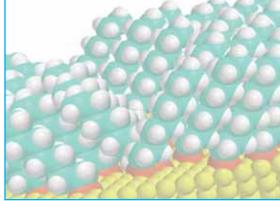
The optimum performance of silanes is associated with siliceous substrates. While the use of silanes has been extended to metal substrates, both the effectiveness and strategies for bonding to these less-reactive substrates vary. Four approaches of bonding to metals have been used with differing degrees of success. In all cases, selecting a dipodal or polymeric silane is preferable to a conventional trialkoxy silane.

Metals that form hydrolytically stable surface oxides, e.g. aluminum, tin, titanium. These oxidized surfaces tend to have sufficient hydroxyl functionality to allow coupling under the same conditions applied to the siliceous substrates discussed earlier.

Metals that form hydrolytically or mechanically unstable surface oxides, e.g. iron, copper, zinc. These oxidized surfaces tend to dissolve in water leading to progressive corrosion of the substrate or form a passivating oxide layer without mechanical strength. The successful strategies for coupling to these substrates typically involves two or more silanes. One silane is a chelating agent such as a diamine, polyamine or polycarboxylic acid. A second silane is selected which has a reactivity with the organic component and reacts with the first silane by co-condensation. If a functional dipodal or polymeric silane is not selected, 10-20% of a non-functional dipodal silane typically improves bond strength.

Metals that do not readily form oxides, e.g. nickel, gold and other precious metals. Bonding to these substrates requires coordinative bonding, typically a phosphine, sulfur (mercapto), or amine functional silane. A second silane is selected which has a reactivity with the organic component. If a functional dipodal or polymeric silane is not selected, 10-20% of a non-functional dipodal silane typically improves bond strength.





Octysilane adsorbed on titanium figure courtesy of M. Banaszak-Holl

Metals that form stable hydrides, e.g. titanium, zirconium, nickel. In a significant departure from traditional silane coupling agent chemistry, the ability of certain metals to form so-called amorphous alloys with hydrogen is exploited in an analogous chemistry in which hydride functional silanes adsorb and then coordinate with the surface of the metal. Most silanes of this class possess only simple hydrocarbon substitution such as octylsilane. However they do offer organic compatibility and serve to markedly change wet-out of the substrate. Both hydride functional silanes and treated metal substrates will liberate hydrogen in the presence of base or with certain precious metals such as platinum and associated precautions must be taken. (see p72.) H

 $H_{2}C = CH(CH_{2})_{8}CH_{2}S_{1}^{\dagger} - H$ SIU9048.0 H

Coupling Agents for Metals*			
Metal Class Screening Candidate			Candidates
Copper	Amine	SSP-060	SIT8398.0
Gold	Sulfur Phosphorus	SIT7908.0 SID4558.0	SIP6926.2 SIB1091.0
Iron	Amine Sulfur	SIB1834.0 SIB1824.6	WSA-7011 SIM6476.0
Tin	Amine	SIB1835.5	
Titanium	Epoxy Hydride	SIG5840.0 SIU9048.0	SIE6668.0
Zinc	Amine Carboxylate	SSP-060 SIT8402.0	SIT8398.0 SIT8192.6

*These coupling agents are almost always used in conjunction with a second silane with organic reactivity or a dipodal silane.

Difficult Substrates

Silane coupling agents are generally recommended for applications in which an inorganic surface has hydroxyl groups and the hydroxyl groups can be converted to stable oxane bonds by reaction with the silane. Substrates such as calcium carbonate, copper and ferrous alloys, and high phosphate and sodium glasses are not recommended substrates for silane coupling agents. In cases where a more appropriate technology is not available a number of strategies have been devised which exploit the organic functionality, film-forming and crosslinking properties of silane coupling agents as the primary mechanism for substrate bonding in place of bonding through the silicon atom. These approaches frequently involve two or more coupling agents.

Calcium carbonate fillers and marble substrates do not form stable bonds with silane coupling agents. Applications of mixed silane systems containing a dipodal silane or tetraethoxysilane in combination with an organofunctional silane frequently increases adhesion. The adhesive mechanism is thought to be due to the low molecular weight and low surface energy of the silanes which allows them initially to spread to thin films and penetrate porous structures followed by the crosslinking which results in the formation of a silica-rich encapsulating network. The silica-rich encapsulating network is then susceptible to coupling chemistry comparable to siliceous substrates. Marble and calciferous substrates can also benefit from the inclusion of anhydride-functional silanes which, under reaction conditions, form dicarboxylates that can form salts with calcium ions.

Metals and many metal oxides can strongly adsorb silanes if a chelating functionality such as diamine or dicarboxylate is present. A second organofunctional silane with reactivity appropriate to the organic component must be present. Precious metals such as gold and rhodium form weak coordination bonds with phosphine and mercaptan functional silanes.

High phosphate and sodium content glasses are frequently the most frustrating substrates. The primary inorganic constituent is silica and would be expected to react readily with silane coupling agents. However alkali metals and phosphates not only do not form hydrolytically stable bonds with silicon, but, even worse, catalyze the rupture and redistribution of silicon-oxygen bonds. The first step in coupling with these substrates is the removal of ions from the surface by extraction with deionized water. Hydrophobic dipodal or multipodal silanes are usually used in combination with organofunctional silanes. In some cases polymeric silanes with multiple sites for interaction with the substrate are used. Some of these, such as the polyethylenimine functional silanes can couple to high sodium glasses in an aqueous environment.

 $O^{-+}Na$ OH

Substrates with low concentrations of non-hydrogen bonded hydroxyl groups, high concentrations of calcium, alkali metals or phosphates pose challenges for silane coupling agents.

Removing Surface Impurities

Eliminating non-bonding metal ions such as sodium, potassium and calcium from the surface of substrates can be critical for stable bonds. Substrate selection can be essential. Colloidal silicas derived from tetraethoxysilane or ammonia sols perform far better than those derived from sodium sols. Bulk glass tends to concentrate impurities on the surface during fabrication. Although sodium concentrations derived from bulk analysis may seem acceptable, the surface concentration is frequently orders of magnitude higher. Surface impurities may be reduced by immersion in 5% hydrochloric acid for 4 hours, followed by a deionized water rinse, and then immersion in deionized water overnight followed by drying.

Oxides with high isoelectric points can adsorb carbon dioxide, forming carbonates. These can usually be removed by a high temperature vacuum bake.

Increasing Hydroxyl Concentration

Hydroxyl functionalization of bulk silica and glass may be increased by immersion in a 1:1 mixture of 50% aqueous sulfuric acid : 30% hydrogen peroxide for 30 minutes followed by rinses in D.I. water and methanol and then air drying. Alternately, if sodium ion contamination is not critical, boiling with 5% aqueous sodium peroxodisulfate followed by acetone rinse is recommended¹.

1. K. Shirai et al, J. Biomed. Mater. Res. 53, 204, 2000.

Catalyzing Reactions in Water-Free Environments

Hydroxyl groups without hydrogen bonding react slowly with methoxy silanes at room temperature. Ethoxy silanes are essentially non-reactive. The methods for enhancing reactivity include transesterification catalysts and agents which increase the acidity of hydroxyl groups on the substrate by hydrogen bonding. Transesterification catalysts include tin compounds such as dibutyldiacetoxytin and titanates such as titanium isopropoxide. Incorporation of transesterification catalysts at 2-3 weight % of the silane effectively promotes reaction and deposition in many instances. Alternatively, amines can be premixed with solvents at 0.01-0.5 weight % based on substrate prior or concurrent to silane addition. Volatile primary amines such as butylamine can be used, but are not as effective as tertiary amines such as benzyldimethylamine or diamines such as ethylenediamine. The more effective amines. however, are more difficult to remove after reaction¹.

1. S. Kanan et al, Langmuir, *18*, 6623, 2002.

Hydroxylation by Water Plasma & Steam Oxidation

Various metals and metal oxides including silicon and silicon dioxide can achieve high surface concentrations of hydroxyl groups after exposure to H_2O/O_2 in high energy environments including steam at 1050° and water plasma¹.

 N. Alcanter et al, in "Fundamental & Applied Aspects of Chemically Modified Surfaces" ed. J. Blitz et al, 1999, Roy. Soc. Chem., p212.

Applying Silanes

Deposition from aqueous alcohol solutions is the most facile method for preparing silylated surfaces. A 95% ethanol-5% water solution is adjusted to pH 4.5-5.5 with acetic acid. Silane is added with stirring to yield a 2% final concentration. Five minutes should be allowed for hydrolysis and silanol formation. Large objects, e.g. glass plates, are dipped into the solution, agitated

gently, and removed after 1-2 minutes. They are rinsed free of excess materials by dipping briefly in ethanol. Particles, e.g. fillers and supports, are silvated by stirring them in solution for 2-3 minutes and then decanting the solution. The particles are usually rinsed twice briefly with ethanol. Cure of the silane layer is for 5-10 mins at 110°C or 24 hours at room temperature (<60% relative humidity).

Deposition from aqueous solution is employed for most commercial fiberglass systems. The alkoxysilane is dissolved at 0.5-2.0% concentration in water. For less soluble silanes, 0.1% of a non-ionic surfactant is added prior to the silane and an emulsion rather than a solution is prepared. The solution is adjusted to pH 5.5 with acetic acid. The solution is either sprayed onto the substrate or employed as a dip bath. Cure is at 110-120°C for 20-30 minutes.

Stability of aqueous silane solutions varies from 2-12 hours for the simple alkyl silanes. Poor solubility parameters limit the use of long chain alkyl and aromatic silanes by this method. Distilled water is not necessary, but water containing fluoride ions must be avoided.

Bulk deposition onto powders, e.g. filler treatment, is usually accomplished by a spray-on method. It assumes that the total amount of silane necessary is known and that sufficient adsorbed moisture is present on the filler to cause hydrolysis of the silane. The silane is prepared as a 25% solution in alcohol. The powder is placed in a high intensity solid mixer, e.g. twin cone mixer with

Fig. 2 Vacuum tumble dryers can be used for slurry treatment of powders.

Fig. 1 Reactor for slurry treatment of powders.

drying steps are required.

Separate filtration and

intensifier. The methods are most effective. If the filler is dried in trays, care must be taken to avoid wicking or skinning of the top layer of treated material by adjusting heat and air flow.

Integral blend methods are used in composite formulations. In this method the silane is used as a simple additive. Composites can be prepared by the addition of alkoxysilanes to dry-blends of polymer and filler prior to compounding. Generally 0.2 to 1.0 weight percent of silane (of the total mix) is dispersed by spraying the silane in an alcohol carrier onto a preblend. The addition of the silane to non-dispersed filler is not desirable in this technique since it can lead to agglomeration. The mix is dry-blended briefly and then melt compounded. Vacuum devolatization of byproducts of silane reaction during melt compounding is necessary to achieve optimum properties. Properties are sometimes enhanced by adding 0.5-1.0% of tetrabutyl titanate or benzyldimethylamine to the silane prior to dispersal.

Anhydrous liquid phase deposition of chlorosilanes, methoxysilanes, aminosilanes and cyclic azasilanes is preferred for small particles and nano-featured substrates. Toluene, tetrahydrofuran or hydrocarbon solutions are prepared containing 5% silane. The mixture is refluxed for 12-24 hours with the substrate to be treated. It is washed with the solvent. The solvent is then removed by air or explosion-proof oven drying. No further cure is necessary. This reaction involves a direct nucleophilic displacement of the silane chlorines by the surface silanol. If monolayer deposition is desired, substrates should be predried at 150°C for 4 hours. Bulk deposition results if adsorbed water is present on the substrate. This method is cumbersome for large scale preparations and rigorous controls must be established to ensure reproducible results. More reproducible coverage is obtained with monochlorosilanes.

Chlorosilanes can also be deposited from alcohol solution. Anhydrous alcohols, particularly ethanol or isopropanol are preferred. The chlorosilane is added to the alcohol to yield a 2-5% solution. The chlorosilane reacts with the alcohol producing an alkoxysilane and HCl. Progress of the reaction is observed by halt of HCl evolution. Mild warming of the solution (30-40°C) promotes completion of the reaction. Part of the HCl reacts with the alcohol to produce small quantities of alkyl halide and water. The water causes formation of silanols from alkoxysilanes. The silanols condense on the substrate. Treated substrates are cured for 5-10 mins. at 110°C or allowed to stand 24 hours at room temperature.







Fig. 3 Twin-cone blenders with intensive mixing bars are used for bulk deposition of silanes onto powders.

►►► Gelest, Inc.

Applying Silanes

Vapor Phase Deposition

Silanes can be applied to substrates under dry aprotic conditions by chemical vapor deposition methods. These methods favor monolayer deposition. Although under proper conditions almost all silanes can be applied to substrates in the vapor phase, those with vapor pressures >5 torr at 100°C have achieved the greatest number of commercial applications. In closed chamber designs, substrates are supported above or adjacent to a silane reservoir and the reservoir is heated to sufficient temperature to achieve 5mm vapor pressure. Alternatively, vacuum can be applied until silane evaporation is observed. In still another variation the silane can be prepared as a solution in toluene, and the toluene brought to reflux allowing sufficient silane to enter the vapor phase through partial pressure contribution. In general, substrate temperature should be maintained above 50° and below 120° to promote reaction. Cyclic azasilanes deposit the quickestusually less than 5 minutes. Amine functional silanes usually deposit rapidly (within 30 minutes) without a catalyst. The reaction of other silanes requires extended reaction times, usually 4-24 hours. The reaction can be promoted by addition of catalytic amounts of amines.

Spin-On

Spin-On applications can be made under hydrolytic conditions which favor maximum functionalization and polylayer deposition or dry conditions which favor monolayer deposition. For hydrolytic deposition 2-5% solutions are prepared (see deposition from aqueous alcohol). Spin speed is low, typically 500 rpm. Following spin-deposition a hold period of 3-15 minutes is required before rinse solvent. Dry deposition employs solvent solutions such as methoxypropanol or ethyleneglycol monoacetate (EGMA). Aprotic systems utilize toluene or THF. Silane solutions are applied at low speed under a nitrogen purge. If strict monolayer deposition is preferred, the substrate should be heated to 50°. In some protocols, limited polylayer formation is induced by spinning under an atmospheric ambient with 55% relative humidity.

Spray application

Formulations for spray applications vary widely depending on end-use. They involve alcohol solutions and continuously hydrolyzed aqueous solutions employed in architectural and masonry applications. The continuous hydrolysis is effected by feeding mixtures of silane containing an acid catalyst such as acetic acid into a water stream by means of a venturi (aspirator). Stable aqueous solutions (see water-borne silanes), mixtures of silanes with limited stability (4-8 hours) and emulsions are utilized in textile and fiberglass applications. Complex mixtures with polyvinyl acetates or polyesters enter into the latter applications as sizing formulations.

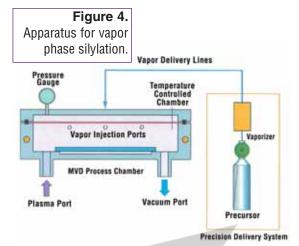


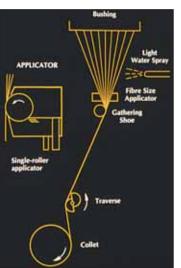
Figure 5. Spin-coater for deposition on wafers.



Figure 6. Spray application of silanes on large structures.



Figure 7. Spray & contact roller application of silanes on fiberglass.



Hydrophobic Silane Selection Guide

Hydrophobic silanes employed in surface moodification form the following major categories:

Methyl-Silanes	20
Linear Alkyl-Silanes	22
Branched Alkyl-Silanes	24
Aromatic-Silanes	26
Fluorinated Alkyl-Silanes	28
Dialkyl-Silanes	28

Methyl-Silanes very hydrophobic, hydrolysates stable to 425°C, acceptable performance to 600°C reported, volatile

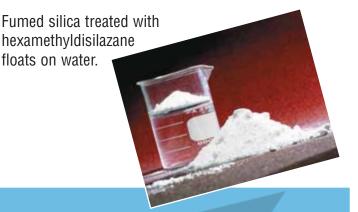
Hydrolyzeable Groups	Product Code	Product Name
chloro	SIM6520.0	methyltrichlorosilane
methoxy	SIM6560.0	methyltrimethoxysilane
ethoxy	SIM6555.0	methyltriethoxysilane
propoxy	SIM6579.0	methyltri-n-propoxysilane
methoxyalkoxy	SIM6585.0	methyltris(methoxyethoxy)silane
acetoxy	SIM6519.0	methyltriacetoxysilane
dimethylamine	SIT8712.0	tris(dimethylamino)methylsilane
other amine silazane (NH)	SIT8710.0	tris(cyclohexylamino)methylsilane
oxime	SIM6590.0	methyltris(methylethylketoximino)silane

3 Hydrolyzeable Groups

Methyl-SiloxanylSilanes

3 Hydrolyzeable Groups

	Hydrolyzeable Groups	Product Code	Product Name	
2 silicon aton	m compounds			
	chloro ethoxy acetoxy	SIT8572.6	trimethylsiloxytrichlorosilane	
3 silicon aton	m compounds		*	
	chloro methoxy ethoxy chloro	You		
oligomeric po	olysiloxanes	(11)		
	chloro methoxy ethoxy amine/silazane silanol selected specialties			
		SID4236.0	dimethyltetramethoxydisiloxane	



1 Hydrolyzeable Group

2 Hydrolyzeable Groups

Product Code	Product Name	Product Code	Product Name
SID4120.0 SID4123.0 SID4121.0	dimethyldichlorosilane dimethyldimethoxysilane dimethyldiethoxysilane	SIT8510.0 SIT8566.0 SIT8515.0 SIT8568.0 SIM6492.8	trimethylchlorosilane trimethylmethoxysilane trimethylethoxysilane trimethyl-n-propoxysilane methoxypropoxytrimethylsilane
SID4076.0 SIB1072.0 SIB1068.0 SIH6102.0	dimethyldiacetoxysilane bis(dimethylamino)dimethylsilane bis(diethylamino)dimethylsilane hexamethylcyclotrisilazane	SIA0110.0 SID3605.0 SID3398.0 SIH6110.0	acetoxytrimethylsilane dimethylaminotrimethylsilane diethylaminotrimethylsilane hexamethyldisilazane

2 Hydrolyzeable Groups

1 Hydrolyzeable Group **Product Code Product Code Product Name Product Name** SID3372.0 dichlorotetramethyldisiloxane SIT7534.0 tetramethyldiethoxydisiloxane SIP6717.0 pentamethylacetoxydisiloxane SID3360.0 dichlorohexamethyltrisiloxane SIB1843.0 bis(trimethylsiloxy)methylmethoxysilane SID3394.0 1,5-diethoxyhexamethyltrisiloxane SIB1837.0 bis(trimethylsiloxy)dichlorosilane Space Shuttle tiles are treated with DMS-K05 chlorine terminated polydimethylsiloxane dimethylethoxysilane to methoxy terminated polydimethylsiloxane DMS-XM11 reduce water absorption. ethoxy terminated polydimethylsiloxane DMS-XE11 dimethylamine terminated polydimethylsiloxane DMS-N05 DMS-S12 silanol terminated polydimethylsiloxane SID4125.0 dimethylethoxysilane SIT8719.5 [tris(trimethylsiloxy)silylethyl]dimethylchlorosilane

Hydrophobic Silane Selection Guide

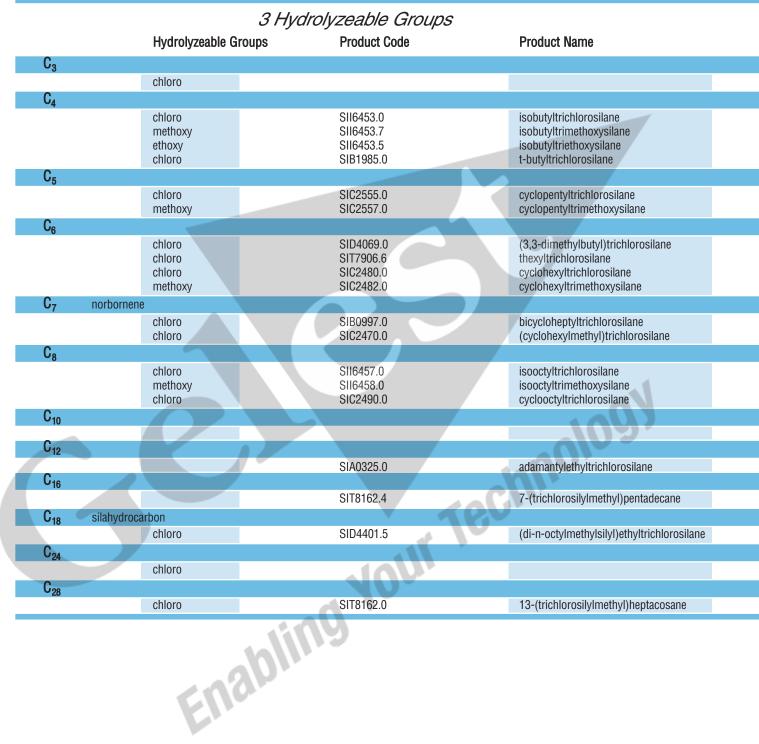
Linear Alkyl-Silanes

3 Hydrolyzeable Groups				
	Hydrolyzeable Groups	Product Code	Product Name	
C ₂	hydrophobic, treatment for microporous r	mineral powders used as fillers for plasti		
	chloro	SIE4901.0	ethyltrichlorosilane	
	methoxy	SIE4901.4	ethyltrimethoxysilane	
	ethoxy	SIE4901.2	ethyltriethoxysilane	
•	acetoxy	SIE4899.0	ethyltriacetoxysilane	
C ₃	hydrophobic, treatment for microporous r chloro	SIP6915.0		
	methoxy	SIP6915.0 SIP6918.0	propyltrichlorosilane propyltrimethoxysilane	
	ethoxy	SIP6917.0	propyltriethoxysilane	
	amine/silazane	3110917.0	propylitietrioxysilarie	
C ₄	moderate hydrophobicity, penetrates micr	oporous structures minimal organic co	mnatibility	
04	chloro	SIB1982.0	n-butyltrichlorosilane	
	methoxy	SIB1988.0	n-butyltrimethoxysilane	
	amine/silazane	CIDITOGOLO		
C ₅	moderate hydrophobicity with minimal or	nanic compatibility		
05	chloro	SIP6720.0	pentyltrichlorosilane	
	ethoxy	SIP6720.2	pentyltriethoxysilane	
C ₆	moderate hydrophobicity with moderate o			
-0	chloro	SIH6167.0	hexyltrichlorosilane	
	methoxy	SIH6168.5	hexyltrimethoxysilane	
	ethoxy	SIH6167.5	hexyltriethoxysilane	
C ₇	moderate hydrophobicity with moderate o	rganic compatibility		
'	chloro	SIH5846.0	heptyltrichlorosilane	
C ₈	hydrophobic with moderate organic comp	atibility - generally most economical		
Ŭ	chloro	SI06713.0	octyltrichlorosilane	
	methoxy	SI06715.5	octyltrimethoxysilane	
	ethoxy	SI06715.0	octyltriethoxysilane	
	amine			
	silazane (NH)			
C ₁₀	hydrophobic, concentrates on surface of r			
	chloro	SID2663.0	decyltrichlorosilane	
	ethoxy	SID2665.0	decyltriethoxysilane	
C ₁₁	hydrophobic, concentrates on surface of r			
	chloro	SIU9050.0	undecyltrichlorosilane	
C ₁₂	hydrophobic, concentrates on surface of r	microporous structures, forms SAMs		
	chloro	SID4630.0	dodecyltrichlorosilane	
	ethoxy	SID4632.0	dodecyltriethoxysilane	
C ₁₄	hydrophobic, concentrates on surface of r			
	chloro	SIT7093.0	tetradecyltrichlorosilane	
C ₁₆	forms hydrophobic and oleophilic coating	s, liquid a room temperature, forms SAN	Лs	
	chloro	SIH5920.0	hexadecyltrichlorosilane	
	methoxy	SIH5925.0	hexadecyltrimethoxysilane	
	ethoxy	SIH5922.0	hexadecyltriethoxysilane	
C ₁₈	forms hydrophobic and oleophilic coating			
	chloro	SI06640.0	octadecyltrichlorosilane	
	methoxy	SI06645.0	octadecyltrimethoxysilane	
	ethoxy	SI06642.0	octadecyltriethoxysilane	
	amine			
0	proprietary	SIS6952.0/PPI-GC18	Siliclad®/Glassclad® 18	
C ₂₀	forms hydrophobic and oleophilic coating			
0	chloro	SIE4661.0	eicosyltrichlorosilane	
C ₂₀₋₂₄	forms hydrophobic and oleophilic coating		da a a chuis bha a tha a tha a tha a th	
0	chloro	SID4621.0	docosyltrichlorosilane blend	
C ₂₆ -C ₃₄	forms hydrophobic and oleophilic coating			
	chloro	SIT8048.0	triacontyltrichlorosilane blend	

2 Hydrolyzea	able Groups	1 Hydrolyz	reable Group	
Product Code	Product Name	Product Code	Product Name	
SIE4896.0	ethylmethyldichlorosilane	SIE4892.0	ethyldimethylchlorosilane	
SIP6912.0 SIP6914.0	propylmethyldichlorosilane propylmethyldimethoxysilane	SIP6910.0 SIP6911.0	propyldimethylchlorosilane propyldimethylmethoxysilane	
		SID4591.0	dipropyltetramethyldisilazane	
		SIB1934.0	n-butyldimethylchlorosilane	
		SIB1937.0	n-butyldimethyl(dimethylamino)silane	Long chain alkylsilanes are processing additives for
				crosslinked polyethylene (XLPE) used in wire
				and cable.
SIH6165.6	hexylmethyldichlorosilane			
SIH5845.0	heptylmethyldichlorosilane			S. S. Maria
SI06712.0	octylmethyldichlorosilane	SI06711.0	octyldimethylchlorosilane	
SI06712.2	octylmethyldiethoxysilane	SI06711.1 SI06711.3	octyldimethylmethoxysilane	
		SID4404.0	dioctyltetramethyldisilazane	102
SID2662.0	decylmethyldichlorosilane	SID2660.0	decyldimethylchlorosilane	Surface conductivity of
				glass substrates is reduced by application of hydropho
			16 0.	bic coatings. Surface arc-tracking is eliminated
SID4628.0 SID4629.0	dodecylmethyldichlorosilane dodecylmethyldiethoxysilane	SID4627.0	dodecyldimethylchlorosilane	on fluorescent light bulbs.
			0 ^V	Control
		119		Glass
SI06625.0	octadecylmethyldichlorosilane	SI06615.0	octadecyldimethylchlorosilane	Glassona
SI06629.0 SI06627.0	octadecylmethyldimethoxysilane octadecylmethyldiethoxysilane	SIO6618.0	octadecyldimethylmethoxysilane	
0100027.0	oolaaooyimetnyialemoxysiialle	SI06617.0	octadecyldimethyl(dimethylamino)silane	
SID4620.0	docosylmethyldichlorosilane blend			
		SIT8045.0	triacontyldimethylchlorosilane blend	

Hydrophobic Silane Selection Guide

Branched and Cyclic Alkyl-Silanes



	eable Groups		zeable Group	lsobutyltriethoxysilane solutions in ethanol
Product Code	Product Name	Product Code	Product Name	are applied by spray
SII6463.0	isopropylmethyldichlorosilane	SII6462.0	isopropyldimethylchlorosilane	to protect architecture.
				THE -
SII6452.8	isobutylmethyldimethoxysilane	SII6452.5	isobutyldimethylchlorosilane	2
SIB1972.2	t-butylmethyldichlorosilane	SIB1935.0	t-butyldimethylchlorosilane	
			1-1	
		SID4065.0	(3,3-dimethylbutyl)dimethylchlorosilane	
SIC2468.0	cyclohexylmethyldichlorosilane	SIT7906.0 SIC2465.0	thexyldimethylchlorosilane cyclohexyldimethylchlorosilane	
SIC2469.0	cyclohexylmethyldimethoxysilane	3102403.0	cyclonexylumethylchlorosilane	
		SIB0994.0	bicycloheptyldimethylchlorosilane	
		0100004.0	bioyolonoptylaimothylomorobland	
		SII6456.6	isooctyldimethylchlorosilane	
				03
		SID4074.0	(dimethylchlorosilyl)methylpinane	19.
			A 460.	
		SID4401.0	(di-n-octylmethylsilyl)ethyldimethylchlorosilane	
		SIC2266.5	11-(chlorodimethylsilylmethyl)tricosane	
		SIC2266.0	13-(chlorodimethylsilylmethyl)heptacosane	
	Enab	S		
	A			
	CUA.			

Hydrophobic Silane Selection Guide

Phenyl- and Phenylalkyl-Silanes

3 Hydrolyzeable Groups

Hydrolyzeable GroupsProduct CodeProduct Namespacer atoms = 0chloroSIP6810.0phenyltrichlorosilanemethoxySIP6820.0phenyltrimethoxysilaneethoxySIP6821.0phenyltritethoxysilaneacetoxySIP6790.0phenyltritethoxysilaneoxime/amineSIP6826.5phenyltritethoxysilanespacer atoms = 1	3 Hydrolyzeable Groups				
chloro SIP6810.0 phenyltrichlorosilane methoxy SIP6822.0 phenyltrimethoxysilane ethoxy SIP6821.0 phenyltriethoxysilane acetoxy SIP6790.0 phenyltriethoxysilane acetoxy SIP6826.5 phenyltriethoxysilane spacer atoms = 1		Hydrolyzeable Gr	oups Product Code	Product Name	
methoxySIP6822.0phenyltrimethoxysilaneethoxySIP6821.0phenyltriethoxysilaneacetoxySIP6790.0phenyltriacetoxysilaneoxime/amineSIP6826.5phenyltris(methylethylketoximino)silanespacer atoms = 1	spacer atoms = 0				
ethoxySIP6821.0phenyltriethoxysilaneacetoxySIP6790.0phenyltriacetoxysilaneoxime/amineSIP6826.5phenyltris(methylethylketoximino)silanespacer atoms = 1chloroSIB0970.0benzyltrichlorosilaneethoxySIB0971.0benzyltrichlorosilaneothoroSIP6813.01-phenyl-1-trichlorosilylbutanespacer atoms = 2chloroSIP6722.0phenethyltrichlorosilanemethoxySIP6722.6phenethyltrichlorosilanespacer atoms = 3spacer atoms = 4chloroSIP6723.3phenoxypropyltrichlorosilanespacer atoms > 4chloroSIP6736.4phenoxyundecyltrichlorosilanespacer atoms > 4chloroSIP6736.4phenoxyundecyltrichlorosilanespacer atoms > 4chloroSIP6736.4phenoxyundecyltrichlorosilanechloroSIP6736.4phenylhexyltrichlorosilanechloroSIP6736.4phenoxyundecyltrichlorosilanespacer atoms > 4chloroSIP6736.4phenoxyundecyltrichlorosilanechloroSIP6736.4phenylhexyltrichlorosilanechloroSIP6736.4phenylhexyltrichlorosilanechloroSIP6736.4phenylhexyltrichlorosilanechloroSIP6736.4phenylhexyltrichlorosilane		chloro	SIP6810.0	phenyltrichlorosilane	
acetoxy SIP6790.0 phenyltriacetoxysilane oxime/amine SIP6826.5 phenyltriacetoxysilane spacer atoms = 1 chloro SIB0970.0 benzyltrichlorosilane ethoxy SIB0971.0 benzyltrichlorosilane ethoro SIP6813.0 1-phenyl-1-trichlorosilylbutane spacer atoms = 2 chloro SIP6722.0 phenethyltrichlorosilane spacer atoms = 3 chloro SIP6722.6 phenethyltrinethoxysilane spacer atoms = 3 chloro SIP6722.6 phenethyltrinethoxysilane spacer atoms = 4 chloro SIP6723.3 phenoxypropyltrichlorosilane spacer atoms = 4 chloro SIP6723.3 phenoxypropyltrichlorosilane spacer atoms > 4 chloro SIP6723.4 phenoxypropyltrichlorosilane		methoxy	SIP6822.0	phenyltrimethoxysilane	
oxime/amineSIP6826.5phenyltris(methylethylketoximino)silanespacer atoms = 1chloroSIB0970.0benzyltrichlorosilaneethoxySIB0971.0benzyltriethoxysilanechloroSIP6813.01-phenyl-1-trichlorosilylbutanespacer atoms = 2chloroSIP6722.0chloroSIP6722.6phenethyltrichlorosilanephenethyltrichlorosilanephenethyltrichlorosilanespacer atoms = 3		ethoxy	SIP6821.0	phenyltriethoxysilane	
spacer atoms = 1 chloro SIB0970.0 benzyltrichlorosilane ethoxy SIB0971.0 benzyltriethoxysilane chloro SIP6813.0 1-phenyl-1-trichlorosilylbutane spacer atoms = 2 chloro SIP6722.0 phenethyltrichlorosilane methoxy SIP6722.6 phenethyltrimethoxysilane spacer atoms = 3 chloro SIP6722.6 chloro SIP6722.6 phenethyltrimethoxysilane spacer atoms = 3 chloro SIP6723.3 chloro SIP6723.3 phenotyputrichlorosilane spacer atoms = 4 chloro SIP6723.3 chloro SIP6723.4 phenoxypropyltrichlorosilane spacer atoms > 4 chloro SIP6723.4		acetoxy	SIP6790.0	phenyltriacetoxysilane	
chloro SIB0970.0 benzyltrichlorosilane ethoxy SIB0971.0 benzyltriethoxysilane chloro SIP6813.0 1-phenyl-1-trichlorosilylbutane spacer atoms = 2 chloro SIP6722.0 phenethyltrichlorosilane methoxy SIP6722.6 phenethyltrichlorosilane methoxy SIP6722.6 phenethyltrimethoxysilane spacer atoms = 3		oxime/amine	SIP6826.5	phenyltris(methylethylketoximino)silane	
ethoxy chloroSIB0971.0 SIP6813.0benzyltriethoxysilane 1-phenyl-1-trichlorosilylbutanespacer atoms = 2chloroSIP6722.0 sIP6722.6 amine/silazanephenethyltrichlorosilane phenethyltrimethoxysilanespacer atoms = 3chloroSIP6724.9 SIP6723.34-phenylbutyltrichlorosilane phenoxypropyltrichlorosilanespacer atoms = 4chloroSIP6723.3phenoxypropyltrichlorosilane phenoxypropyltrichlorosilanespacer atoms > 4chloroSIP6723.4phenoxyundecyltrichlorosilane phenylbutyltrichlorosilane	spacer atoms = 1				
chloro SIP6813.0 1-phenyl-1-trichlorosilylbutane spacer atoms = 2 chloro SIP6722.0 phenethyltrichlorosilane methoxy SIP6722.6 phenethyltrimethoxysilane spacer atoms = 3 chloro spacer atoms = 4 chloro SIP6724.9 4-phenylbutyltrichlorosilane spacer atoms = 4 spacer atoms = 4 chloro SIP6723.3 phenoxypropyltrichlorosilane spacer atoms > 4 spacer atoms = 4 chloro SIP6736.4 phenoxypropyltrichlorosilane spacer atoms > 4 siP6736.4 phenoxypropyltrichlorosilane		chloro	SIB0970.0	benzyltrichlorosilane	
spacer atoms = 2 chloro SIP6722.0 phenethyltrichlorosilane methoxy SIP6722.6 phenethyltrimethoxysilane spacer atoms = 3 chloro chloro SIP6724.9 chloro SIP6723.3 spacer atoms > 4 chloro chloro SIP6723.3 spacer atoms > 4 chloro chloro SIP6723.4		ethoxy	SIB0971.0	benzyltriethoxysilane	
chloro SIP6722.0 phenethyltrichlorosilane methoxy SIP6722.6 phenethyltrimethoxysilane spacer atoms = 3 chloro spacer atoms = 4 chloro SIP6724.9 4-phenylbutyltrichlorosilane spacer atoms = 4 chloro SIP6723.3 chloro SIP6723.3 phenoxypropyltrichlorosilane spacer atoms > 4 chloro SIP6736.4 chloro SIP6723.4 phenoxyundecyltrichlorosilane		chloro	SIP6813.0	1-phenyl-1-trichlorosilylbutane	
methoxy amine/silazane SIP6722.6 phenethyltrimethoxysilane spacer atoms = 3 chloro spacer atoms = 4 chloro chloro SIP6724.9 chloro SIP6723.3 spacer atoms > 4 chloro SIP6736.4 chloro SIP6723.4	spacer atoms = 2				
amine/silazane amine/silazane spacer atoms = 3 chloro spacer atoms = 4 chloro chloro SIP6724.9 chloro SIP6723.3 spacer atoms > 4 chloro chloro SIP6736.4 chloro SIP6723.4					
spacer atoms = 3 chloro spacer atoms = 4 chloro chloro SIP6724.9 chloro SIP6723.3 phenoxypropyltrichlorosilane spacer atoms > 4 chloro SIP6736.4 chloro SIP6723.4		2	SIP6722.6	phenethyltrimethoxysilane	
chloro SIP6724.9 4-phenylbutyltrichlorosilane chloro SIP6723.3 phenoxypropyltrichlorosilane spacer atoms > 4 chloro SIP6736.4 phenoxyundecyltrichlorosilane chloro SIP6723.4 phenoxyundecyltrichlorosilane		amine/silazane			
spacer atoms = 4 chloro SIP6724.9 4-phenylbutyltrichlorosilane chloro SIP6723.3 phenoxypropyltrichlorosilane spacer atoms > 4 chloro SIP6736.4 phenoxyundecyltrichlorosilane chloro SIP6723.3 phenoxyundecyltrichlorosilane spacer atoms > 4 spacer atoms > 4 spacer atoms > 4	spacer atoms = 3				
chloro SIP6724.9 4-phenylbutyltrichlorosilane chloro SIP6723.3 phenoxypropyltrichlorosilane spacer atoms > 4 chloro SIP6736.4 phenoxyundecyltrichlorosilane chloro SIP6723.4 phenoxyundecyltrichlorosilane		chloro			
chloro SIP6723.3 phenoxypropyltrichlorosilane spacer atoms > 4 chloro SIP6736.4 phenoxyundecyltrichlorosilane chloro SIP6723.4 phenoxyundecyltrichlorosilane	spacer atoms = 4				
spacer atoms > 4 SIP6736.4 phenoxyundecyltrichlorosilane chloro SIP6723.4 phenylhexyltrichlorosilane					
chloro SIP6736.4 phenoxyundecyltrichlorosilane chloro SIP6723.4 phenylhexyltrichlorosilane		chloro	SIP6723.3	phenoxypropyltrichlorosilane	
chloro SIP6723.4 phenylhexyltrichlorosilane	spacer atoms > 4		0100700 (
Substituted Deenvil and Deenviellard Silence		chioro	SIP6723.4	pnenyinexyitrichiorosilane	
Substituted Phenyl- and Phenylalkyl-Silanes	Substituted Ph	nenyl- and P	henylalkyl-Silanes		
spacer atoms = 0	spacer atoms = 0				
chloro SIT8040.0 p-tolyltrichlorosilane		chloro	SIT8040.0	p-tolyltrichlorosilane	
methoxy SIT8042.0 p-tolyltrimethoxysilane		methoxy	SIT8042.0	p-tolyltrimethoxysilane	
spacer atoms = 2	spacer atoms = 2		V KO		
methyl/chloro		methyl/chloro			
ethyl/methoxy SIE4897.5 ethylphenethyltrimethoxysilane		ethyl/methoxy	SIE4897.5	ethylphenethyltrimethoxysilane	
t-butyl/chloro SIB1973.0 p-(t-butyl)phenethyltrichlorosilane		t-butyl/chloro	SIB1973.0	p-(t-butyl)phenethyltrichlorosilane	

Napinyi-Silan	85		
	methoxy chloro	SIN6597.0 SIN6596.0	1-napthyltrimethoxysilane (1-napthylmethyl)trichlorosilane
Specialty Aro	matic- Silane	s	
spacer atoms = 0			
	chloro		
spacer atoms = 4			
	chloro		

SIM6492.5

3-(p-methoxyphenyl)propyltrichlorosilane

spacer atoms = 3

Nanthyl-Silanes

chloro

2 Ludra	luzoabla Graupa	1 Ludrolut	aabla Graup
Product Code	<i>lyzeable Groups</i> Product Name	Product Code	<i>eable Group</i> Product Name
SIP6738.0	phenylmethyldichlorosilane	SIP6728.0	phenyldimethylchlorosilane
SIP6740.0 SIP6739.0	phenylmethyldimethoxysilane phenylmethyldiethoxysilane	SIP6728.4	phenyldimethylethoxysilane
SIP6736.8	phenylmethylbis(dimethylamino)silane		
		SIB0962.0	benzyldimethylchlorosilane
SIP6738.5	1-phenyl-1-methyldichlorosilylbutane		
SIP6721.5	phenethylmethyldichlorosilane	SP6721.0	phenethyldimethylchlorosilane
		SIP6721.2	phenethyldimethyl(dimethylamino)silane
SIP6744.0	(3-phenylpropyl)methyldichlorosilane	SIP6743.0	(3-phenylpropyl)dimethylchlorosilane
SIP6724.8	4-phenylbutylmethyldichlorosilane	SIP6724.7	4-phenylbutyldimethylchlorosilane
SIP6723.25	phenoxypropylmethyldichlorosilane	SIP6723.2	phenoxypropyldimethylchlorosilane
			109'
SIT8035.0	p-tolylmethydichlorosilane	SIT8030.0	p-tolyldimethylchlorosilane
			p tolylandon ylandoronano
SIM6511.0	(p-methylphenethyl)methyldichlorosilane		
0100011.0	(p menypreneuty)menymenorsmane	SIB1972.5	p-(t-butyl)phenethyldimethylchlorosilane
	0 (a makkay mkan J)awan Jnasthi Jaliah awa ilana	NU	
SIM6492.4	3-(p-methoxyphenyl)propylmethyldichlorosilane		
	2011		
	Enar		
		SIP6723.0	m-phenoxyphenyldimethylchlorosilane
		SIN6598.0	p-nonylphenoxypropyldimethylchlorosilane

Hydrophobic Silane Selection Guide

Fluorinated Alkyl-Silanes 3 Hydrolyzeable Groups **Product Code** Hydrolyzeable Groups **Product Name** C_3 chloro SIT8371.0 (3,3,3-trifluoropropyl)trichlorosilane methoxy SIT8372.0 (3,3,3-trifluoropropyl)trimethoxysilane amine/silazane C_6 chloro SIN6597.6 nonafluorohexyltrichlorosilane SIN6597.7 nonafluorohexyltrimethoxysilane methoxy SIN6597.65 nonafluorohexyltriethoxysilane ethoxy amino SIN6597.4 nonafluorohexyltris(dimethylamino)silane C_8 chloro SIT8174.0 (tridecafluoro-1,1,2,2-tetrahydrooctyl)trichlorosilane SIT8176.0 (tridecafluoro-1,1,2,2-tetrahydrooctyl)trimethoxysilane methoxy SIT8175.0 (tridecafluoro-1,1,2,2-tetrahydrooctyl)triethoxysilane ethoxy C₁₀ (heptadecafluoro-1,1,2,2-tetrahydrodecyl)trichlorosilane chloro SIH5841.0 (heptadecafluoro-1,1,2,2-tetrahydrodecyl)trimethoxysilane methoxy SIH5841.5 (heptadecafluoro-1,1,2,2-tetrahydrodecyl)triethoxysilane SIH5841.2 ethoxy

DiAlkyl Silanes

2 Hydrolyzeable Groups

4

Highest Carbon #	Next Carbon #	Hydrolyzeable Groups	Product Code	Product Name
C ₂	C ₂			1047
		chloro ethoxy	SID3402.0 SID3404.0	diethyldichlorosilane diethyldiethoxysilane
C ₃	C ₃			
		chloro methoxy	SID3537.0 SID3538,0	diisopropyldichlorosilane diisopropyldimethoxysilane
C ₄	C ₄			
		chloro methoxy methoxy ethoxy	SID3203.0 SID3214.0 SID3530.0 SID3528.0	di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane diisobutyldiethoxysilane
C ₄	C ₃			
		methoxy	SII6452.6	isobutylisopropyldimethoxysilane
C ₅	С ₅			
		chloro methoxy	SID3390.0 SID3391.0	dicyclopentyldichlorosilane dicyclopentyldimethoxysilane
C ₆	C ₆			
		chloro chloro	SID3510.0 SID3382.0	di-n-hexyldichlorosilane dicyclohexyldichlorosilane
C ₈	C ₈			
		chloro	SID4400.0	di-n-octyldichlorosilane

<i>2 Hydrolyzeable Groups</i> Product Code Product Name		<i>1 Hydrolyzea</i> Product Code	<i>able Group</i> Product Name
SIT8369.0 SIT8370.0	(3,3,3-trifluoropropyl)methyldichlorosilane (3,3,3-trifluoropropyl)methyldimethoxysilane	SIT8364.0	(3,3,3-trifluoropropyl)dimethylchlorosilane
0.10010.0		SIB1828.4	bis(trifluoropropyl)tetramethyldisilazane
SIN6597.5	nonafluorohexylmethyldichlorosilane	SIN6597.3	nonafluorohexyldimethylchlorosilane
SIT8172.0	(tridecafluoro-1,1,2,2-tetrahydrooctyl)methyldichlorosilane	SIT8170.0	(tridecafluoro-1,1,2,2-tetrahydrooctyl)dimethylchlorosilane
SH5840.6	(heptadecafluoro-1,1,2,2-tetrahydrodecyl)methyldichlorosilane	SIH5840.4	(heptadecafluoro-1,1,2,2-tetrahydrodecyl)dimethylchlorosilane



Pigments *treated with hydrophobic silanes resist agglomeration in highly polar vehicle and film-forming compositions such as those used in nail polish.*

Hydrophobic Silane Properties

Conventional Surface Bonding

	name	MW	bp/mm (mp)	D 4 ²⁰	n _20
$CH_{3}COS_{1}-CH_{3}$ $CH_{3}COS_{1}-CH_{3}$ CH_{3}	SIA0110.0 ACETOXYTRIMETHYLSILANE <i>O-TRIMETHYLSILYLACETATE</i> C ₅ H ₁₂ O ₂ Si vapor pressure, 30°: 35mm HYDROLYTIC SENSITIVITY: 4 no reaction under neutral co [2754-27-0] TSCA HMIS: 3-4-1-X	132.23 flashpoint: onditions 25g/\$11.00	X /	0.891 100g/\$3	1.3890
City		259/\$11.00)	100g/\$3	4.00
CH ₂ CH ₂ SiCl ₃	SIA0325.0 ADAMANTYLETHYLTRICHLOROSILANE $C_{12}H_{19}CI_3Si$ contains up to 5% α -isomer forms silica bonded phases for reverse phase 1. Yang et al, Anal. Chem., <i>59</i> , 2750, 1988		135°/3 (36-7°)mp 155°C (310°F) aphy'.	1.2204	1.5135
	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [37843-11-1] TSCA HMIS: 3-1-1-X	, water, protic s 5.0g/\$73.00		25g/\$29	2.00
CH ₂ Si -Cl CH ₂ Si -Cl CH ₃	SIB0962.0 BENZYLDIMETHYLCHLOROSILANE C ₉ H ₁₃ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [1833-31-4] TSCA HMIS: 3-2-1-X			0.949 50g/\$172	1.5040 2.00
CH ₂ Si -Cl Cl	SIB0970.0 BENZYLTRICHLOROSILANE C ₇ H ₇ Cl ₃ Si dipole moment: 1.78 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [770-10-5] TSCA HMIS: 3-2-1-X	flashpoint:			-
CH ₂ Si -OC ₂ H ₅ OC ₂ H ₅ OC ₂ H ₅	SIB0971.0 BENZYLTRIETHOXYSILANE C ₁₃ H ₂₂ O ₃ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [2549-99-7] TSCA HMIS: 2-1-0-X	254.40 flashpoint:	148°/26 127°C (260°F)	0.986 50g/\$15	1.4628 ²⁵
Si(CH ₃) ₂ Cl	SIB0994.0 2-(BICYCLOHEPTYL)DIMETHYLCHLOROSILANE C ₉ H ₁₇ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [117046-42-1 HMIS: 3-2-1-X	188.77 flashpoint: , water, protic s 25g/\$68.00		0.99 100g/\$2	20.00
SiCl ₃	SIB0997.0 2-(BICYCLOHEPTYL)TRICHLOROSILANE C ₇ H ₁₁ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18245-29-9] TSCA HMIS: 3-2-1-X	229.61 flashpoint: , water, protic s 10g/\$31.00	63-4°/4.5 83°C (181°F) solvents	1.2678 50g/\$124	
$(C_2H_5)_2N$, CH_3 $(C_2H_5)_2N$, CH_3	SIB1068.0 BIS(DIETHYLAMINO)DIMETHYLSILANE C ₁₀ H ₂₆ N ₂ Si silylates diamines to cyclic diaminosilanes ¹ . 1. E. Schwartz et al, J. Org. Chem., <i>50</i> , 5469, ⁻¹ HYDROLYTIC SENSITIVITY: 8 Si-NR reacts rapidly with moistur [4669-59-4] TSCA HMIS: 3-3-1-X	1985.	192-5° 35°C (95°F) solvents 50g/\$127.00	0.826	1.435
$(CH_3)_2N$ CH_3	SIB1072.0 BIS(DIMETHYLAMINO)DIMETHYLSILANE $C_6H_{18}N_2Si$	146.31 flashpoint:	128-9° (-98°)mp -3°C (27°F)	0.810	1.416922
(CH ₃) ₂ N ^{CH} ₃	couples silanol-terminated siloxanes HYDROLYTIC SENSITIVITY: 8 Si-NR reacts rapidly with me [3768-58-9] TSCA HMIS: 3-4-1-X	-	protic solvents	100g/\$7	5.00
$\begin{array}{ccc} CH_3 & CH_3\\ CF_3CH_2CH_2\cdotSi & & N \\ & & Si - CH_2CH_2CH_2CF_3\\ & & CH_3 & H & CH_3 \end{array}$	SIB1828.4 BIS(TRIFLUOROPROPYL)TETRAMETHYL- DISILAZANE, 95% C ₁₀ H ₂₁ F ₆ NSi ₂ fluorinated blocking agent HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo [39482-87-6] TSCA HMIS: 2-2-1-X	-	76-8°/10 78°C (173°F) 50g/\$148.00	1.110	1.3860
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HYDROPHOBIC

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰	
$\begin{array}{c} CH_3 & CI & CH_3 \\ I & I & I \\ CH_3 - Si & O - Si & O - Si \\ CH_3 & CI & CH_3 \\ CH_3 & CI & CH_3 \end{array}$	SIB1837.0 BIS(TRIMETHYLSILOXY)DICHLOROSILANE <i>3,3-DICHLOROHEXAMETHYLTRISILOXANE</i> C ₆ H ₁₈ CI ₂ O ₂ Si ₃ [2750-44-9] HMIS: 3-2-1-X	277.37 vapor pres	173° (-53°)mp sure, 57°: 12mm 25g/\$96.00		1.3983	
$\begin{array}{c} CH_3\\ H_3C-S_i-CH_3\\ O\\ H_3C-S_i-OCH_3\\ O\\ H_3C-S_i-CH_3\end{array}$	SIB1843.0 BIS(TRIMETHYLSILOXY)METHYMETHOXY SILANE <i>METHOXYHEPTAMETHYLTRISILOXANE</i> $C_8H_{24}O_3Si_3$ [7671-19-4] HMIS: 3-2-1-X	252.53	82°/47 25g/\$68.00	0.862	1.3883225	
$OSi(CH_3)_3$ $CH_3C=NSi(CH_3)_3$	SIB1846.0 N,O-BIS(TRIMETHYLSILYL)ACETAMIDE C ₈ H ₂₁ NOSi ₂ <i>BSA</i> versatile blocking agent. HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [10416-59-8] TSCA HMIS: 3-3-1-X	TOXICITY /ater/moisture	71-3°/35 (-24°)mp 42°C (108°F) - oral rat, LD50: 100g/\$52.00		-	COMMERCIAL
$OSi(CH_3)_3$ $CF_3C = NSi(CH_3)_3$	SIB1876.0 BIS(TRIMETHYLSILYL)TRIFLUOROACETAMIDE <i>BSTFA</i> C ₈ H ₁₈ F ₃ NOSi ₂ silylation reagent for preparing derivatives of a 1. D. Stalling et al, Biochem. Biophys., Res. Co HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [25561-30-2] TSCA HMIS: 3-3-1-X	amino acids omm., <i>31</i> , 6 e, water, protic	16, 1968.	0.969 2kg/\$13	1.3840 60.00	ERCIAL
CH ₃ CH ₂ CH ₂ CH ₂ CH ₂ S _i -Cl CH ₃	SIB1934.0 n-BUTYLDIMETHYLCHLOROSILANE C ₆ H ₁₅ CISi forms bonded phases for HPLC HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [1000-50-6] TSCA HMIS: 3 -3-1-X			0.8751 100g/\$1		
$\begin{array}{c} CH_3 & Me \\ \searrow & -C - Si - Cl \\ H_3C - C - Si - Cl \\ CH_3 & Me \end{array}$	SIB1935.0 t-BUTYLDIMETHYLCHLOROSILANE C ₆ H ₁₅ CISi vapor pressure, 100°: 476mm silylation reagent - derivatives resistant to Grig blocking agent widely used in prostaglandin s HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18162-48-6] TSCA HMIS: 3-4-1-X	gnards, alky ynthesis e, water, protic		0.83 nds etc. 2kg/\$72	0.00	COMMERCIAL
$CH_{3}CH_{2}CH_{2}CH_{2}CH_{2}S_{1} - N(CH_{3})_{2}$ CH_{3}	SIB1937.0 n-BUTYLDIMETHYL(DIMETHYLAMINO)SILANE C ₈ H ₂₁ NSi highly reactive reagent for bonded phases wit HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/m [181231-67-4] TSCA-L HMIS: 3-3-1-X	flashpoint: hout acidic l		0.772 50g/\$15	1.4220 2.00	-
$\begin{array}{c} CH_3 OCH_3 CH_3 \\ H_3C - C - Si - CH \\ CH_3 OCH_3 CH_3 \end{array}$	SIB1971.0 t-BUTYLISOPROPYLDIMETHOXYSILANE $C_9H_{22}O_2Si$ HMIS: 3-2-1-X	190.36	75°/20 1.0g/\$126.00	0.871	1.4189	
CH ₃ CH ₂ CH ₂ CH ₂ CH ₂ CH ₂ CI H ₃ CCI	SIB1972.0 n-BUTYLMETHYLDICHLOROSILANE C ₅ H ₁₂ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture [18147-23-4] TSCA HMIS: 3-3-1-X		148° 30°C (86°F) 10g/\$35.00	1.0424	1.4312	-
$\begin{array}{ccc} CH_3 & CH_3 \\ \swarrow & & 1\\ H_3C - C - Si - Cl \\ CH_3 & Cl \end{array}$	SIB1972.2 t-BUTYLMETHYLDICHLOROSILANE C ₅ H ₁₂ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moistur [18147-18-7] HMIS: 3-3-1-X		130-2° (88-90°)mp 26°C (79°F) 5.0g/\$89.00			

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	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
$\begin{array}{c} CH_3 \\ H_3C -C \\ CH_3 \end{array} \xrightarrow{CH_2 - CH_2 - SiCl} \\ CH_3 \\ CH_3 \end{array}$	SIB1972.5 p-(t-BUTYL)PHENETHYLDIMETHYLCHLORO- SILANE contains ~5% meta isomer C ₁₄ H ₂₃ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture. [93502-75-1] HMIS: 3-2-1-X	254.87	122-3°/2 25g/\$78.00	0.95	
			259/\$78.00		
$H_3C \xrightarrow{CH_3} CH_2 - CH_2 - SiCl_3$	SIB1973.0 p-(t-BUTYL)PHENETHYLTRICHLOROSILANE C ₁₂ H ₁₇ Cl ₃ Si mixed isomers for HPLC bonded phase HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture.	-	124-9°/2.5 108°C (226°F)	1.16	
5	HMIS: 3-2-1-X		25g/\$78.00		
CH ₃ CH ₂ CH ₂ CH ₂ SiCl ₃	SIB1982.0 n-BUTYLTRICHLOROSILANE C ₄ H ₉ Cl ₃ Si		142-3° 45°C (114°F) sure, 31°: 10mm	1.1608	1.4364
	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture. [7521-80-4] TSCA HMIS: 3-3-1-X	protic solvents 25g/\$37.00		100g/\$1	21.00
$\begin{array}{ccc} CH_3 & Cl \\ \searrow & I \\ H_3C - C - Si - Cl \\ \swarrow & I \\ CH_3 & Cl \end{array}$	SIB1985.0 t-BUTYLTRICHLOROSILANE C ₄ H ₉ Cl ₃ Si forms silanetriol HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture.	191.56 flashpoint:	142-3° (97-100°)mp 40°C (105°F)	1.1608	1.436
	[18171-74-9] TSCA HMIS: 3-3-1-X	10g/\$41.00		50g/\$16	4.00
CH ₃ CH ₂ CH ₂ CH ₂ Si(OCH ₃) ₃	SIB1988.0 n-BUTYLTRIMETHOXYSILANE C ₇ H ₁₈ O ₃ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa		164-5° 49°C (120°F)	0.9312	1.3979
	[1067-57-8] TSCA HMIS: 3-2-1-X	25g/\$42.00		100g/\$1	36.00
$\begin{array}{c} CH_3 OCH_3 \\ H_3C - C - Si - OCH_3 \\ \end{array}$	SIB1989.0 t-BUTYLTRIMETHOXYSILANE C7H18O3Si HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with wa	178.30	140-1°	0.903	1.3941
CH ₃ OCH ₃	[18395-29-4] HMIS: 3-2-1-X		10g/\$143.00		
	SIC2266.0 13-(CHLORODIMETHYLSILYLMETHYL)- HEPTACOSANE, 95% $C_{30}H_{63}CISi$	487.37	200-210°/0.01	0.84825	1.454230
	forms hydrophobic bonded phases HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moist [194243-00-0] TSCA-L HMIS: 3-1-1-X	ure, protic solve	^{nts} 10g/\$117.00		
H ₃ C-Si-CH ₃	SIC2266.5 11-(CHLORODIMETHYLSILYLMETHYL)- TRICOSANE C ₂₆ H ₅₅ ClSi forms self-assembled oleophilic monolayers	431.27	170°/0.075		1.4575 ²²
, H ₄ C —Şi –CH ₃	employed as bonded phase in HPLC HMIS: 3-1-1-X		10g/\$101.00		
	SIC2465.0				
H ₃ C ^{Si} CH ₃	CYCLOHEXYLDIMETHYLCHLOROSILANE C ₈ H ₁₇ CISi silane blocking agent with good resistance to C HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture	Grignard rea		0.956	1.4626
×	[71864-47-6] HMIS:: 3-2-1-X	25g/\$36.00		100g/\$1	17.00
	SIC2468.0 CYCLOHEXYLMETHYLDICHLOROSILANE C ₇ H ₁₄ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture		83°/15 66°C (151°F) solvents	1.095	1.4724
н₃С́СІ 8	[5578-42-7] TSCA HMIS: 3-2-1-X	25g/\$25.00		2 kg/\$4	02.00

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	name	MW	bp/mm (mp)	D4 ²⁰ n ²⁰	
H ₃ C ^{Si} OCH ₃	SIC2469.0 CYCLOHEXYLMETHYLDIMETHOXYSILANE C ₉ H ₂₀ O ₂ Si vapor pressure, 20°: 12mm donor for polyolefin polymerization HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [17865-32-6] TSCA HMIS: 2-3-1-X	flashpoint:	196° oral rat, LD50: 3(66°C (151°F) 100g/\$37.00	0.9472 1.4354 000mg/kg 2kg/\$496.00	HYL
CH ₂ , SiCl ₃	SIC2470.0 (CYCLOHEXYLMETHYL)TRICHLOROSILANE C ₇ H ₁₃ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18388-16-4] TSCA HMIS: 3-2-1-X	231.62 e, water, protic s	94-8°/11 solvents 10g/\$93.00		HYDROPHOBIC
	SIC2480.0 CYCLOHEXYLTRICHLOROSILANE C ₆ H ₁₁ Cl ₃ Si intermediate for melt-processable silsesquioxa employed in solid-phase extraction columns ² . 1. J. Lichtenhan et al, Macromolecules, <i>26</i> , 21- 2. B. Tippins, Nature, <i>334</i> , 273, 1988. HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [98-12-4] TSCA HMIS: 3-2-1-X	ne-siloxane 41, 1993.	solvents	1.222 1.4774 100g/\$110.00	-
CH ₃ OCH ₃	SIC2482.0 CYCLOHEXYLTRIMETHOXYSILANE C ₉ H ₂₀ O ₃ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [17865-54-2] HMIS: 2-3-1-X	204.34 ater/moisture 10g/\$31.00	207-9°	50g/\$124.00	_
SiCl ₃	SIC2490.0 CYCLOOCTYLTRICHLOROSILANE, 95% C ₈ H ₁₅ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture HMIS: 3-2-1-X	245.65 a, water, protic s 10g/\$37.00		1.19 50g/\$148.00	_
SiCl ₃	SIC2555.0 CYCLOPENTYLTRICHLOROSILANE C ₅ H ₉ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [14579-03-4] HMIS: 3-2-1-X			1.2255 1.4713 100g/\$146.00	_
Si(OCH ₃) ₃	SIC2557.0 CYCLOPENTYLTRIMETHOXYSILANE C ₈ H ₁₈ O ₃ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [143487-47-2] HMIS: 3-3-1-X		75°/10 54°C (130°F)	0.990 ²⁵ 1.4240 ²⁵ 50g/\$136.00	_
$CH_{3}(CH_{2})_{9} \xrightarrow{CH_{3}}_{I} Cl$ $CH_{3}(CH_{2})_{9} \xrightarrow{CH_{3}}_{I} Cl$	SID2660.0 n-DECYLDIMETHYLCHLOROSILANE C ₁₂ H ₂₇ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [38051-57-9] TSCA HMIS: 3-1-1-X			0.866 1.441 100g/\$117.00	_
$CH_{3}(CH_{2})_{9} \xrightarrow{Cl}_{I} CH_{3}$	SID2662.0 n-DECYLMETHYLDICHLOROSILANE C ₁₁ H ₂₄ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18051-88-2] TSCA HMIS: 3-1-1-X		111-4°/3 120°C (248°F) ^{solvents} 25g/\$30.00	0.960 1.4490	_
$CH_3(CH_2)_9 \xrightarrow{Cl}_{l} Cl$	SID2663.0 n-DECYLTRICHLOROSILANE C ₁₀ H ₂₁ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [13829-21-5] TSCA HMIS: 3-1-1-X			1.0540 1.4528 100g/\$65.00	_
$CH_{3}(CH_{2})_{9} \xrightarrow[OC_{2}H_{5}]{} CH_{1}CH_{2}H_{5}$	SID2665.0 n-DECYLTRIETHOXYSILANE C ₁₆ H ₃₆ O ₃ Si see also SIB1829.0 for dipodal version HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [2943-73-9] HMIS: 2-1-0-X	304.54 ater/moisture 25g/\$54.00	150°/8	0.8790 1.4220 100g/\$175.00	_
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	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
nC_4H_9 Cl	SID3203.0 DI-n-BUTYLDICHLOROSILANE, 95% C ₈ H ₁₈ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture		212° 64°C (147°F) solvents	0.991	1.4448
nC_4H_9 CI	[3449-28-3] TSCA HMIS: 3-2-1-X	10g/\$52.00		50g/\$20	8.00
nC ₄ H ₉ OCH ₃ nC ₄ H ₉ OCH ₃	SID3214.0 DI-n-BUTYLDIMETHOXYSILANE C10H24O2Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [18132-63-3] TSCA-L HMIS: 3-2-1-X		125°/50 103°C (217°F) 25g/\$64.00	0.861	
$nC_{4}H_{9}-Si - N - Si - nC_{4}H_{9}$	SID3349.0 DI-n-BUTYLTETRAMETHYLDISILAZANE C ₁₂ H ₃₁ NSi ₂ HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mod [82356-80-7] HMIS: 2-1-1-X	•	81°/2 86°C (187°F)	0.80 100g/\$2	1.4353 40.00
$\begin{array}{cccc} CH_3 & CH_3 & CH_3 \\ I & I & I \\ CI & Si & O & Si & O \\ I & I & I \\ CH_3 & CH_3 & CH_3 \end{array}$	SID3360.0 1,5-DICHLOROHEXAMETHYLTRISILOXANE, 95% C ₆ H ₁₈ Cl ₂ O ₂ Si ₃ ΔHvap: 11.4 kcal/mole HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [3582-71-6] TSCA HMIS: 3-2-1-X	vapor pres		1.018 100g/\$1	
Cl	SID3367.6 DICHLOROPHENYLTRICHLOROSILANE, 95% C ₆ H ₃ Cl ₅ Si-isomeric mixture vapor pressure, 102°: 7mm	280.44 flashpoint:	260-1° 150°C (302°F)		1.564
	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [27137-85-5] TSCA HMIS: 3-1-1-X	e, water, protic 25g/\$45.00		100g/\$1	46.00
Cl - Si - O - Si - Cl	SID3372.0 1,3-DICHLOROTETRAMETHYLDISILOXANE C ₄ H ₁₂ Cl ₂ OSi ₂ vapor pressure, 25°: 8mm blocking agent	203.22 flashpoint:	138° (-37°)mp 15°C (59°F)	1.039	1.4054
CH ₃ CH ₃	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [2401-73-2] TSCA HMIS: 3-4-1-X	, water, protic 25g/\$36.00		100g/\$1	17.00
Si Cl	SID3382.0 DICYCLOHEXYLDICHLOROSILANE C ₁₂ H ₂₂ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18035-74-0] HMIS: 3-1-1-X		123°/0.4 149°C (300°F) solvents 25g/\$60.00	1.103	
CI-Si-CI	SID3390.0 DICYCLOPENTYLDICHLOROSILANE C ₁₀ H ₁₈ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture		105-7°/10 84°C (183°F) solvents	1.110	
	[139147-73-2] HMIS: 3-2-1-X	10g/\$29.00		50g/\$11	6.00
H ₄ CO-Si-OCH ₃	SID3391.0 DICYCLOPENTYLDIMETHOXYSILANE $C_{12}H_{24}O_2Si$		120°/6 102°C (216°F)	1.00	1.4663
	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [126990-35-0] TSCA HMIS: 3-1-1-X	ater/moisture 10g/\$24.00)	50g/\$96	.00
	SID3394.0 1,5-DIETHOXYHEXAMETHYLTRISILOXANE C ₁₀ H ₂₈ O ₄ Si ₃ [17928-13-1] HMIS: 2-2-1-X	296.59	51-2°/0.8 25g/\$118.00	0.912	1.3889
CH ₃ CH ₃ CH ₃ CH ₃	SID3398.0 (DIETHYLAMINO)TRIMETHYLSILANE TMSDEA $C_7H_{19}NSi$ Δ Hform: -87.7kcal/mole	145.32 flashpoint:	126-7° (-10°)mp 10°C (50°F)	0.7627	1.4109
CH ₃ CH ₂ NSi(CH ₃) ₃	silylation reagent: F&F: <i>3</i> , 317; <i>4</i> , 544; <i>6</i> , 634; HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [996-50-9] TSCA HMIS: 3-4-1-X)	100g/\$9	0.00

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰	-
CH ₃ CH ₂ , Cl CH ₃ CH ₂ , Cl	SID3402.0 DIETHYLDICHLOROSILANE C ₄ H ₁₀ Cl ₂ Si Δ Hvap: 10.0 kcal/mole dipole moment: 2.4 surface tension: 30.3 dynes/cm vapor pressure, 21°: 10mm HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture	flashpoint: thermal co		W/m°C	g	
	[1719-53-5] TSCA HMIS: 3-3-1-X	25g/\$23.00		100g/\$7	5.00	
CH_3CH_2 , OC_2H_5 CH_3CH_2 , OC_2H_5	SID3404.0 DIETHYLDIETHOXYSILANE C ₈ H ₂₀ O ₂ Si vapor pressure, 73°: 38mm HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [5021-93-2] TSCA HMIS: 2-3-1-X		157° 43°C (109°F)	0.8622 50g/\$14		
CH ₃ (CH ₂) ₅ , Cl CH ₃ (CH ₂) ₅ Cl	SID3510.0 DI-n-HEXYLDICHLOROSILANE C ₁₂ H ₂₆ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18204-93-8] TSCA HMIS: 3-2-1-X		111-3°/6 88°C (190°F) solvents	0.962 50g/\$16		
H ₃ C、CH ₃ CH CH ₂ H-Si-Cl CH ₂ H ₃ C、CH ₃ CH ₂ CH ₂	SID3526.0 DIISOBUTYLCHLOROSILANE C ₈ H ₁₉ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18279-73-7] HMIS: 3-3-1-X	178.78 flashpoint:	166-7° 42°C (108°F)	0.995	1.4340	
CH H_3C CH_3 $CH_2CH_2CH_3CH_2O$ CH_3CH_2O \Rightarrow i - OCH_2CH_3 CH_2 CH	SID3528.0 DIISOBUTYLDIETHOXYSILANE C ₁₂ H ₂₈ O ₂ Si [18297-14-8] HMIS: 2-2-1-X	232.44	221° 10g/\$86.00	0.8450	1.4179	
$H_3C \xrightarrow{CH_3} H_3C \xrightarrow{CH_3} H_3C \xrightarrow{CH_3} H_3C \xrightarrow{CH_3} H_3C \xrightarrow{CH_3} H_3C \xrightarrow{CH_2} H_2$	SID3530.0 DIISOBUTYLDIMETHOXYSILANE C ₁₀ H ₂₄ O ₂ Si intermediate for diisobutylsilanediol, a liquid cr employed in polyolefin polymerization		120°/6 102°C (216°F)	0.87	1.4167	
H ₃ C CH	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [17980-32-4] TSCA HMIS: 2-1-1-X	ater/moisture 10g/\$20.00		50g/\$80	.00	
H ₃ C, CH ₃ CH CI-Si-CI	SID3537.0 DIISOPROPYLDICHLOROSILANE C ₆ H ₁₄ Cl ₂ Si forms bis(blocked) or tethered alcohols ^{1,2} . 1. J. Hutchinson et al, Tet. Lett., <i>32</i> , 573, 1991. 2. C. Bradford et al, Tet. Lett., <i>36</i> , 4189, 1995.	185.17 flashpoint:	64-5°/25 43°C (109°F)	12	1.4450	
H ₃ C CH ₃	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [7751-38-4] HMIS: 3-3-1-X	e, water, protic 10g/\$21.00	solvents	50g/\$84	.00	
H ₃ C CH ₃ CH CH ₃ O Si - OCH ₃	SID3538.0 DIISOPROPYLDIMETHOXYSILANE $C_8H_{20}O_2Si$ cocatalyst for α -olefin polymerization ¹ . 1. S. Lee et al, US Pat. 5,223,466, 1993	176.33 flashpoint:	85-7°/50 43°C (109°F)	0.875	1.4140	
H ₃ C ^{CH} CH ₃	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [18230-61-0] TSCA HMIS: 3-3-1-X	ater/moisture 10g/\$39.00		50g/\$15	6.00	
Si(OC ₂ H ₅) ₃	SID3544.0 3,5-DIMETHOXYPHENYLTRIETHOXYSILANE	300.43	136-8°/0.6	1.050		
CH ₃ O OCH ₃	C ₁₄ H ₂₄ O ₅ Si HMIS: 2-1-1-X		5.0g/\$175.00			
$CH_{3} \rightarrow N - Si - CH_{3}$ $CH_{3} \rightarrow I - CH_{3}$ $CH_{3} \rightarrow CH_{3}$	SID3605.0 (N,N-DIMETHYLAMINO)TRIMETHYLSILANE <i>TMSDMA PENTAMETHYLSILANAMINE</i> C ₅ H ₁₅ NSi stronger silylation reagent than HMDS; silylate selectively silylates equatorial hydroxyl groups 1. K. Rühlman, Chem. Ber., <i>94</i> , 1876, 1961. 2. E. Yankee et al, J. Am. Chem. Soc., <i>94</i> , 365	∆Hvap: 7.6 s amino aci in prostagla	ids¹.	0.741	1.3970	COMMERCIAL
	HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with wa [2083-91-2] TSCA HMIS: 3-4-1-X	ater/moisture 25g/\$38.00	100g/\$123.00	2kg/\$92		

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	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
CH ₃ CHCH ₂ CH ₃ H ₃ C Si	SID4040.0 DIMETHYLBIS(s-BUTYLAMINO)SILANE 95% $C_{10}H_{26}N_2Si$		82°/15 (<-50°)mp - oral rat, LD50: 9 : 40°C (104°F)	0.810 007mg/kg	1.4271
H ₃ C NH CH ₃ CHCH ₂ CH ₃	chain-extender for silicones HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [93777-98-1] TSCA HMIS: 3-3-1-X		c solvents	100g/\$	133.00
$\begin{array}{ccc} CH_3 & CH_3 \\ H_3CCH_2CH_2Si & -Cl \\ CH_3 & CH_3 \end{array}$	SID4065.0 (3,3-DIMETHYLBUTYL)DIMETHYLCHLORO- SILANE NEOHEXYLDIMETHYLCHLOROSILANE C ₈ H ₁₉ CISi blocking agent HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [96220-76-7] HMIS: 3-3-1-X	·	167° : 38°C (100°F) c solvents	0.849 100g/\$1	1.4240
$\begin{array}{ccc} CH_3 & CI \\ I & I \\ CH_3CCH_2CH_2Si & -CI \\ CH_3 & CI \end{array}$	SID4069.0 (3,3-DIMETHYLBUTYL)TRICHLOROSILANE NEOHEXYLTRICHLOROSILANE $C_6H_{13}Cl_3Si$ [105732-02-3] HMIS: 3-2-1-X	219.61	183-4° 25g/\$48.00	1.1355	1.4479
CH ₂ -Si-Cl CH ₃	SID4074.0 (DIMETHYLCHLOROSILYL)METHYLPINANE C ₁₂ H ₂₃ CISi acetylenic derivative forms chiral polymer mer 1. T. Aoki et al, Makromol. Chem. Rapid Comm HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [2182-66-3] TSCA HMIS: 3-2-1-X	1*S,2*S,5 nbrane that nun, <i>13</i> , 56	5, 1992	0.957 5% optica acids ¹ .	1.4780 al purity
COMMERCIAL	SID4074.4 1,1-DIMETHYLCYCLOSILAZANES, 22-25% in hexane primarily trimer and tetramer HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/me TSCA HMIS: 2-4-1-X		: 20°C (-25°F) .00	0.69 2kg/\$1	90.00
$\begin{array}{c} O CH_3 O \\ \parallel & \parallel & \parallel \\ CH_3CO - Si - OCCH_3 \\ H \\ CH_3 \end{array}$	SID4076.0 DIMETHYLDIACETOXYSILANE C ₆ H ₁₂ O ₄ Si reagent for the preparation of cis-diols and co 1. R. Kelley, J. Chromatog., <i>43</i> , 229, 1969; F& HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [2182-66-3] TSCA HMIS: 2-3-1-X	rticosteroid F <i>3</i> , 113		1.054 500g/\$1	1.4030
CH ₃ CI-Si-CI CH ₃	SID4120.0 DIMETHYLDICHLOROSILANE $C_2H_6Cl_2Si$ viscosity: 0.47 cSt Δ Hvap: 8.0 kcal/mole vapor pressure, 17°: 100mm coefficient of thermal expansion: 1.3 x 10 ⁻³ critical temperature: 247.2° autoignition temperature: 410° fundamental monomer for silicones; hydropho HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [75-78-5] TSCA HMIS: 3-4-2-X	flashpoint ∆Hcomb: specific ho surface te critical pre flammabil bic surface re, water, protic	c solvents 00_2kg/\$58.00_18k	0ppm/4⊢ s/cm % g/\$477.00	
CI-Si-CI CH ₃ CH ₃	SID4120.1 DIMETHYLDICHLOROSILANE, 99+% C ₂ H ₆ Cl ₂ Si redistilled HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [75-78-5] TSCA HMIS: 3-4-2-X) 500g/\$68.00 18	<g \$1224.0<="" th=""><th>1.4055 00*+container 3-019 required</th></g>	1.4055 00*+container 3-019 required

	name	MW	bp/mm (mp)	D ₄ ²⁰ n _D ²⁰	
$C_{2}H_{5}O - Si - OC_{2}H_{5}$ CH_{3}	SID4121.0 DIMETHYLDIETHOXYSILANE $C_6H_{16}O_2Si$ viscosity; 0.53cSt vapor pressure, 25°: 15mm Δ Hvap: 9.8 kcal/mole Δ Hform: 200 kcal/mole coefficient of thermal expansion: 1.3 x 10 ⁻³ hydrophobic surface treatment and release ag HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w	flashpoint: <u>A</u> Hcomb: - dipole mor ent ater/moisture			HYDROPHOBIC commercial
	[78-62-6] TSCA HMIS: 2-4-1-X SID4123.0	100g/\$12.0	0 2kg/\$144.00	15kg/\$930.00	IC IERCI
CH ₃ O-Si-OCH ₃ CH ₃ O-CH ₃	DIMETHYLDIMETHOXYSILANE $C_4H_{12}O_2Si$ Δ Hcomb: 832 kcal/mole Δ Hform: 171 kcal/mole vapor pressure, 36°: 100mm coefficient of thermal expansion: 1.3 x 10 ⁻³	dipole mor viscosity, 2	82° (-80°)mp -8°C (18°F) nent 1.33 20°C: 0.44cSt	0.8646 1.3708	Υ.
CH ₃	HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with w [1112-39-6] TSCA HMIS: 3-4-1-X	ater/moisture 25g/\$10.00	2kg/\$110.00	15kg/\$600.00	
CH ₃ O-Si-OCH ₃ CH ₃	SID4123.1 DIMETHYLDIMETHOXYSILANE, 99+% <i>DMDMOS</i> C ₄ H ₁₂ O ₂ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [1112-39-6] TSCA HMIS: 3-4-1-X	120.22 ater/moisture	82° (-80°)mp 500g/\$89.00	0.8646 1.3708	
CH ₃ H-Si-OC ₂ H ₅ CH ₃	SID4125.0 DIMETHYLETHOXYSILANE C ₄ H ₁₂ OSi vapor pressure, 25°: 281mm undergoes hydrosilylation reactions waterproofing agent for space shuttle thermal 1. W. Hill et al, Poly. Mat. Sci. Eng., <i>62</i> , 668, 19 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [14857-34-2] TSCA HMIS: 2-4-1-X	flashpoint: tiles ¹ . 990	54-5° oral rat, LD50: 5 15°C (59°F)	0.757 1.3683 000mg/kg 100g/\$98.00	
CH ₃ CH ₃ O-Si-Cl CH ₃	SID4210.0 DIMETHYLMETHOXYCHLOROSILANE, 90% C ₃ H ₉ CIOSi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [1825-68-9] TSCA HMIS: 3-4-1-X		77° -9°C (16°F) solvents	0.953 ²⁵ 1.3865 100g/\$150.00	
$\begin{array}{c} OCH_3 OCH_3 \\ H_3C-Si-O-Si-CH_3 \\ OCH_3 OCH_3 \end{array}$	SID4236.0 1,3-DIMETHYLTETRAMETHOXY- DISILOXANE, 95% C ₆ H ₁₈ O ₅ Si ₂ HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [18186-97-5] HMIS: 3-3-1-X		165° 30°C (86°F)	1.010 1.3834 50g/\$120.00	
CH ₃ (CH ₂) ₇ Cl	SID4400.0 DI-n-OCTYLDICHLOROSILANE C ₁₆ H ₃₄ Cl ₂ Si	325.44	145°/0.2	0.940	
CH ₃ (CH ₂) ₇ Cl	HYDRÓLYTIC SENSITIVITY: 8 reacts rapidly with moistur [18416-07-4] HMIS: 3-2-1-X	e, water, protic 25g/\$38.00		100g/\$124.00	
H ₃ C SiCH ₂ CH ₃ H ₃ C CH ₂ CH ₂ Si -Cl CH ₃	SID4401.0 (DI-n-OCTYLMETHYLSILYL)ETHYLDIMETHYL- CHLOROSILANE C ₂₁ H ₄₇ CISi ₂ forms bonded phases for reverse phase chron HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [472513-03-7] HMIS: 3-2-1-X	natography	165-6°/0.1 ^{solvents} 25g/\$117.00	0.859	

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	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
H ₃ C – SiCH ₂ CH ₂ Si –Cl	SID4401.5 (DI-n-OCTYLMETHYLSILYL)ETHYLTRI- CHLOROSILANE C ₁₉ H ₄₁ Cl ₃ Si ₂ forms bonded phases for reverse phase HPL0 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur HMIS: 3-2-1-X		166-8°/0.1 ic solvents 25g/\$117.00	0.966	
$\begin{array}{ccc} CH_3 & CH_3 \\ CH_3(CH_2)_7 - Si - N - Si - (CH_2)_7CH_3 \\ H_3 H & CH_3 \end{array}$	SID4404.0 1, 3-DI-n-OCTYLTETRAMETHYLDISILAZANE C ₂₀ H ₄₇ NSi ₂ HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/n [69519-51-3] HMIS: 2-1-0-X		160-5°/1 t: >110°C (>230°F 10g/\$49.00	0.826	1.4500
	$\begin{array}{l} \text{SID4510.0} \\ \text{DIPHENYLDICHLOROSILANE, 95\%} \\ \text{C}_{12}\text{H}_{10}\text{Cl}_2\text{Si} \\ \text{vapor pressure, } 125^\circ\text{: 2mm} \\ \text{\Delta}\text{Hvap: 15.0 kcal/mole} \\ \text{coefficient of thermal expansion: } 0.7 \text{ x } 10^{-3} \\ \text{specific heat: } 0.30 \\ \text{silicone monomer; forms diol on contact with} \\ \text{HYDROLYTIC SENSITIVITY: } 8 \text{ reacts rapidly with moistu} \\ [80-10-4] \text{ TSCA HMIS: } 3-1-1-X \end{array}$	flashpoint dipole mo viscosity, water			
Si Cl	SID4510.1 DIPHENYLDICHLOROSILANE, 99% C ₁₂ H ₁₀ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistu [80-10-4] TSCA HMIS: 3-1-1-X	flashpoint re, water, prot	304-5° (-22°)mp Y- ipr mus, LD50: : t: 157°C (314°F) ic solvents 0 100g/\$36.00		-
Si OC ₂ H ₅	SID4525.0 DIPHENYLDIETHOXYSILANE C ₁₆ H ₂₀ O ₂ Si vapor pressure, 125°: 2mm HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with v [2553-19-7] TSCA HMIS: 2-1-0-X		167°/15 t: 175°C (347°F) 0 100g/\$58.00	1.0329 2kg/\$26	1.5269 5.00
Si OCH3 OCH3	SID4535.0 DIPHENYLDIMETHOXYSILANE C ₁₄ H ₁₆ O ₂ Si viscosity, 25°: 8.4 cSt HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with v [6843-66-9] TSCA HMIS: 3-1-1-X		161°/15 t: 121°C (250°F) 00	1.0771 2kg/\$19	1.5447
Si ^{CH3}	SID4552.0 DIPHENYLMETHYLCHLOROSILANE $C_{13}H_{13}CISi$ vapor pressure, 125°: 3mm Δ Hvap: 149 kcal/mole surface tension: 40.0 dynes/cm α silylates esters, lactones; precursors to α si 1. G. Larson et al, J. Am. Chem. Soc., <i>103</i> , 2 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistu [144-79-6] TSCA HMIS 3-1-1-X	viscosity, thermal c lyl enolates 418, 1981.	ic solvents		1.5742
Si CH ₃ N(CH ₃) ₂	SID4552.5 DIPHENYLMETHYL(DIMETHYLAMINO)SILANE C ₁₅ H ₁₉ NSi HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [68733-63-1] TSCA-L HMIS: 3-3-1-X	241.41 vater/moisture 25g/\$34.0		1.011 100g/\$	110.00

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
Si OC ₂ H ₅	SID4553.0 DIPHENYLMETHYLETHOXYSILANE C ₁₅ H ₁₈ OSi ∆Hvap: 14.8 kcal/mole vapor pressure: 125°: 3mm HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w	viscosity, 2	100-2°/0.3 (-27°)mp 165°C (329°F) 25°: 6.5 cSt	1.018	1.544025
\sim	[1825-59-8] TSCA HMIS: 2-0-0-X	109/\$23.00)	50g/\$92	.00
$\begin{bmatrix} \swarrow & \overset{CH_3}{\underset{I}{\overset{I}{\overset{I}{\overset{I}{\overset{I}{\overset{I}{\overset{I}{I$	SID4586.0 1,3-DIPHENYL-1,1,3,3,-TETRAMETHYL- DISILAZANE C ₁₆ H ₂₃ NSi ₂ HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo	bisture	96-9°/0.1 162°C (324°F)	0.985	1.5384
	[3449-26-1] TSCA-L HMIS: 3-1-1-X	5.0g/\$30.0	0	25g/\$12	0.00
$\begin{array}{ccc} CH_{3} & CH_{3} \\ H_{3} \\ CH_{3}CH_{2}CH_{2} \\ -Si \\ -N \\ -Si \\ -Si \\ -N \\ -Si \\ -CH_{2}CH_{2}CH_{2}CH_{3} \\ H_{3} \\ $	SID4591.0 1,3-DI-n-PROPYLTETRAMETHYLDISILAZANE C ₁₀ H ₂₇ NSi ₂ [14579-90-9] HMIS: 3-2-1-X	217.51 flashpoint:	84°/9 65°C (150°F) 25g/\$140.00	0.800	1.4290
CH ₃ Si ^{Cl}	SID4598.0 DI(p-TOLYL)DICHLOROSILANE, 95% C ₁₄ H ₁₄ Cl ₂ Si forms polymers w/liquid crystal behavior ¹ . 1. M. Lee et al, Polymer, <i>34</i> , 4882, 1993.		225-6°/50 -4'dimethylbipher	1.10 iyl	1.568
CH ₃	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18414-38-5] HMIS: 3-2-1-X	e, water, protic 10g/\$37.00		50g/\$14	8.00
CH ₃ OCH ₃ CH ₃ OCH ₃	SID4599.0 DI(p-TOLYL)DIMETHOXYSILANE C ₁₆ H ₂₀ O ₂ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [92779-72-1] HMIS: 3-2-1-X	272.42 ater/moisture	140°/0.5 25g/\$155.00	1.023	1.535525
$CH_{3}(CH_{2})_{20}CH_{2}$ Cl H_{3}CCl	SID4620.0 DOCOSYLMETHYLDICHLOROSILANE, blend C ₂₃ H ₄₈ Cl ₂ Si contains C ₂₀ to C ₂₄ homologs HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [67892-56-2] TSCA HMIS: 3-1-1-X		218-20°/0.5 (21-9°)mp 172°C (342°F) solvents 50g/\$130.00	0.93	9
CH ₃ (CH ₂) ₂₀ CH ₂ Cl Cl Cl Cl	SID4621.0 DOCOSYLTRICHLOROSILANE, blend C ₂₂ H ₄₅ Cl ₃ Si contains C ₂₀ to C ₂₄ homologs HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [7325-84-0] TSCA HMIS: 3-1-1-X		210°/0.2 (20-8°)mp 200°C (392°F) solvents 25g/\$85.00	0.94	
CH ₃ (CH ₂) ₁₀ CH ₂ CH ₃ H ₃ C Cl	SID4627.0 DODECYLDIMETHYLCHLOROSILANE C ₁₄ H ₃₁ ClSi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [66604-31-7] HMIS: 3-2-1-X	262.94 e, water, protic	291-3° solvents 25g/\$58.00	0.865	1.445
$\begin{array}{c} CH_{3}(CH_{2})_{10}CH_{2} \\ CI \\ H_{3}C \\ CI \end{array}$	SID4628.0 DODECYLMETHYLDICHLOROSILANE C ₁₃ H ₂₈ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [18407-07-3] TSCA HMIS:3-1-1-X		124-7°/3 143°C (289°F) solvents 25g/\$48.00	0.955	1.4581
CH ₃ (CH ₂) ₁₀ CH ₂ OCH ₂ CH ₃ H ₃ C OCH ₂ CH ₃	SID4629.0 DODECYLMETHYLDIETHOXYSILANE C ₁₇ H ₃₈ O ₂ Si HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo [60317-40-0] TSCA HMIS: 2-1-0-X	-	140°/0.5 152°C (305°F) 25g/\$55.00	0.84525	

	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
CH ₃ (CH ₂) ₁₀ CH ₂ SiCl ₃	SID4630.0 DODECYLTRICHLOROSILANE C ₁₂ H ₂₅ Cl ₃ Si	303.77 flashpoint:	120°/3 (-30°)mp 165°C (329°F)	1.0242	1.4581
	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [4484-72-4] TSCA HMIS: 3-1-1-X		solvents	250g/\$1	12.00
CH ₃ (CH ₂) ₁₀ CH ₂ Si(OC ₂ H ₅) ₃	SID4632.0 DODECYLTRIETHOXYSILANE C ₁₈ H ₄₀ O ₃ Si HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mod		152-3°/3 >110°C (>230°F)		⁵1.4330 ²⁵
	[18536-91-9] TSCA HMIS: 2-1-0-X	25g/\$27.00		100g/\$8	8.00
CH ₃ (CH ₂) ₁₈ CH ₂ SiCl ₃	SIE4661.0 EICOSYLTRICHLOROSILANE, 95% C ₂₀ H ₄₁ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistur [18733-57-8] TSCA HMIS: 3-0-1-X		200°/0.5 230°C (446°F) ^{solvents} 25g/\$160.00		
CH_3CH_2 — Si – Cl	SIE4892.0 ETHYLDIMETHYLCHLOROSILANE C ₄ H ₁₁ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture		91° -4°C (24°F)	0.8756	1.4050
CH ₃	[6917-76-6] HMIS: 3-4-1-X	10g/\$24.00		50g/\$96	.00
CH ₃ , Cl	SIE4896.0 ETHYLMETHYLDICHLOROSILANE $C_3H_8Cl_2Si$ dipole moment: 2.32 debye	143.09 flashpoint:	100° 2°C (36°F)	1.0630	1.4197
CH ₃ CH ₂ Cl	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [4525-44-4] TSCA HMIS: 3-4-1-X	e, water, protic s 25g/\$31.00	solvents	100g/\$1	00.00
OSi(CH ₃) ₃ N II .C.	SIE4897.0 (ETHYLMETHYLKETOXIMINO)TRIMETHYL- SILANE <i>O-(TRIMETHYLSILYL)OXIME-2-BUTANONE</i> C ₇ H ₁₇ NOSi		65°/75	0.82625	1.4125 ²⁵
H ₃ C CH ₂ CH ₃	HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo [37843-14-4] HMIS: 2-3-1-X	bisture	10g/\$41.00		
CH ₃ CH ₂	SIE4897.5 m,p-ETHYLPHENETHYLTRIMETHOXY- SILANE, 95% C ₁₃ H ₂₂ O ₃ Si	254.40	93-6°/4	0.996	1.4776 ²⁵
CH ₂ CH ₂ Si(OMe) ₃	component in optical hard coating resins HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo [259818-29-6] HMIS: 3-2-1-X	pisture	25g/\$102.00		
O OCCH ₃ O CH ₃ CH ₂ -Si-O-CCH ₃	SIE4899.0 ETHYLTRIACETOXYSILANE C ₈ H ₁₄ O ₆ Si liquid cross-linker for silicone RTVs	243.28 flashpoint:	107-8°/8 (7-9°)mp 106°C (223°F)	1.143	1.4123
OCCH3	HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo [17689-77-9] TSCA HMIS: 3-1-1-X	bisture 25g/\$10.00		2.0kg/\$1	48.00
	SIE4901.0 ETHYLTRICHLOROSILANE	163.51	100-1°	1.237	
$CH_{3}CH_{2}-Si-Cl$	C ₂ H ₅ Cl ₃ Si vapor pressure, 20°: 26mm, 30.4°; 66mm ΔHvap: 9.0 kcal/mole coefficient of expansion: 1.5x10 ⁻³ viscosity: 0.48 cSt HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture	flashpoint: dipole mon critical tem	perature: 287°		
	[115-21-9] TSCA HMIS: 3-3-1-X	25g/\$10.00		4kg/\$17	6.00
OC_2H_5	SIE4901.2 ETHYLTRIETHOXYSILANE $C_8H_{20}O_3Si$	192.33 TOXICITY-	158-9° (-78°)mp oral rat, LD50: 1	0.8963 3,720 mg	
$CH_3CH_2 - Si - OC_2H_5$ OC_2H_5	viscosity: 0.70 cSt vapor pressure, 50°: 10mm coefficient of thermal expansion: 1.5 x 10 ⁻³ ΔHvap: 7.8 kcal/mole HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moisture	autoignitior specific he γc of treate critical tem	flashpoint: 40°(n temperature: 23 at: 0.43/g/° ed surface: 26.3 d perature: 314°	C (104°F 35°C (459 lynes/cm) 5°F)
	[78-07-9] TSCA HMIS: 3-2-1-X	100g/\$37.0	0	500g/\$1	40.00

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	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
$CH_{3}CH_{2} - Si - OCH_{3}$ OCH_{3} OCH_{3}	SIE4901.4 ETHYLTRIMETHOXYSILANE C ₅ H ₁₄ O ₃ Si viscosity: 0.5 cSt HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mc	∆Hcomb: 3	124-5° 27°C (80°F) 425 kcal/mole	0.9488	
Control Glassclad [®] 18	 [5314-55-6] TSCA HMIS: 3-3-1-X PP1-GC18 GLASSCLAD[®] 18 OCTADECYL FUNCTIONAL SILANE 20% in t-BUTYL ALCOHOL and DIACETONE ALCOHOL γc of treated glass surface: 31 dynes/cm coefficient of friction of treated glass surface: 0 surface resistivity of treated surface: 1.2 x 10¹³ reduces blood protein adsorption¹. 1. B. Arkles et al in "Silanes Surfaces & Interface TSCA HMIS: 2-3-1-X 	flashpoint: amber liqui).2-0.3 ohms s" D. Leyden	id		сомменсія 16, р91
$CF_3(CF_2)_7CH_2CH_2 \xrightarrow{CH_3}{-Si-Cl}_{CH_3}$	SIH5840.4 (HEPTADECAFLUORO-1,1,2,2-TETRA- HYDRODECYL)DIMETHYLCHLOROSILANE <i>PERFLUORODECYL-1H,1H,2H,2H-DIMETHYLCHLORO</i> C ₁₂ H ₁₀ CIF ₁₇ Si derivatizing agent for fluorous phase synthesis HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture [74612-30-9] HMIS: 3-2-1-X		197-8°	1.51 25g/\$16	1.3410
$CF_{3}(CF_{2})_{7}CH_{2}CH_{2} - Si - Cl$	SIH5840.6 (HEPTADECAFLUORO-1,1,2,2-TETRA- HYDRODECYL)METHYLDICHLOROSILANE C ₁₁ H ₇ Cl ₂ F ₁₇ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture [3102-79-2] HMIS: 3-2-1-X	561.14 , protic solvents 5.0g/\$48.00	205-7° (26-7°)mp	1.63 25g/\$19	2.00
$CF_{3}(CF_{2})_{7}CH_{2}CH_{2} \xrightarrow{\qquad Cl}_{\qquad Cl}$	SIH5841.0 (HEPTADECAFLUORO-1,1,2,2-TETRA- HYDRODECYL)TRICHLOROSILANE <i>PERFLUORODECYL-1H,1H,2H,2H-TRICHLOROSILANE</i> $C_{10}H_4Cl_3F_{17}Si$ $\gamma c of treated surfaces: 12 dynes/cm1.1. J. Brzoska et al, Langmuir, 10, 4367, 1994HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture[78560-44-8] TSCA HMIS: 3-2-1-X$	E	216-8° oral rat, LD50: >	1.703 5000 mg 25g/\$14	
$CF_{3}(CF_{2})_{7}CH_{2}CH_{2} \xrightarrow{OC_{2}H_{5}}{-Si - OC_{2}H_{5}}$	SIH5841.2 (HEPTADECAFLUORO-1,1,2,2-TETRA- HYDRODECYL)TRIETHOXYSILANE C ₁₆ H ₁₉ F ₁₇ O ₃ Si hydrolysis in combination with polydimethoxys 1. T. Oota et al, Jpn. Kokai JP 06,293,782, 199 HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mc [101947-16-4] HMIS: 3-2-1-X	610.38 iloxane give 3; CA 122:	103-6°/3 s hard hydrophot	1.40725	1.3419 ngs¹.
$CF_3(CF_2)_7CH_2CH_2 \xrightarrow{OCH_3}_{I}OCH_3$ OCH ₃	SIH5841.5 (HEPTADECAFLUORO-1,1,2,2-TETRA- HYDRODECYL)TRIMETHOXYSILANE C ₁₃ H ₁₃ F ₁₇ O ₃ Si HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mod [83048-65-1] HMIS: 3-2-1-X	568.30 ^{iisture} 5g/\$42.00	247°	1.54 25g/\$16	1.331 ²⁵
F ₃ C F-C-O-CH ₂ CH ₂ CH ₂ SiCl ₃ F ₃ C	SIH5842.0 (3-HEPTAFLUOROISOPROPOXY)PROPYL- TRICHLOROSILANE C ₆ H ₆ Cl ₃ F ₇ OSi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture [15538-93-9] HMIS: 3-3-1-X	361.55 , protic solvents	85-7°/35 5.0g/\$64.00	1.497	1.3710
$CH_{3}(CH_{2})_{6} \xrightarrow{Cl}{-Si} -CH_{3}$	SIH5845.0 n-HEPTYLMETHYLDICHLOROSILANE C ₈ H ₁₈ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture [18395-93-2] TSCA HMIS: 3-2-1-X		207-8° 66°C (150°F) 25g/\$74.00	0.978	1.4396 ²⁵

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	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
CH ₃ (CH ₂) ₆ SiCl ₃	SIH5846.0 n-HEPTYLTRICHLOROSILANE C ₇ H ₁₅ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture [871-41-0] HMIS: 3-2-1-X		211-2° 64°C (146°F) 25g/\$74.00	1.087	1.443925
$H_2C = CHCF_2(CF_2)_6CF_2CH_2CH_2SiCl_3$	SIH5918.0 HEXADECAFLUORODODEC-11-ENE-1-YL- TRICHLOROSILANE C ₁₂ H ₇ Cl ₃ F ₁₆ Si forms self-assembled monolayers/ reagent for HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo HMIS: 3-1-1-X		94-6°/0.6 tion of DNA 5.0g/\$190.00	1.626	1.3713
CH ₃ (CH ₂) ₁₄ CH ₂ SiCl ₃	SIH5920.0 HEXADECYLTRICHLOROSILANE, 95% C ₁₆ H ₃₃ Cl ₃ Si γc of treated surfaces: 21 dynes/cm HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture [5894-60-0] TSCA HMIS: 3-1-1-X			0.98 100g/\$4	1.4592
CH ₃ (CH ₂) ₁₄ CH ₂ Si(OC ₂ H ₅) ₃	SIH5922.0 HEXADECYLTRIETHOXYSILANE, 95% C ₂₂ H ₄₈ O ₃ Si HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo [16415-13-7] HMIS: 2-1-1-X	388.71 isture 25g/\$23.00	160-1°/1 (-9°)mp 0	0.888 100g/\$7	1.4370
CH ₃ (CH ₂) ₁₄ CH ₂ Si(OCH ₃) ₃	SIH5925.0 HEXADECYLTRIMETHOXYSILANE, 95% C ₁₉ H ₄₂ O ₃ Si viscosity: 7 cSt HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo	346.63	155°/0.2 (-1°)mp	0.89	
	[16415-12-6] TSCA HMIS: 2-2-1-X	25g/\$18.00) 2kg/\$290.00	16kg/\$1	536.00
$H H_{3}C C H_{3}N H_{3}C H_{$	 SIH6102.0 1,1,3,3,5,5-HEXAMETHYLCYCLOTRISILAZANE C₆H₂₁N₃Si₃ ΔHform: 132 kcal/mole viscosity, 20°: 1.7 cSt modifies positive resists for O₂ plasma resistar polymerizes to polydimethylsilazane oligomer i silylation reagent for diols³. 1. E. Babich et al, Microelectron. Eng., <i>11</i>, 503 2. Y. Blum et al, US Pat., 4,216,383, 1986; US 3. L. Birkofer et al, J. Orgmet. Chem., <i>187</i>, 21, see also SID4074.4 HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mode 	dipole moi dielectric o nce ¹ . n presence , 1990. Pat. 4,788 1980.	constant, 1000Hz e of Ru/H ₂ ².	0.922	1.4448
COMMERCI	[1009-93-4] TSCA HMIS: 2-2-1-X	25g/\$29.00) 100g/\$94.00	2kg/\$63	6.00
$\begin{array}{c} CH_{3} \\ CH_{3$	SIH6110.0 HEXAMETHYLDISILAZANE C ₆ H ₁₉ NSi ₂ <i>HMDS, HMDZ</i> viscosity: 0.90 cSt vapor pressure, 50°: 50mm pKa: 7.55 surface tension: 18.2 dynes/cm Ea, reaction w/SiO ₂ surface: 17.6 kcal/mole versatile silylation reagent; creates hydrophobi	TOXICITY- flashpoint: ΔHvap: 8.3 dielectric of specific we c surfaces	126-7° - oral rat, LD50: 8 - ipr mus, LDLo: 6 14°C (57°F) 3 kcal mole constant, 1000 Hz etting surface: 48	50mg/kg 550mg/kg z: 2.27	1.4080
	HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo [999-97-3] TSCA HMIS: 2-4-1-X	isture 25g/\$10.00) 1.5kg/\$60.00	14kg/\$3	05.00
$\begin{array}{c} CH_3 \\ CH_3 \\ CH_3 \end{array} \begin{array}{c} H \\ Si - N \\ CH_3 \end{array} \begin{array}{c} CH_3 \\ CH_3 \end{array} \begin{array}{c} CH_3 \\ CH_3 \end{array}$	SIH6110.1 HEXAMETHYLDISILAZANE, 99% C ₆ H ₁₉ NSi ₂ <i>HMDS, HMDZ</i> <5ppm chloride photoresist adhesion promoter HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo	isture	126-7° - ipr mus, LDLo: 6	650mg/kg	
	[999-97-3] TSCA HMIS: 2-4-1-X SIH6165.6	25g/\$13.00)	1.5kg/\$8	35.00
CH ₃ (CH ₂) ₄ CH ₂ , Cl CH ₃ Si Cl	HEXYLMETHYLDICHLOROSILANE C ₇ H ₁₆ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [14799-94-1] TSCA HMIS: 3-2-1-X	-	204-6° 85°C (185°F) ^{solvents} 25g/\$31.00	0.993	1.4390

	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
CH ₃ (CH ₂) ₄ CH ₂ ,Cl	SIH6167.0 HEXYLTRICHLOROSILANE C ₆ H ₁₃ Cl ₃ Si	219.61 flashpoint:	191-2° 85°C (185°F)	1.107	1.3473
CI	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [928-65-4] TSCA HMIS: 3-2-1-X		solvents	100g/\$4	9.00
$CH_3(CH_2)_4CH_2Si(OC_2H_5)_3$	SIH6167.5 HEXYLTRIETHOXYSILANE C ₁₂ H ₂₈ O ₃ Si HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo	oisture	115°/18 95°C (203°F)	0.860	1.40825
	[18166-37-5] HMIS: 2-1-1-X SIH6168.5	25g/\$31.00)	100g/\$ ⁻	
CH ₃ (CH ₂) ₄ CH ₂ Si(OCH ₃) ₃	HEXYLTRIMETHOXYSILANE C ₉ H ₂₂ O ₃ Si HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo	oisture	202-3° 62°C (144°F)		1.4070
H ₂ C CH ₃	[3069-19-0] TSCA HMIS: 3-2-1-X SII6452.5	50g/\$31.00		2kg/\$19	0.00
$\begin{array}{c} H_{3}C \\ CHCH_{2}Si - Cl \\ H_{3}C \\ CH_{3} \end{array}$	ISOBUTYLDIMETHYLCHLOROSILANE C ₆ H ₁₅ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [60090-96-2] HMIS:3-4-1-X		131-3° 18°C (64°F) solvents 10g/\$28.00		1.4187 ²⁵
H ₃ C CH ₃	SII6452.8 ISOBUTYLMETHYLDIMETHOXYSILANE	162.30	63°/40	0.851	1.3962
$H_{3}C$ $H_{2}Si - OCH_{3}$ OCH_{3}	C ₇ H ₁₈ O ₂ Si HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo [18293-82-8] HMIS: 2-3-1-X	flashpoint:	38°C (101°F) 25g/\$57.00		
$H_{3}C$ Cl Cl $H_{2}Si$ $-Cl$ $H_{3}C$ Cl Cl Cl Cl Cl Cl Cl C	SII6453.0 ISOBUTYLTRICHLOROSILANE	191.56	140°	1.162	1.4335
H_3C Cl	C ₄ H ₉ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18169-57-8] TSCA HMIS: 3-3-1-X			100g/\$3	36.00
H_3C OC_2H_5 CHCH $_2Si$ $-OC_2H_5$	SII6453.5 ISOBUTYLTRIETHOXYSILANE C ₁₀ H ₂₄ O ₃ Si	flashpoint:	190-1° oral rat, LD50: > 63°C (145°F)		1.3908 /kg
H_3C OC_2H_5	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [17980-47-1] TSCA HMIS: 2-2-1-X		2kg/\$92.00	16kg/\$5	28.00
H ₃ C OCH ₃	SII6453.7 ISOBUTYLTRIMETHOXYSILANE TRIMETHOXYSILYL-2-METHYLPROPANE		154° 42°C (107°F)		1.3960
H ₃ C CHCH ₂ Si —OCH	C ₇ H ₁₈ O ₃ Si viscosity: 0.8 cSt branched structure provides hydrophobic surfa		oral rat,LD50: >	Ŭ	•
OCH ₃	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [18395-30-7] TSCA HMIS: 3-2-1-X	ater/moisture	2kg/\$110.00	17kg/\$4	-
CH_3 CH_3 CH_3 CH_3 $CH_3CCH_2CHCH_2SiCI$	SII6456.6 ISOOCTYLDIMETHYLCHLOROSILANE C ₁₀ H ₂₃ CISi	206.83	83-5°/10	0.852	
CH_3 CH_3	[79957-95-2] HMIS: 3-3-1		25g/\$72.00		
CH ₃ CH ₃	SII6457.0 ISOOCTYLTRICHLOROSILANE <i>1-TRICHLOROSILYL-2,4,4-TRIMETHYLPENTANE</i> C ₈ H ₁₇ Cl ₃ Si	247.67 flashpoint	117°/50 : 85°C (185°F)	1.0684	1.4510
$CH_3CCH_2CHCH_2SiCl_3$ CH_3	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18379-25-4] TSCA HMIS: 3-2-1-X	e, water, protic : 25g/\$22.00		100g/\$7	2.00
CH ₃ CH ₃ CH ₃ CH ₃ CH ₃ CCH ₂ CHCH ₂ Si(OCH ₃) ₃	SII6458.0 ISOOCTYLTRIMETHOXYSILANE C ₁₁ H ₂₆ O ₃ Si viscosity: 2 cSt.	autoignitio	90°/10 52°C (126°F) n temp.: 310°	0.887	1.4176
CH ₃	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [34396-03-7] TSCA HMIS: 3-2-1-X	ater/moisture 25g/\$12.00	100g/\$39.00	2kg/\$19	0.00

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	name	MW	bp/mm (mp)	D420	n _D ²⁰
$H_{3}C$ CH_{3} CHSi - CI	SII6462.0 ISOPROPYLDIMETHYLCHLOROSILANE C ₅ H ₁₃ CISi see also SID4065.0		114° : 15°C (59°F)	0.873	1.4138
H ₃ C CH ₃	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [3634-56-8] HMIS: 3-4-1-X	e, water, protic 25g/\$48.00		100g/\$1	56.00
CH ₃ O — CH ₂ CH ₂ CH ₂ CH ₂ CH ₂ Si – CH ₃	SIM6492.4 3-(p-METHOXYPHENYL)PROPYLMETHYL- DICHLOROSILANE C ₁₁ H ₁₆ Cl ₂ OSi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture HMIS: 3-1-1-X store <5°	-	115-6°/0.3 : >110°C (>230°F solvents 25g/\$68.00	1.13)	
CH ₃ O-CH ₂ CH ₂ CH ₂ CH ₂ Si -Cl	SIM6492.5 3-(p-METHOXYPHENYL)PROPYLTRICHLORO- SILANE C ₁₀ H ₁₃ Cl ₃ OSi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [163155-57-5] HMIS: 3-1-1-X		128-9°/1 : >110°C (>230°F solvents 25g/\$68.00	1.226)	
CH ₃ O H ₂ C CH O	SIM6492.8 (1-METHOXY-2-PROPOXY)TRIMETHYLSILANE C ₇ H ₁₈ O ₂ Si		132° (-40°)mp : 20°C (68°F)	0.83	1.3965
H ₃ C – Si – CH ₃ CH ₃	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [55816-62-1] HMIS: 3-2-1-X	viscosity: 2 ater/moisture	2 cSt 25g/\$64.00		
H ₃ C — CH ₂ CH ₂ Cl	SIM6511.0 (p-METHYLPHENETHYL)METHYLDICHLORO- SILANE, 95% (p-TOLYLETHYL)METHYLDICHLOROSILANE $C_{10}H_{14}Cl_2Si \alpha: \beta \sim 40:60$ HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/m		103-5°/2 : 95°C (203°F)	1.1	1.5100 ²⁵
CH ₃ CH ₂ CH ₂ CH ₃ Cl		233.21 oisture 25g/\$45.00	50g/\$88.00	1.1165 100g/\$1	1.5152
$\begin{array}{c} O\\ O\\ O\\ O\\ O\\ CH_3 O\\ CH_3 - Si - O - CCH_3\\ O\\ O\\ CCH_3 \end{array}$	SIM6519.0 METHYLTRIACETOXYSILANE, 95% C ₇ H ₁₂ O ₆ Si vapor pressure, 94°: 9mm most common crosslinker for condensation cu HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w	220.25 flashpoint: re silicone ater/moisture	87-8°/3 (40°)mp : 85°C (185°F) RTV's	1.175	1.4083
0	[4253-34-3] TSCA HMIS: 3-2-1-X SIM6520.0	50g/\$19.00) 2kg/\$280.00	18kg/\$5	76.00
	METHYLTRICHLOROSILANE CH ₃ Cl ₃ Si vapor pressure, 13.5°: 100mm ΔHvap: 7.4 kcal/mole viscosity: 0.46 cSt	flashpoint: autoignitio	66.4° (-78°)mp - ihl rat,LDLo: 45 -15°C (5°F) on temperature: 39	0ppm/4H	1.4110
	critical pressure: 39 atm specific heat: 0.22 cal/g/° coefficient of thermal expansion: 1.3 x 10 ⁻³ HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/m [75-79-6] TSCA HMIS: 3-4-2-X	ionization surface te oisture	nperature: 243°C potential: 11.36 e nsion: 20.3 dynes 0 500g/\$26.00 201 *zDR-S-0	/cm <g \$480.0<="" th=""><th>0*+ container S-019 required</th></g>	0*+ container S-019 required
H ₃ C Cl Si Cl	SIM6520.1 METHYLTRICHLOROSILANE, 99% CH ₃ Cl ₃ Si in combination w/H ₂ forms SiC by CVD ¹ . 1. A. Josiek et al, Chem. Vap. Dep., 2, 17, 1996	149.48	66.4° (-78°)mp	1.275	1.4110
	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/m [75-79-6] TSCA HMIS: 3-4-2-X	oisture 25g/\$36.00)	500g/\$2	52.00

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
H_3C , OC_2H_5 C_2H_5O , OC_2H_5	SIM6555.0 METHYLTRIETHOXYSILANE C ₇ H ₁₈ O ₃ Si vapor pressure, 25°: 6mm dipole moment: 1.72 debye viscosity: 0.6 cSt HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [2031-67-6] TSCA HMIS: 1-3-1-X	flashpoint: 3 autoignition ∆Hcomb: 1 ater/moisture	142° oral rat, LD50: 12, 30°C (86°F) temperature: 225 831 kcal/mole 2.0kg/\$100.00	°C (437°	g =)
H ₃ C, OCH ₃ CH ₃ O, OCH ₃	SIM6560.0 METHYLTRIMETHOXYSILANE C ₄ H ₁₂ O ₃ Si viscosity: 0.50 cSt dipole moment: 1.60 debye intermediate for coating resins HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w. [1185-55-3] TSCA HMIS: 3-4-1-X	136.22 TOXICITY- flashpoint: δ autoignition ΔHcomb: 1 ater/moisture	102-3° (-78°)mp oral rat, LD50: 12,	0.955 500mg/k	1.3696 g
H ₃ C OCH ₃ Si OCH ₃	SIM6560.1 METHYLTRIMETHOXYSILANE, 99+% C ₄ H ₁₂ O ₃ Si viscosity: 0.50 cSt dipole moment: 1.60 debye intermediate for coating resins [1185-55-3] TSCA HMIS: 3-4-1-X	flashpoint: 8 autoignition	102-3° (-78°)mp oral rat, LD50: 12, 3°C(46°F) temperature: 255 142 kcal/mole 100g/\$91.00	500mg/k	1.3696 g
OCH ₂ CH ₂ CH ₃ H ₃ C-Si-OCH ₂ CH ₂ CH ₂ CH ₃ OCH ₂ CH ₂ CH ₃	SIM6579.0 METHYLTRI-n-PROPOXYSILANE C ₁₀ H ₂₄ O ₃ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w. [5581-66-8] TSCA HMIS: 2-2-1-X		83-4°/13 50°C (130°F) 25g/\$51.00	0.878	1.4085
OCH ₂ CH ₂ OCH ₃ H ₃ C-Si-OCH ₂ CH ₂ OCH ₃ OCH ₂ CH ₂ OCH ₃	SIM6585.0 METHYLTRIS(METHOXYETHOXY)SILANE C ₁₀ H ₂₄ O ₆ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [17980-64-2] TSCA HMIS: 3-1-0-X	268.38 ater/moisture	145°/15 25g/\$34.00	1.045	1.4178
$\begin{pmatrix} H_{3}C \\ CH_{3}CH_{2} \end{pmatrix} C = N - O - Si - CH_{3}$	SIM6590.0 METHYLTRIS(METHYLETHYLKETOXIME)- SILANE, 95% <i>METHYLTRIS(2-BUTANONEOXIME)SILAN</i> C ₁₃ H ₂₇ N ₃ O ₃ Si neutral crosslinker for condensation cure silicone HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [22984-54-9] TSCA HMIS: 2-2-1-X	TOXICITY- flashpoint: S es	110-1°/2 (-22°)mp oral rat, LD50: 200 90°C (194°F) 0		
CH ₂ SiCl ₃	SIN6596.0 (1-NAPTHYLMETHYL)TRICHLOROSILANE C ₁₁ H ₉ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [17998-59-3] HMIS: 3-2-1-X	275.64	150-1°/7	1.3112	
Si(OCH ₃) ₃	SIN6597.0 1-NAPTHYLTRIMETHOXYSILANE C ₁₃ H ₁₆ O ₃ Si employed in high refractive index surface modific HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with w [18052-76-1] HMIS: 3-2-1-X	248.35 cation ater/moisture	150°/2 (33-5°)mp 5.0g/\$180.00		1.5562
$CF_{3}CF_{2}CF_{2}CF_{2}CH_{2}CH_{2}SH - CH_{3}$	SIN6597.3 NONAFLUOROHEXYLDIMETHYLCHLORO- SILANE $C_8H_{10}CIF_9Si$ HMIS: 3-3-1-X	340.69	162-4° 10g/\$45.00	1.3422	
$CF_{3}CF_{2}CF_{2}CF_{2}CF_{2}CH_{2}CH_{2}Si -Cl$	SIN6597.6 NONAFLUOROHEXYLTRICHLOROSILANE $C_6H_4Cl_3F_9Si$ [78560-47-1] TSCA HMIS: 3-2-1-X	381.53 10g/\$27.00	70-2°/15	1.542 50g/\$10	8.00

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	name	MW	bp/mm (mp)	D 4 ²⁰	$\mathbf{n}_{\mathrm{D}}^{20}$
OCH ₂ CH ₃ CF ₃ CF ₂ CF ₂ CF ₂ CH ₂ CH ₂ Si -OCH ₂ CH ₃	SIN6597.65 NONAFLUOROHEXYLTRIETHOXYSILANE	410.35			
OCH ₂ CH ₃	C ₁₂ H ₁₉ F ₉ O ₃ Si [102390-98-7] tsca hmis: 2-2-1-x		25g/\$74.00		
$CF_3CF_2CF_2CF_2CH_2CH_2Si - OCH_3$	SIN6597.7 NONAFLUOROHEXYLTRIMETHOXYSILANE $C_9H_{13}F_9O_3Si$ $\gamma c of treated surface: 23 dynes/cm$	368.27	68-9°/15	1.335	1.3376
OCH ₃	[85877-79-8] TSCA HMIS: 3-2-1-X	10g/\$32.0	00	50g/\$12	28.00
CH ₃ (CH ₂) ₈ CH ₃ -OCH ₂ CH ₂ CH ₂ CH ₂ Si -Cl	SIN6598.0 p-NONYLPHENOXYPROPYLDIMETHYL- CHLOROSILANE, 90% C ₂₀ H ₃₅ CIOSi	355.04	181°/0.75	0.963	1.4925
	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistu HMIS: 3-1-1-X	re, water, proti	c solvents 10g/\$95.00		
CH ₃	SIO6615.0 n-OCTADECYLDIMETHYLCHLOROSILANE DIMETHYL-n-OCTADECYLCHLOROSILANE	347.10	159°/0.1 (28-30°)mp	0.85629	1.49982
$CH_{3}(CH_{2})_{16}CH_{2} \xrightarrow{CH_{3}}_{I}CH_{3}$	HYDROLY IIC SENSITIVITY: 8 reacts rapidly with moistu	s" D. Leyder re, water, proti			
CII	[18643-08-8] TSCA HMIS: 3-1-1-X SIO6615.1	25g/\$25.0	0	2kg/\$41	2.00
$CH_3(CH_2)_{16}CH_2 - Si - Cl$	n-OCTADECYLDIMETHYLCHLOROSILANE, 97% DIMETHYL-n-OCTADECYLCHLOROSILANE C ₂₀ H ₄₃ CISi contains 3-6% C ₁₈ isomers	347.10 flashpoint	159°/0.1 (28-30°)mp : 201°C (394°F)	0.95629	1.4998²
CH ₃	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistu [18643-08-8] TSCA HMIS: 3-1-1-X	re, water, proti 25g/\$51.0		100g/\$ ⁻	165.00
$CH_{3}(CH_{2})_{16}CH_{2} \xrightarrow{CH_{3}}{I}CH_{3}$		347.10 flashpoint	159°/0.1 : 5°C (41°F)	0.854	
CH ₃	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistu [18643-08-8] TSCA HMIS: 3-3-1-X	re, water, proti 25g/\$21.0		2kg/\$35	50.00
CH_3 $CH_3(CH_2)_{16}CH_2 -Si - N(CH_3)_2$	SIO6617.0 n-OCTADECYLDIMETHYL(DIMETHYLAMINO)- SILANE contains 5-10% C ₁₈ isomers C ₂₂ H ₄₉ NSi HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with v	355.72	160°/0.1	9.	
ĊH ₃	[76328-77-3] TSCA HMIS: 3-3-1-X	10g/\$42.0		50g/\$16	68.00
$CH_3(CH_2)_{16}CH_2 -Si - OCH_3$	SIO6618.0 n-OCTADECYLDIMETHYLMETHOXYSILANE C ₂₁ H ₄₆ OSi contains 5-10% C ₁₈ isomers employed in SAM resist ¹ . 1. T. Oh et al, Mol. Cryst. Liq. Cryst. Sci. A, <i>337</i> ,	342.68 7. 1999.	184-6°/0.2	0.8325	1.444
CH ₃	HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with v [71808-65-6] TSCA HMIS: 2-1-0-X		0	100g/\$1	169.00
	SIO6624.0 n-OCTADECYLMETHOXYDICHLORO- SILANE, 95% $C_{19}H_{40}Cl_2OSi$	383.51	144-7°/1.5	0.9425	1.452
$CH_3(CH_2)_{16}CH_2 = Si - OCH_3$	maintains reactivity of octadecyltrichlorosilane, I HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistu			t	
	HMIS: 3-1-1-X	25g/\$39.0		100g/\$1	127.00
$CH_3(CH_2)_{16}CH_2 - Si - CH_3$	SIO6625.0 n-OCTADECYLMETHYLDICHLOROSILANE $C_{19}H_{40}Cl_2Si$ contains 5-10% C_{18} isomers	367.52 flashpoint	185°/2.5 (24-6°)mp : 185°C (365°F)	0.930	
Ċl	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moistu [5157-75-5] TSCA HMIS: 3-1-1-X		c solvents	500g/\$2	262.00
$CH_{3}(CH_{2})_{16}CH_{2} - Si - CH_{3}$ $OC_{2}H_{5}$ $OC_{2}H_{5}$	SIO6627.0 n-OCTADECYLMETHYLDIETHOXYSILANE $C_{23}H_{50}O_2Si$ contains 5-10% C_{18} isomers	386.73 flashpoint	197°/2 : >110°C (>230°F)	0.852	1.4407
	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with v [67859-75-0] TSCA HMIS: 2-1-0-X	water/moisture	25g/\$38.00		

	name	MW k	pp/mm (mp)	D420	n _D ²⁰	
OCH ₃ Harris CH ₂ (CH ₂), CH ₂ -Si - CH ₂	$\begin{array}{llllllllllllllllllllllllllllllllllll$		190°/3 (17-18°)mp 110°C (>230°F)	0.85	1.4427	НҮІ
CH ₃ (CH ₂) ₁₆ CH ₂ -Si-CH ₃ I OCH ₃	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [70851-50-2] TSCA HMIS: 3-1-0-X	autoignition ater/moisture 25g/\$52.00	temp: 225°	100g/\$1	69.00	HYDROPHOBIC
	SIO6640.0 n-OCTADECYLTRICHLOROSILANE, 95% $C_{18}H_{37}CI_3Si$ contains 5-10% C_{18} isomers	387.93 flashpoint: 1	160-2°/3 (22°)mp 89°C (372°F)	0.95022	1.4602	
$CH_{3}(CH_{2})_{16}CH_{2} - Si - Cl$	provides lipidophilic surface coatings employed in patterning and printing of electroact see also SIO6624.0 1. Z. Huan et al, Synth. Met., <i>85</i> , 1375, 1997. 2. N. Jeon et al, Langmuir, <i>13</i> , 3382, 1997. HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [112-04-9] TSCA HMIS: 3-1-1-X	ve molecular	films ^{1,2} .	15kg/\$9	62.00	COMMERCIAL
$CH_{3}(CH_{2})_{16}CH_{2} \xrightarrow{CI}_{I}$	SIO6640.1 n-OCTADECYLTRICHLOROSILANE C ₁₈ H ₃₇ Cl ₃ Si contains <3% C ₁₈ isomers highest concentration of terminal silane substituti HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [112-04-9] TSCA HMIS: 3-1-1-X	387.93 on	160-2°/3 (22°)mp	0.950 ²²	1.4602	-
$CH_{3}(CH_{2})_{16}CH_{2} - Si - OC_{2}H_{5}$ $OC_{2}H_{5}$ $OC_{2}H_{5}$	SIO6642.0 n-OCTADECYLTRIETHOXYSILANE, 95% C ₂₄ H ₅₂ O ₃ Si contains 5-10% C ₁₈ isomers forms hydrophobic, oleophilic coatings HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [7399-00-0] HMIS: 2-1-0-X	416.76 flashpoint: >	165-9°/0.2 (10-12°)mp 150°C (>302°F)	0.87 100g/\$9	1.4386	-
$CH_{3}(CH_{2})_{16}CH_{2} \xrightarrow{OCH_{3}}_{I}OCH_{3}$	SIO6645.0 n-OCTADECYLTRIMETHOXYSILANE, 95% C ₂₁ H ₄₆ O ₃ Si contains 5-10% C ₁₈ isomers see also SIH5925.0 forms clear, ordered, films w/ tetramethoxysilane ¹ . 1. A. Shimjima et al, J. Am. Chem. Soc., <i>120</i> , 425 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [3069-42-9] TSCA HMIS: 2-1-1-X	flashpoint: 1 58, 1998.	170°/1 (13-17°)mp oral rat, LD50: >50 40°C (284°F)		-	COMMERCIAL
$\begin{array}{c} H_{3}C \\ H_{3}$	SIO6698.0 OCTAMETHYLCYCLOTETRASILAZANE $C_8H_{28}N_4Si_4$ Δ Hform: 188 kcal/mole forms α -Si ₃ N ₄ by ammonia thermal synthesis ¹ . 1. S. Schaible et al, Applied Organomet. Chem., HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mod [1020-84-4] TSCA HMIS: 2-2-1-X	<i>7</i> , 53, 1993	225° (97°)mp 6°C (150°F)	0.950 ²² 100g/\$8		-
$\begin{array}{c} H_{3}C \\ CH_{3}\\ CH_{3}(CH_{2})_{6}CH_{2} - Si - Cl \\ CH_{3}(CH_{2})_{6}CH_{2} - Si - Cl \\ CH_{3}C \\ H_{3}C \\ CH_{3}\end{array}$	SIO6710.5 n-OCTYLDIISOPROPYLCHLOROSILANE C ₁₄ H ₃₁ CISi reagent for preparation of HPLC stationary phase 1. J. Kirkland et al, J. Chrom. Sci., <i>32</i> , 473, 1994. HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moistu [117559-37-2] HMIS: 3-1-1-X	262.94 flashpoint: > es w/high sta	95-9°/0.5 110°C (>230°F) bility and efficiend 10g/\$58.00	0.875	1.4550	-
$\begin{array}{c} H_{3}C \\ CH_{3}CH$	SIO6710.7 n-OCTYLDIISOPROPYL(DIMETHYLAMINO)- SILANE C ₁₆ H ₃₇ NSi HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist [151613-25-1] TSCA HMIS: 3-2-1-X	271.57 ure	105°/0.7 25g/\$250.00	0.833	1.4560	_

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	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
$CH_{3}(CH_{2})_{6}CH_{2} \xrightarrow{CH_{3}}_{i} -CI$	SIO6711.0 n-OCTYLDIMETHYLCHLOROSILANE C ₁₀ H ₂₃ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, w [18162-84-0] TSCA HMIS: 3-1-1-X			0.794 100g/\$9	14328 ²⁵ 11.00
$CH_{3}(CH_{2})_{6}CH_{2} - Si - OCH_{3}$ $CH_{3}(CH_{2})_{6}CH_{2} - Si - OCH_{3}$	SIO6711.1 OCTYLDIMETHYLMETHOXYSILANE C ₁₁ H ₂₆ OSi [93804-29-6] HMIS: 3-2-1-X	202.42	221-223° 82°C(181°F) 25g/\$84.00	0.813	1.4230
$CH_{3}(CH_{2})_{6}CH_{2} \xrightarrow[]{CH_{3}}{}^{CH_{3}}_{CH_{3}}O(CH_{3})_{2}$	SIO6711.3 n-OCTYLDIMETHYL(DIMETHYLAMINO)SILANE C ₁₂ H ₂₉ NSi HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist [2530-86-1] HMIS: 3-2-1-X		94-6°/10 69°C (156°F) 25g/\$52.00	0.8025	
CH ₃ (CH ₂) ₆ CH ₂ H ₃ C Si Cl	SIO6712.0 n-OCTYLMETHYLDICHLOROSILANE C ₉ H ₂₀ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [14799-93-0] TSCA HMIS: 3-2-1-X		94°/6 98°C (209°F) rents	0.9761 500g/\$1	
$CH_{3}(CH_{2})_{6}CH_{2}$ $H_{3}C$ $OC_{2}H_{5}$ $OC_{2}H_{5}$	SIO6712.2 n-OCTYLMETHYLDIETHOXYSILANE C ₁₃ H ₃₀ O ₂ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate [2652-38-2] HMIS: 2-2-0-X		80-2°/2 >110°C (>230°F)	0.8478 100g/\$6	
CH ₃ (CH ₂) ₆ CH ₂ , OCH ₃ H ₃ C OCH ₃	SIO6712.4 n-OCTYLMETHYLDIMETHOXYSILANE $C_{11}H_{26}O_2Si$ [85712-15-8] HMIS: 3-2-1-X	218.42	87-9°/5 94°C(201°F)	0.858 100g/\$9	1.4190
$CH_{3}(CH_{2})_{6}CH_{2} - Si - Cl$	SIO6713.0 n-OCTYLTRICHLOROSILANE C ₈ H ₁₇ Cl ₃ Si vapor pressure, 140°: 2mm HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [5283-66-9] TSCA HMIS: 3-1-1-X			1.0744 2.0kg/\$ ⁻	1.4490
$CH_{3}(CH_{2})_{6}CH_{2} - Si - OC_{2}H_{5}$ $OC_{2}H_{5}$	SIO6715.0 n-OCTYLTRIETHOXYSILANE C ₁₄ H ₃₂ O ₃ Si viscosity: 1.9 cSt vapor pressure, 75°: 1mm may be formulated to stable water emulsions ¹ . 1. R. Depasquale et al, US Pat. 4,648,904, 1987 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate [2943-75-1] TSCA HMIS: 2-1-0-X	00	98-9°/2 (<-40°)mp 100°C (212°F) 2.0kg/\$140.00	0.8750 15kg/\$5	
$CH_{3}(CH_{2})_{6}CH_{2} - Si - OCH_{3}$ OCH_{3}	SIO6715.5 n-OCTYLTRIMETHOXYSILANE C ₁₁ H ₂₆ O ₃ Si vapor pressure, 75°: 0.1mm see also- SII6458.0 ISOOCTYLTRIMETHOXYS HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with wate [3069-40-7] TSCA HMIS: 3-2-1-X	SILANE	191-2° 68°C (154°F)	0.907 2.0kg/\$	1.417
$\begin{array}{ccc} O & CH_3 & CH_3 \\ \parallel & & & \\ CH_3C - O - S_i - O - S_i - CH_3 \\ & & & \\ CH_3 & CH_3 \end{array}$	SIP6717.0 1,1,1,3,3-PENTAMETHYL-3-ACETOXY- DISILOXANE C ₇ H ₁₈ O ₃ Si ₂ HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate [70693-47-9] TSCA HMIS: 2-2-1-X		149-50° 40°C (104°F)	0.90 50g/\$14	1.3887 ²⁵
$C_{5}H_{11}S_{1} = C_{1}$	SIP6720.0 PENTYLTRICHLOROSILANE AMYLTRICHLOROSILANE mixed isomers C ₅ H ₁₁ Cl ₃ Si specific heat: 0.35 cal/g/° HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, w [107-72-2] TSCA HMIS: 3-3-1-X	209.59 flashpoint: viscosity:	171-2° 61°C (142°F) I.1 cSt.	1.142	1.4456

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
$\begin{array}{c} OC_2H_5\\ C_5H_{11}Si & -OC_2H_5\\ OC_2H_5 \end{array}$	SIP6720.2 PENTYLTRIETHOXYSILANE <i>AMYLTRIETHOXYSILANE</i> mixed isomers C ₁₁ H ₂₆ O ₃ Si HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with wat	viscosity:	95-6°/1.3 : 68°C (154°F) 2.1 cSt	0.895	1.4059
$OC_2\Pi_5$	[2761-24-2] TSCA HMIS: 2-2-1-X	cirmoisture	25g/\$55.00		
$CF_{3}(CF_{2})_{11}CH_{2}CH_{2} - Si - OC_{2}H_{5}$	SIP6720.5 PERFLUORODODECYL-1H,1H,2H,2H-TRIETHOXY- SILANE -PERFLUOROTETRADECYL-1H,1H,2H,2H- TRIETHOXYSILANE MIXTURE, 80% (contains for the preparation of low surface energy substra HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wat HMIS: 2-1-1-X	ates	157-198°/1.5 (70-85°)mp 841.2, balance hig 5.0g/\$127.00	her homo	logs)
C ₈ F ₁₇ SiCl ₃	SIP6720.7 PERFLUOROOCTYLPHENYLTRICHLOROSILANE C ₁₄ H ₄ Cl ₃ F ₁₇ Si contact angle treated glass surface, water: 115°.1 1. Y. Kondo, J. Oleoscience, <i>53</i> , 143, 2004 [753025-21-7] HMIS: 3-1-1-X		67-9°/3 stable to >300° 1.0g/\$232.00		1
$CH_2 iC_3H_7 CH_2-Si-Cl iC_3H_7$	SIP6720.8 PHENETHYLDIISOPROPYLCHLOROSILANE, C_8H_{22} CISi contains α , β -isomers [151613-24-4] TSCA HMIS: 3-2-1-X	254.87	105-9°/0.3 5.0g/\$120.00	0.97	
$\bigcup_{\substack{CH_2\\CH_2-CH_2-Si-Cl}}^{IC_3II7}$	SIP6721.0 PHENETHYLDIMETHYLCHLOROSILANE C ₁₀ H ₁₅ CISi contains α,β-isomers see also SIP6724.7 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, [17146-08-6] TSCA HMIS: 3-2-1-X		56°/0.2 : 70°C (158°F) /vents 50g/\$170.00	0.999	1.5185
CH ₃ CH ₂ CH ₂ CH ₃ CH ₃ CH ₃	SIP6721.2 PHENETHYLDIMETHYL(DIMETHYLAMINO)- SILANE contains α ,β-isomers C ₁₂ H ₂₁ NSi HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mois	207.39	109°/2	0.890	4
CH ₃	[181231-68-5] TSCA-L HMIS: 3-2-1-X		10g/\$117.00		
CH ₂ Cl CH ₂ -Si - CH ₃	$\label{eq:sigma} \begin{array}{l} SIP6721.5 \\ PHENETHYLMETHYLDICHLOROSILANE \\ \hline \textit{METHYL(PHENETHYL)DICHLOROSILANE} \\ \hline C_9H_{12}Cl_2Si contains \ \alpha,\beta\mbox{-isomers} \\ \hline HYDROLYTIC SENSITIVITY: 8 \ reacts rapidly with moisture, \end{array}$	water, protic sc	99°/6 : 80°C (176°F) Ivents	09	1.5120
à à	[17146-08-6] TSCA HMIS: 3-2-1-X	25g/\$38.0	0	100g/\$ ⁻	124.00
	SIP6722.0 PHENETHYLTRICHLOROSILANE $C_8H_9Cl_3Si$ contains α,β -isomers	flashpoint	93-6°/3 - oral rat, LD50: 28 : 91°C (196°F)	1.240 330mg/kg	1.5185
CH_2 - $\dot{S}i$ -Cl	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, [940-41-0] TSCA HMIS: 3-1-1-X	25g/\$25.0		100g/\$8	32.00
Сң ₂ осн ₃	SIP6722.6 PHENETHYLTRIMETHOXYSILANE C ₁₁ H ₁₈ O ₃ Si contains α,β-isomers HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wat		95-6°/2 : 109°C (228°F)	1.037	1.4753
CH ₂ -Si-OCH ₃ OCH ₃	[49539-88-0] TSCA HMIS: 3-1-1-X	25g/\$28.0	0 100g/\$91.00	2kg/\$42	20.00
O O CH ₃ Si-Cl CH ₃	SIP6723.0 m-PHENOXYPHENYLDIMETHYLCHLORO- SILANE, 95% contains other isomers C ₁₄ H ₁₅ CIOSi end-capper for low-temperature lubricating fluids 1. M. Gardos, ASLE Transactions, <i>18</i> , 31, 1972 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, HMIS: 3-2-1-X		102-6°/1 Ivents 5.0g/\$94.00	1.11 ²⁵	1.560325
O-CH ₂ CH ₂ CH ₂ Si -Cl	SIP6723.2 3-PHENOXYPROPYLDIMETHYLCHLOROSILANE C ₁₁ H ₁₇ CIOSi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture,				100.05
CH ₃	[69733-73-9] HMIS: 3-2-1-X	25g/\$42.0	U	100g/\$ ⁻	138.00

	name	MW k	pp/mm (mp)	D 4 ²⁰	n _D ²⁰
O-CH ₂ CH ₂ CH ₂ Si -CH ₃	$\begin{array}{l} SIP6723.25\\ 3\text{-PHENOXYPROPYLMETHYLDICHLOROSILANE}\\ C_{10}H_{14}OCl_2Si\\ [28229-56-3] \text{HMIS: 3-2-1-X} \end{array}$	249.21	110°/1 25g/\$84.00		
O-CH ₂ CH ₂ CH ₂ CH ₂ Si -Cl	SIP6723.3 3-PHENOXYPROPYLTRICHLOROSILANE C ₉ H ₁₁ Cl ₃ OSi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [60333-76-8] HMIS: 3-2-1-X		40°/0.02 110°C (>230°F) ents	1.2574 100g/\$1	
$ \bigcirc -O - (CH_2)_{10}CH_2S_1 - Cl \\ Cl \\ Cl \\ Cl \\ \\ \\ Cl \\ \\ \\ \\$	SIP6723.4 11-PHENOXYUNDECYLTRICHLOROSILANE C ₁₇ H ₂₇ Cl ₃ OSi forms SAMs that orient pentacene [526204-46-6] HMIS: 3-1-1-X	381.85	5.0g/\$210.00		
$(CH_2)_4Si - Cl$	SIP6724.7 4-PHENYLBUTYLDIMETHYLCHLOROSILANE C ₁₂ H ₁₉ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v HMIS: 3-2-1-X		85-7°/0.6 110°C (>230°F) nts 25g/\$110.00	0.964	1.4979 ²⁵
$(CH_2)_4 \overset{Cl}{\underset{Cl}{\overset{I}{\overset{I}{\overset{I}{\overset{I}{\overset{I}{\overset{I}{\overset{I}{$	SIP6724.8 4-PHENYLBUTYLMETHYLDICHLOROSILANE C ₁₁ H ₁₆ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v HMIS: 3-2-1-X		105-9°/1.5 110°C (>230°F) nts 25g/\$110.00	1.0925	
$ \begin{array}{c} Cl \\ CH_2CH_2CH_2CH_2 - Si - Cl \\ Cl \\ Cl \end{array} $	SIP6724.9 4-PHENYLBUTYLTRICHLOROSILANE C ₁₀ H ₁₃ Cl ₃ Si employed in bonded phases for HPLC HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [17886-88-3] TSCA HMIS: 3-2-1-X		82°/0.4 •110°C (>230°F) •nts 25g/\$110.00	1.192	1.5121
$\overbrace{CH_3}^{CH_3} \underset{CH_3}{\overset{H}{\longrightarrow}}$	SIP6726.0 PHENYLDIMETHYLACETOXYSILANE C ₁₀ H ₁₄ O ₂ Si HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with water [17887-60-4] TSCA HMIS: 2-2-1-X		127-9°/44 '2°C (162°F) 25g/\$68.00	1.006	1.4907
CH ₃ -Si-Cl CH ₃	SIP6728.0 PHENYLDIMETHYLCHLOROSILANE C ₈ H ₁₁ CISi vapor pressure, 25°: 1 mm viscosity: 1.4 cSt HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v	flashpoint: 6 ∆Hvap: 11.4		1.032	1.5082
$\overbrace{CH_3}^{CH_3}_{i-OC_2H_5}$	[768-33-2] TSCA HMIS: 3-2-1-X SIP6728.4 PHENYLDIMETHYLETHOXYSILANE C ₁₀ H ₁₆ OSi viscosity: 1.3 cSt dipole moment: 1.34 HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with wate	180.32 TOXICITY- of flashpoint: 6	100g/\$84.00 93°/25 pral rat, LD50: 24(11°C (141°F)		1. 4799
	[1825-58-7] TSCA HMIS:2-2-0-X	10g/\$20.00		50g/\$80	.00
Cl C2H5 Cl	SIP6730.0 PHENYLETHYLDICHLOROSILANE C ₈ H ₁₀ Cl ₂ Si ΔHvap: 11.9 kcal/mole HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [1125-27-5] TSCA HMIS: 3-2-1-X	205.16 flashpoint: 9 vapor press vater, protic solve	ure, 100°: 13mm	1.184	1.5321
CH ₂	SIP6736.4 6-PHENYLHEXYLTRICHLOROSILANE $C_{12}H_{17}Cl_3Si$ [18035-33-1] HMIS: 3-1-1-X	295.71	95°/0.1 5.0g/\$96.00		1.505225

	name	MW k	p/mm (mp)	D4 ²⁰	n _D ²⁰	
Si N(CH ₃) ₂	SIP6736.8 PHENYLMETHYLBIS(DIMETHYLAMINO)SILANE C ₁₁ H ₂₀ N ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [33567-83-8] HMIS: 3-2-1-X	208.38 flashpoint: 7 water, protic solve			1.4982	;
CH_3' N(CH ₃) ₂			109/\$50.00			- 1
	SIP6738.0 PHENYLMETHYLDICHLOROSILANE $C_7H_8Cl_2Si$ vapor pressure:, 82.5°: 13mm Δ Hvap: 11.5 kcal/mole	191.13 TOXICITY- i flashpoint: 8	205-6° (-53°)mp pr mus, LD50: 30(2°C (180°F)	1.187 Omg/kg	1.5180	
CH ₃ Cl	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [149-74-6] TSCA HMIS: 3-2-1-X			500g/\$6	4 00	ē
$\langle \bigcirc \rangle$		209/012.00		300g/#0	4.00	-
CH CH CH CH CH CH	SIP6738.5 1-PHENYL-1-(METHYLDICHLOROSILYL)BUTANE C ₁₁ H ₁₆ Cl ₂ Si HMIS: 3-2-1-X	247.24 flashpoint: >	87-9°/1 110°C(>230°F) 25g/\$120.00	1.10	1.5120	
ĊH ₃	SIP6739.0 PHENYLMETHYLDIETHOXYSILANE $C_{11}H_{18}O_2Si$ dipole moment: 1.32	210.35 flashpoint: 8	117-8°/31 9°C (192°F)	0.963	1.4690	-
CH ₃ OC ₂ H ₅	HYDROLYTIC SENSITIVITY: 7 SI-OR reacts slowly with wate [775-56-4] TSCA HMIS: 2-2-1-X	er/moisture 25g/\$23.00		100g/\$7	8.00	
Si OCH3	SIP6740.0 PHENYLMETHYLDIMETHOXYSILANE C ₉ H ₁₄ O ₂ Si viscosity, 20°: 1.65 cSt HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate	flashpoint: 7	199-200° oral rat, LD50: 892 6°C (168°F)	0.9934 2 mg/kg	1.4694	-
CH ₃ OCH ₃	[3027-21-2] TSCA HMIS: 3-2-1-X	25g/\$15.00		250g/\$1	05.00	
CH ₂ CH ₂ CH ₂ Si -Cl CH ₃ CH ₂ CH ₂ CH ₂ Si -Cl CH ₃	SIP6743.0 (3-PHENYLPROPYL)DIMETHYLCHLOROSILANE C ₁₁ H ₁₇ CISi see also SIP6724.7 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [17146-09-7] TSCA HMIS: 3-1-1-X		75°/0.5 03°C (216°F) ^{nts}	0.963 50g/\$11	9.00	-
CH ₂ CH ₂ CH ₂ Si -CH ₃	SIP6744.0 (3-PHENYLPROPYL)METHYLDICHLOROSILANE C ₁₀ H ₁₄ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, w [17776-66-8] HMIS: 3-2-1-X	233.21 water, protic solve	96-8°/4 ^{nts} 25g/\$87.00	1.08625	1.509025	-
Si - O-CCH ₃ O OCCH ₃ O	SIP6790.0 PHENYLTRIACETOXYSILANE $C_{12}H_{14}O_6Si$ HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with water	•	158°/30 02°C (216°F)	1.194 100g/\$2	1.4708	-
Ö	[18042-54-1] TSCA HMIS: 3-2-1-X	259/904.00		100y/şz	08.00	
\square	SIP6810.0 PHENYLTRICHLOROSILANE C ₆ H ₅ Cl ₃ Si	211.55	201° (-33°)mp	1.324	1.5247	G
	 ΔHvap: 11.4 kcal/mole vapor pressure, 75°: 10mm surface tension: 27.9 dynes/cm specific heat: 0.24 cal/g/° coefficient of thermal expansion: 1.2 x 10⁻³ HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, x [98-13-5] TSCA HMIS: 3-2-1-X 	flashpoint: 9 viscosity: 1.0 dipole mom critical temp water, protic solve	oral rat, LD50: 234 1°C (195°F) 08 cSt ent: 2.41 erature: 438°	18kg/\$5	76.00	COMMERCIAL
CH = CH = CH = CH	SIP6813.0 1-PHENYL-1-TRICHLOROSILYLBUTANE C ₁₀ H ₁₃ CI ₃ Si HMIS: 3-2-1-X	267.65 flashpoint: >	78-80°/0.8 110°C(>230°F) 10g/\$110.00	1.201	1.5180	-

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	name	MW b	op/mm (mp)	D4 ²⁰	n _D ²⁰
C ₂ H ₅ OC ₂ H ₅ C ₂ H ₅ OC ₂ H ₅	SIP6821.0 PHENYLTRIETHOXYSILANE C ₁₂ H ₂₀ O ₃ Si vapor pressure, 75°: 1mm coefficient of thermal expansion: 0.9 x 10 ³ dipole moment: 1.85 debye viscosity, 25°: 1.7 cSt improves photoresist adhesion to silicon nitride effective treatment for organic-grafted clays ¹ . 1. K. Canrado et al, Chem. Mater. <i>13</i> , 3766, 2001 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate [780-69-8] TSCA HMIS: 2-1-1-X	flashpoint: 9 surface tens dielectric co	112-3°/10 oral rat, LD50: 28 96°C (205°F) sion 28 dynes/cm onstant: 4.12		1.4718
E CH ₃ O ^{Si} OCH ₃	SIP6822.0 PHENYLTRIMETHOXYSILANE C ₉ H ₁₄ O ₃ Si viscosity, 25°: 2.1 cSt vapor pressure, 108°: 20mm dipole moment: 1.77 intermediate for silicone resin coatings HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate [2996-92-1] TSCA HMIS: 3-2-1-X	flashpoint: 8 dielectric co			1.4734
$\begin{pmatrix} H_{3}C \\ CH_{3}CH_{2} \end{pmatrix} C = N - O \\ 3 \end{bmatrix} Si - \sum_{3} $	SIP6826.5 PHENYLTRIS(METHYLETHYLKETOXIMINO)- SILANE, 95% C ₁₈ H ₂₉ N ₃ O ₃ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate [34036-80-1] TSCA HMIS: 3-2-1-X		60-5°/3 ⋅61°C (>142°F)	0.995 250g/\$6	8.00
$CH_{3}CH_{2}CH_{2} - Si - Cl$ $CH_{3}CH_{2}CH_{2} - Si - Cl$ $CH_{3}CH$	SIP6910.0 n-PROPYLDIMETHYLCHLOROSILANE C ₅ H ₁₃ CISi HYDROLYTIC SENSITIVITY: 8 Si-CI reacts rapidly with water, [17477-29-1] TSCA HMIS: 3-4-1-X	136.70 flashpoint: 1 /moisture 25g/\$49.00	113-4° 0°C (50°F)	0.8726 100g/\$1	
$CH_{3}CH_{2}CH_{2}-Si - OCH_{3}$	SIP6911.0 PROPYLDIMETHYLMETHOXYSILANE C ₆ H ₁₆ OSi [18182-14-4] HMIS: 3-3-1-X	132.28	94-6° 10g/\$82.00	0.787	1.392725
$CH_{3}CH_{2}CH_{2} - Si - CH_{3}$	SIP6912.0 n-PROPYLMETHYLDICHLOROSILANE C ₄ H ₁₀ Cl ₂ Si viscosity, 20°: 0.8 cSt. HYDROLYTIC SENSITIVITY: 8 Si-CI reacts rapidly with water [4518-94-9] TSCA HMIS: 3-3-1-X	157.11 flashpoint: 2 /moisture 25g/\$38.00	125° 27°C (81°F)	1.027 100g/\$1	1.425 24.00
$CH_3CH_2CH_2 - Si - CH_3$ OCH ₃	SIP6914.0 PROPYLMETHYLDIMETHOXYSILANE $C_6H_{16}O_2Si$ [18173-73-4] HMIS: 3-3-1-X	148.28	126° 25g/\$86.00	0.8689	1.3931
$CH_{3}CH_{2}CH_{2} - Si - Cl$	SIP6915.0 n-PROPYLTRICHLOROSILANE C ₃ H ₇ Cl ₃ Si vapor pressure, 16°: 10mm HYDROLYTIC SENSITIVITY: 8 Si-CI reacts rapidly with water, [141-57-1] TSCA HMIS: 3-3-1-X	177.53 flashpoint: 3 ∆Hvap: 8.7 /moisture 25g/\$13.00		1.185 2.5kg/\$2	1.4290
	SIP6917.0 n-PROPYLTRIETHOXYSILANE C ₉ H ₂₂ O ₃ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate [2550-02-9] TSCA HMIS: 2-3-1-X	206.36 flashpoint: 5	179-80° 57°C (135°F)	0.8916 2.0kg/\$1	1.3956
CH ₃ CH ₂ CH ₂ -Si-OCH ₃ OCH ₃ OCH ₃	$\begin{array}{l} \text{SIP6918.0} \\ \text{n-PROPYLTRIMETHOXYSILANE} \\ \text{C}_{6}\text{H}_{16}\text{O}_{3}\text{Si} \\ _{7}\text{c of treated surface: 28.5 dynes/cm} \\ \text{utilized in architectural hydrophobic coatings} \\ \text{HVDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate} \\ \text{[1067-25-0] TSCA HMIS: 3-3-1-X} \end{array}$	flashpoint: 3		0.932 ²⁵ 20mg/kg 16kg/\$3	

	name	MW b	p/mm (mp)	D 4 ²⁰	n _D ²⁰
O (CH ₃ (CH ₂) ₁₇ Si O O	 SIS6952.0 SILICLAD® OCTADECYL FUNCTIONAL SILANE 20% in t-AMYL ALCOHOL and DIACETONE A γc of treated glass surface: 31 dynes/cm coefficient of friction of treated glass surface: 0.2 surface resistivity of treated surface: 1.2 x 10¹³ of reduces blood protein adsorption¹. hydrophobic, anti-stiction coating for silicon subs 1. B. Arkles et al, in "Silanes Surfaces & Interface 2. A. Almanza-Workman et al, J. Electro Chem. S for application information see Performance Prodi HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate [39443-39-5] TSCA HMIS: 2-3-1-X 	2-0.3 hms trates ² . es" D. Leyden oc. <i>149</i> , H6, 20 ucts Brochure er/moisture	amber liquid ed. Gordon & Br		EnciAL
ОН	SIS6984.0 SODIUM METHYLSILICONATE, 30% in water	116.12		1.24	1
$H_{3}C - s_{i}O^{T}Na^{+}$	CH ₅ NaO ₃ Si	pH: 13.0 viscosity: 10	cSt.		
ОН	[16589-43-8] TSCA HMIS: 3-0-0-X		2.0kg/\$50.00	20kg/\$4	20.00
CH ₃ (CH ₂) ₁₃ SiCl ₃	SIT7093.0 TETRADECYLTRICHLOROSILANE C ₁₄ H ₂₉ Cl ₃ Si [18402-22-7] TSCA HMIS: 3-1-1-X	331.83	155-6°/3 25g/\$80.00		1.4575
$\begin{array}{c} OC_2H_5 OC_2H_5 \\ H_3C-Si-O-Si-CH_3 \\ OC_2H_5 OC_2H_5 \end{array}$	$\begin{array}{l} SIT7095.0\\ 1,1,3,3\text{-}TETRAETHOXY-1,3\text{-}DIMETHYL-\\ DISILOXANE, 95\%\\ C_{10}H_{26}O_5Si_2\\ \text{HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate}\\ [18001-60-0] \hspace{0.1cm} \text{HMIS: 3-3-1-X} \end{array}$	282.48 flashpoint: 58 er/moisture	205° 3°C (136°F) 25g/\$57.00	0.953	1.3912
$\begin{array}{ccc} CH_3 & CH_3 \\ I & I \\ C_2H_5O - Si - O - Si - OC_2H_5 \\ I & I \\ CH_3 & CH_3 \end{array}$	SIT7534.0 1,1,3,3-TETRAMETHYL-1,3-DIETHOXYDISILOXANE C ₈ H ₂₂ O ₃ Si ₂ viscosity: 1.0 cSt HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wate [18420-09-2] TSCA HMIS: 2-2-0-X	222.43 flashpoint: 38 pr/moisture 25g/\$28.00	161° (-134°)mp 3°C (100°F)	0.879 100g/\$9	1.3880
$ \bigcirc_{H_{3}C} + \bigvee_{H_{3}C} + \bigvee_$	SIT7753.0 1,1,3,3-TETRAPHENYLDIMETHYLDISILAZANE C ₂₆ H ₂₇ NSi ₂ deactivates glass capillary columns by persilylati 1. K. Grob et al, High Resol. Chrom. & Col Chron	ion¹. m., <i>3</i> , 197, 198	218-220°/1.5 (91°)mp 110°C (>230°F) 30.	99	7
	HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mois [7453-26-1] TSCA-L HMIS: 2-1-0-X	ture 5.0g/\$25.00		25g/\$10	2.00
$\begin{array}{c} H_{3}C \\ H_{3}$	SIT7906.0 THEXYLDIMETHYLCHLOROSILANE <i>t-HEXYLDIMETHYLCHLOROSILANE</i> C ₈ H ₁₉ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, w		· /	0.911	1.4490
	[67373-56-2] HMIS: 3-2-1-X	5.0g/\$16.00		25g/\$64	.00
$\begin{array}{c} H_{3}C \\ CHC \\ H_{3}C \\ H_{3}C \\ CH_{3}C \\ H_{3}C \\ CH_{3}C \\ CH_{3}C$	SIT7906.6 THEXYLTRICHLOROSILANE C ₆ H ₁₃ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [18151-53-6] HMIS: 3-3-1-X	219.61 vater, protic solver	70-2°/15 nts, protic solvents 10g/\$101.00		
H ₃ C - CH ₃ Si-Cl CH ₃	SIT8030.0 p-TOLYLDIMETHYLCHLOROSILANE C ₉ H ₁₃ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, w [35239-30-6] TSCA HMIS: 3-2-1-X	184.74 flashpoint: 67 vater, protic solver		1.00725	1.5055
H ₃ C-Cl Cl	SIT8035.0 p-TOLYLMETHYLDICHLOROSILANE C ₈ H ₁₀ Cl ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [25898-37-7] TSCA HMIS: 3-2-1-X	205.16 flashpoint: 8(vater, protic solver	· · ·	1.1609	1.5330

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	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
H ₃ C-Cl Si-Cl	SIT8040.0 p-TOLYLTRICHLOROSILANE C ₇ H ₇ Cl ₃ Si γc of treated surface: 34 dynes/cm HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v	-	218-20° 92°C (197°F)	1.28	1.522425
Cl	[701-35-9] TSCA HMIS: 3-2-1-X	25g/\$31.00		100g/\$1	01.00
H ₃ C - CH ₃ Si - OCH ₃ OCH ₃	SIT8042.0 p-TOLYLTRIMETHOXYSILANE C ₁₀ H ₁₆ O ₃ Si γc of treated surface: 34 dynes/cm charge control surface treatment for electrostatic 1. H. Yamazaki, Jpn. Kokai, JP 06027719 A2, 19 HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mois	c copier parti 194.	75-8°/8 94°C (201°C) cles¹.	1.033	1.4726 ²⁵
	[17873-01-7] HMIS: 3-1-1-X	10g/\$38.00)	50g/\$15	52.00
$CH_{3}(CH_{2})_{28}CH_{2} - Si - CI$	SIT8045.0 TRIACONTYLDIMETHYLCHLOROSILANE, blend C ₃₂ H ₆₇ CISi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [70851-52-4] TSCA HMIS: 3-1-0-X			; ₂₂ -C ₂₈ 100g/\$1	69.00
$CH_{3}(CH_{2})_{28}CH_{2} - Si - Cl$	SIT8048.0 TRIACONTYLTRICHLOROSILANE, blend $C_{30}H_{61}CI_3Si$ employed in bonded phases for HPLC of caroter	556.26 80% C ₃₀ a nes	(60-82°)mp and higher, 20% C		
Ċl	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture, v [70851-48-8] TSCA HMIS: 3-1-1-X	water, protic solv 25g/\$52.00		100g/\$1	69.00
	SIT8162.0 13-(TRICHLOROSILYLMETHYL)HEPTACOSANE, 95% 2 <i>-DODECYLHEXADECYLTRICHLOROSILANE</i> C ₂₈ H ₅₇ Cl ₃ Si contains isomers	528.21	215°/0.01 (20-35°)mp	0.946	
a	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [194242-99-4] TSCA-L HMIS: 3-1-1-X	e, water, protic	solvents 10g/\$127.00		
	SIT8162.4 7-(TRICHLOROSILYLMETHYL)PENTADECANE C ₁₆ H ₃₃ Cl ₃ Si 2- <i>HEXYLDECYLTRICHLOROSILANE</i> HMIS: 3-1-1-X	359.88	146-9°/0.2 10g/\$174.00	0.985	
CH ₃ CF ₃ CF ₂ CF ₂ CF ₂ CF ₂ CF ₂ CF ₂ CH ₂ CH ₂ Si - Cl CH ₃	SIT8170.0 (TRIDECAFLUORO-1,1,2,2-TETRAHYDRO- OCTYL)DIMETHYLCHLOROSILANE C ₁₀ H ₁₀ CIF ₁₃ Si <i>PERFLUOROOCTYL-1H,1H,2H,2H-EL</i> employed in column chromatography where low employed in solid phase extraction of fluorous pl modification of layered silicate yields material w/ 1. G. Xindu et al, J. Chromatog, <i>269</i> , 96, 1983. 2. D. Curran, J. Org. Chem. <i>62</i> ,6714, 1997. 3. M. Ogawa et al, Chem. Mater., <i>10</i> , 3787, 1998 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture	DIMETHYLCH protein reter hases ² . film forming 8. e, water, protic	189-91° 52°C (127°F) <i>LOROSILANE</i> ntion is required ¹ . properties ³ .	1.473	1.3453
	[102488-47-1] HMIS: 3-3-1-Х SIT8172.0	10g/\$31.00)	50g/\$12	
$\begin{array}{c} Cl \\ CF_3CF_2CF_2CF_2CF_2CF_2CF_2CH_2CH_2Si - CH_3 \\ Cl \end{array}$	(TRIDECAFLUORO-1,1,2,2-TETRAHYDRO- OCTYL)METHYLDICHLOROSILANE C ₉ H ₇ Cl ₂ F ₁₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture	vapor pres	189-90° 51°C (125°F) sure,76°: 12mm solvents	1.550 ²⁵	1.3500
	[73609-36-6] HMIS: 3-3-1-Х SIT8174.0	10g/\$41.00)	50g/\$16	64.00
Cl I CF ₃ CF ₂ CF ₂ CF ₂ CF ₂ CF ₂ CH ₂ CH ₂ Si – Cl	(TRIDECAFLUORO-1,1,2,2-TETRAHYDRO- OCTYL)TRICHLOROSILANE $C_8H_4Cl_3F_{13}Si$ lowers the coefficient of friction of silicon substra	-	84-5°/17 54°C (129°F)	1.639	1.3521
Cl	1. V. DePalma et al, Langmuir, <i>5</i> , 868, 1989. HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [78560-45-9] TSCA-L HMIS: 3-3-1-X	e, water, protic 10g/\$28.00		50g/\$11	2.00
OC ₂ H ₅ CF ₃ CF ₂ CH ₂ CH ₂ S CF ₃ CF ₂ CF ₂ CF ₂ CF ₂ CF ₂ CF ₂ CH ₂ CH ₂ S	SIT8175.0 (TRIDECAFLUORO-1,1,2,2-TETRAHYDRO- OCTYL)TRIETHOXYSILANE $C_{14}H_{19}F_{13}O_3Si$ viscosity: 3.5 cSt.	∆Hvap: 66	86°/1.5 (<-38°)mp 84°C (183°F) .1 kj/mole	1.351	1.3436
3	HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mois [51851-37-7] TSCA HMIS: 2-2-1-X	ture 10g/\$26.00)	50g/\$10	04.00

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					JCICSI, IIIC
	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
$CF_3CF_2CF_2CF_2CF_2CF_2CF_2CH_2CH_2S_1 \rightarrow OCH_3$	$\begin{array}{l} SIT8176.0 \\ (TRIDECAFLUORO-1,1,2,2-TETRAHYDRO-OCTYL)TRIMETHOXYSILANE \\ C_{11}H_{13}F_{13}O_3Si \\ HYDROLYTIC SENSITIVITY: 7 \ reacts slowly with water/moisture [85857-16-5] \ HMIS: 3-1-1-X \end{array}$	468.29 ^{ure} 10g/\$37.00	60-2°/0.5	1.44 50g/\$14	1.3322
$CF_3CH_2CH_2 - Si - CH_3$	SIT8369.0 (3,3,3-TRIFLUOROPROPYL)METHYL- DICHLOROSILANE C ₄ H ₇ Cl ₂ F ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture	flashpoint: , water, protic		9	1.3850
$CF_3CH_2CH_2 - Si - Cl$	$\begin{tabular}{lllllllllllllllllllllllllllllllllll$, water, protic	113-4° 15°C (59°F) solvents	50g/\$12	1.385
$CI \\ OCH_3 \\ CF_3CH_2CH_2 - Si - OCH_3 \\ OCH_3 \\ OCH_3$	$\begin{tabular}{lllllllllllllllllllllllllllllllllll$	flashpoint:	144° 38°C (100°F) ed surface: 33.5 dyl	50g/\$12 1.137 nes/cm 25g/\$13	1.3546
Cl—Si—CH ₃ Cl—Si—CH ₃ CH ₃	SIT8510.0 TRIMETHYLCHLOROSILANE C_3H_9CISi TMCS vapor pressure, 20°: 190mm; 50°: 591 mm Δ Hvap: 6.6 kcal/mole most economical and broadly used silylation reas	flashpoint: autoignitio gent	57.6° (-57.7°)mp ihl mus, LDLo: 500 -27°C (-17°F) n temperature: 395	0mg/m³/1 .°	
$C_{2}H_{5}O - S_{1}CH_{3}$ $C_{1}H_{3}CH_{3}$	[75-77-4] TSCA HMIS: 3-4-2-X SIT8515.0 TRIMETHYLETHOXYSILANE <i>ETHOXYTRIMETHYLSILANE</i> C ₅ H ₁₄ OSi dipole moment: 1.2 AHcomb: 970.4 kcal/mole critical temperature: 233° HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moistr [1825-62-3] TSCA HMIS: 2-4-1-X	vapor pres ∆Hvap: 33	75-6° (-83°)mp -27°C (-17°F) ssure, 25°: 111mm .5 kcal/mole	3kg/\$16 0.7573 14kg/\$6	1.3742
CH ₃ O-Si-CH ₃ CH ₃ O-Si-CH ₃ CH ₃	SIT8566.0 TRIMETHYLMETHOXYSILANE C ₄ H ₁₂ OSi dipole moment: 1.18 debye HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moistu [1825-61-2] TSCA HMIS: 3-4-1-X		57-8° -11°C (12°F)	0.7560	1.3678
$ \begin{array}{ccc} CH_3 & Cl \\ I & I \\ H_3C - Si - O - Si - Cl \\ CH_3 & Cl \end{array} $	SIT8572.6 TRIMETHYLSILOXYTRICHLOROSILANE $C_3H_9Cl_3OSi_2$ [2750-45-0] HMIS: 3-4-1-X	223.63	128° 16°C (61°F) 25g/\$72.00	1.126	
$\begin{array}{c} H_{3}C \\ CH_{3} \\ CH_{3} \\ H_{3} \\ H_{3$	SIT8712.0 TRIS(DIMETHYLAMINO)METHYLSILANE $C_7H_{21}N_3Si$		55-6°/17 (-11°)mp 30°C (86°F)	0.85022	1.43222
H ₃ C ^{/N} CH ₃	HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moistr [3768-57-8] TSCA HMIS: 3-3-1-X	ure 10g/\$29.00	0	50g/\$11	6.00
$\begin{array}{c} H_{3}C \swarrow_{Si}^{CH_{3}}CH_{3} \\ (CH_{3})_{3}Si \searrow_{O} \bigvee_{Si}^{O} \bigvee_{O}^{Si(CH_{3})_{3}} \\ (CH_{2})_{2} \\ H_{3}C - Si - CH_{3} \\ CI \end{array}$	$\label{eq:sigma} \begin{array}{l} \text{SIT8719.5} \\ [\text{TRIS}(\text{TRIMETHYLSILOXY})\text{SILYLETHYL}]\text{DIMETHYL-} \\ \text{CHLOROSILANE} \\ \text{C}_{13}\text{H}_{37}\text{O}_3\text{CISi}_5 \\ \text{forms hydrophobic monolayers} \\ \text{HYDROLYTIC SENSITIVITY: 8} \\ \text{Si-CI reacts rapidly with waterr} \\ \text{HMIS: 3-2-1-X} \end{array}$	417.32 /moisture, prot	85°/0.6 ic solvents 10g/\$84.00	0.906	1.43175
CH ₃ (CH ₂) ₉ CH ₂ SiCl ₃	SIU9050.0 UNDECYLTRICHLOROSILANE C ₁₁ H ₂₃ Cl ₃ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18052-07-8] HMIS: 3-1-1-X		155-60°/15 107°C (225°) solvents 25g/\$104.00	1.02	

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Hydrophobic Dipodal Silanes

Dipodal Surface Bonding

	name	MW	bp/mm (mp)	D4 ²⁰	n _{D}^{20}
ClMe ₂ SiCH ₂ CH ₂ CH ₂ CH ₂ SiMe ₂ Cl	SIB1030.0 BIS[2-(CHLORODIMETHYLSILYL)- ETHYL]BENZENE mixed isomers C ₁₄ H ₂₄ Cl ₂ Si ₂ intermediate for silahydrocarbon polymers HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [74129-20-7] TSCA HMIS: 3-1-1-X		116-7°/0.2 187°C (369°F) solvents 50g/\$204.00	1.02	
Cl(CH ₃) ₂ SiCH ₂ CH ₂ Si(CH ₃) ₂ Cl	SIB1042.0 1,2-BIS(CHLORODIMETHYLSILYL)ETHANE <i>TETRAMETHYLDICHLORODISILETHYLENE</i> C ₆ H ₁₆ Cl ₂ Si ₂ reagent for protection of primary amines, inclu 1. S. Djuric et al, Tet. Lett., <i>22</i> , 1787, 1981 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [13528-93-3] TSCA HMIS: 3-2-1-X	ding amino	solvents	100g/\$6	8.00
Cl(CH ₃) ₂ Si(CH ₂) ₆ Si(CH ₃) ₂ Cl	SIB1046.0 1,6-BIS(CHLORODIMETHYLSILYL)HEXANE, 95% C ₁₀ H ₂₄ Cl ₂ Si ₂ HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [14799-66-7] HMIS: 3-1-1-X		113-6°/3 150°C (302°F) solvents	0.961 100g/\$1	1.4538 69.00
Cl(CH ₃) ₂ Si(CH ₂) ₈ Si(CH ₃) ₂ Cl	SIB1048.0 1,8-BIS(CHLORODIMETHYLSILYL)OCTANE, 95% C ₁₂ H ₂₈ Cl ₂ Si ₂ intermediate for sila-hydrocarbon polymers HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [5089-28-1] HMIS: 3-1-1-X			46 100g/\$1	1.4540 34.00
$CI - Si$ $CI - Si$ CH_3 CH_2 CH_3 CH_2 CH_3 CH_2 CH_3 CH_2 CH_3 CH_3	SIB1048.2 1,3-BIS(CHLORODIMETHYLSILYL)PROPANE C ₇ H ₁₈ Cl ₂ Si ₂ forms cyclic derivatives of polyalkyleneoxides sui 1. T. Zundel et al, Macromol, 31, 2724, 1998 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [2295-06-9] HMIS: 3-2-1-X			1.0244 tion ¹ .	1.4647
$Cl Cl Cl Cl CH_3SiCH_2CH_2SiCH_3$ $Cl Cl Cl$	SIB1614.0 BIS(METHYLDICHLOROSILYL)ETHANE <i>1,4-DIMETHYL-1, 1,4,4-TETRACHLORO-1,4-DISILABUT</i> C ₄ H ₁₀ Cl ₄ Si ₂ dipodal coupling agent HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [3353-69-3] TSCA HMIS: 3-2-1-X	flashpoint:		1.2628 100g/\$1	1.4760
$\begin{array}{ccc} C_2H_5O & OC_2H_5\\ CH_3SiCH_2CH_2SiCH_3\\ C_2H_5O & OC_2H_5 \end{array}$	$\begin{array}{l} \text{SIB1615.0} \\ \text{BIS}(\text{METHYLDIETHOXYSILYL})\text{ETHANE} \\ \text{C}_{12}\text{H}_{30}\text{O}_{4}\text{Si2} \\ \text{[18043-74-8]} \text{HMIS: 2-2-1-X} \end{array}$	294.54	80°/1.5 25g/\$62.00	0.92	1.4170
$ \begin{array}{cccc} F & F \\ I & I \\ CH_3SiCH_2CH_2SiCH_3 \\ F & F \\ F & F \end{array} $	$\begin{array}{l} \text{SIB1630.0} \\ \text{BIS}(\text{METHYLDIFLUOROSILYL})\text{ETHANE} \\ \text{C}_{4}\text{H}_{10}\text{F}_{4}\text{Si}_{2} \\ \text{HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture} \\ \text{HMIS: 3-3-1-X} \end{array}$	190.29 , water, protic	114° ^{solvents} 10g/\$69.00	1.118	
	SIB1808.0 1,2-BIS(TRICHLOROSILYL)DECANE C ₁₀ H ₂₀ Cl ₆ Si ₂ [62987-03-3] HMIS: 3-2-1-X	409.16	114°/1 25g/\$85.00	1.2496	1.4754
SiCl ₃					

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
$\begin{array}{c} CF_2 CF_2 CF_2 CF_2 CF_2 CF_2 CF_2 CF_2$	SIB1811.5 1,8-BIS(TRICHLOROSILYLETHYL)HEXA- DECAFLUOROOCTANE C ₁₂ H ₈ Cl ₆ F ₁₆ Si ₂ HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [445303-83-3] HMIS: 3-1-1-X	725.06 ater/moisture	142-4°/0.6 (69-70°)mp 5.0g/\$170.00		
5 0.03			5.09/01/0.00		
Cl C	SIB1812.0 BIS(TRICHLOROSILYL)HEXANE C ₆ H ₁₂ Cl ₆ Si ₂ forms mesoporous sol-gel structures		148-50°/10 1.3 75°C (167°F)	327	1.4759
ĊI ĊI	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [13083-94-8] TSCA HMIS: 3-2-1-X	e, water, protic 10g/\$41.00	solvents)	50g/\$16	4.00
Cl Cl Cl I I Cl	SIB1813.0 BIS(TRICHLOROSILYL)METHANE CH ₂ Cl ₆ Si ₂ nucleus for star polymers and dendrimers HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [4142-85-2] HMIS: 3-2-1-X	282.9 e, water, protic	183° solvents 5.0g/\$80.00	1.5567	1.4740
Cl Cl Cl I Cl I Cl	SIB1814.0 BIS(TRICHLOROSILYL)OCTANE C ₈ H ₁₆ Cl ₆ Si ₂ forms mesoporous sol-gel structures HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [52217-53-5] HMIS: 3-1-1-X		140°/1 115°C (240°F) solvents	1.22 100g/\$1	1.4757
Cl C	SIB1815.0 1,3-BIS(TRICHLOROSILYL)PROPANE C ₃ H ₆ Cl ₆ Si ₂ forms mesoporous sol-gel structures HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18171-50-1] HMIS: 3-2-1-X	310.97	115-7°/4 (29-30°)mp	1.4394	
$Cl_3Si - (CH_2)_{11}O(CH_2)_{11} - SiCl_3$	SIB1815.4 BIS(TRICHLOROSILYLUNDECYL)ETHER $C_{22}H_{44}Cl_6OSi_2$ HMIS: 3-1-1-X	593.48	5.0g/\$242.00	. d	\$
$C_{2}H_{5}O - S_{1}$ $C_{2}H_{5}O - S_{1}$ $C_{2}H_{5}O - S_{1}$ $C_{2}H_{5}O$ $OC_{2}H_{5}$	SIB1816.6 1,4-BIS(TRIETHOXYSILYL)BENZENE C ₁₈ H ₃₄ O ₆ Si ₂ forms thermally stable hybrid silica fibers ¹ . 1. Y. Yang et al, Chem. Mater., <i>18</i> , 1324, 2006 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with we [52217-60-4] HMIS: 2-2-1-X	402.64 ater/moisture	130-2°/0.4 5.0g/\$60.00	1.015	1.4549
$\begin{array}{c} OC_{2}H_{5} & OC_{2}H_{5} \\ C_{2}H_{5}O - \begin{array}{c} SiCH_{2}CH_{2}Si - OC_{2}H_{5} \\ OC_{2}H_{5} & OC_{2}H_{5} \end{array}$	 SIB1817.0 BIS(TRIETHOXYSILYL)ETHANE HEXAETHOXYDISILETHYLENE C₁₄H₃₄O₆Si₂ ΔHvap: 101.5 kj/mole additive to silane coupling agent formulations f employed in corrosion-resistant coatings/prime sol-gels of α,ω-bis(trimethoxysilyl)alkanes repor forms mesoporous, derivatizeable molecular s 1. W. Van Ooij et al, J. Adhes. Sci. Tech. <i>11</i>, 29 2. W. Van Ooij et al, Chemtech., <i>28</i>, 26, 1998. 3. D. A. Loy et al, J. Am. Chem. Soc., <i>121</i>, 541 4. B. Molde et al, Chem. Mat., <i>11</i>, 3302, 1999. HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with we [16068-37-4] TSCA-S HMIS: 3-1-1-X 	vapor pres TOXICITY that enhance orted ³ . ieves ⁴ . 0, 1997. 3, 1999.	and aluminum ^{1,2} .	161mg/kg	-
OEt OEt EtO—SiCH2Si –OEt OEt OEt	SIB1821.0 BIS(TRIETHOXYSILYL)METHANE 4,4,6,6-TETRAETHOXY-3,7-DIOXA-4,6-DISILANONANE C ₁₃ H ₃₂ O ₆ Si ₂ intermediate for sol-gel coatings, hybrid inorga HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with with [18418-72-9] HMIS: 2-3-0-X	inic-organic		0.9741 25g/\$96	1.4098

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	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
(C ₂ H ₅ O) ₃ Si(CH ₂) ₈ Si(OC ₂ H ₅) ₃	SIB1824.0 BIS(TRIETHOXYSILYL)OCTANE C ₂₀ H ₄₆ O ₆ Si ₂ employed in sol-gel synthesis of mesoporous s sol-gels of α, ω-bis(trimethoxysilyl)alkanes rep 1. D. A. Loy et al, J. Am. Chem. Soc., 121, 541 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with we [52217-60-4] TSCA-L HMIS: 2-1-1-X	orted ¹ . 3, 1999.	172-5°/0.75	0.926 100g/\$9	1.4240
Si(OCH ₃) ₃	SIB1829.0 1,2-BIS(TRIMETHOXYSILYL)DECANE C ₁₆ H ₃₈ O ₆ Si ₂ pendant dipodal silane; employed in high pH H HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa HMIS: 3-2-1-X		130-2°/0.4	0.984 100g/\$	1.4303
OCH ₃ OCH ₃ CH ₃ O—SiCH ₂ CH ₂ Si -OCH ₃ OCH ₃ OCH ₃	SIB1830.0 BIS(TRIMETHOXYSILYL)ETHANE C ₈ H ₂₂ O ₆ Si ₂ CAUTION: INHALATION HAZARD employed in fabrication of multilayer printed cir 1. J. Palladino, U.S. Pat. 5,073,456, 1991. see also SIB1817.0 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [18406-41-2] TSCA HMIS: 4-2-1-X	vapor pres rcuit boards		1.068 m 100g/\$2	1.4091
(MeO) ₃ SiCH ₂ CH ₂ CH ₂ CH ₂ Si(OMe) ₃	SIB1831.0 BIS(TRIMETHOXYSILYLETHYL)BENZENE C ₁₆ H ₃₀ O ₆ Si ₂ mixed isomers HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wit [58298-01-4] TSCA HMIS: 2-1-0-X		148-50°/.1 193°C (380°F))	1.08 50g/\$13	1.4734
OCH ₃ OCH ₃ CH ₃ O—Si(CH ₂) ₆ Si –OCH ₃ OCH ₃ OCH ₃	$ \begin{array}{l} \text{SIB1832.0} \\ \text{1,6-BIS(TRIMETHOXYSILYL)HEXANE} \\ \text{C}_{12}\text{H}_{30}\text{O}_6\text{Si}_2 \\ \text{sol-gels of } \alpha, \ \omega\text{-bis(trimethoxysilyl)alkanes rep} \\ \text{1. D. A. Loy et al, J. Am. Chem. Soc., } 121, 541 \\ \text{HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wat} \\ [87135-01-1] \text{HMIS: 3-2-1-X} \end{array} $	orted ¹ . 3, 1999.	161°/2 : 95°C (203°F))	1.014 50g/\$15	1.4213
CH ₃ O, CH ₃ O,Si-CH ₂ ,OCH ₃ CH ₃ O,CH ₂ -Si,OCH ₃ CH ₃ O,CH ₂ -Si,OCH ₃ OCH ₃	SIB1832.2 p-BIS(TRIMETHOXYSILYLMETHYL)BENZENE 3C14H26O6Si2 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [193358-40-6] HMIS: 3-1-1-X	346.53 ater/moisture	124-5°/0.05 10g/\$180.00	1.097	1.47025
(CH ₃ O) ₃ SiCH ₂ CH ₂ CH ₂ CH ₂ CH ₂ CH ₂ Si(OCH ₃) ₃	SIB1833.4 BIS-1,3-(TRIMETHOXYSILYLPROPYL)- BENZENE $C_{18}H_{34}O_6Si_2$ HMIS: 3-2-1-X	402.64	5.0g/\$145.00		
$Cl - Si \xrightarrow{CH_3} CH_2CH_2Si - Cl \\CH_3 CH_3 CH_3$	SIC2265.5 (CHLORODIMETHYLSILYL)-6-[2-(CHLORODI- METHYLSILYL)ETHYL]BICYCLOHEPTANE mixtu C ₁₃ H ₂₆ Cl ₂ Si ₂ forms polymers HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa HMIS: 3-2-1-X		l 2 regio isomers, 25g/\$48.00	1.03 exo and	1.4863 endo
$\begin{array}{ccc} & & & & & & \\ & & & & & \\ & & & & \\ & & H_3C - SiCH_2CH_2Si - OC_2H_5 \\ & & & & \\ & & & & \\ & & & OC_2H_5 \\ & & & & & \\ \end{array}$	SIT8185.8 1-(TRIETHOXYSILYL)-2-(DIETHOXYMETHYL- SILYL)ETHANE C ₁₃ H ₃₂ O ₅ Si dipodal silane; forms abrasion-resistant sol-ge HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist [18418-54-7] TSCA HMIS: 3-2-1-X	l coatings	100°/0.5 102°C (215°F) 0 100g/\$130.00	0.946 2kg/\$8	1.4112 40.00

Polymeric Hydrophobic Silanes

Polymeric Surface Bonding

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
$\begin{array}{ccc} CH_2 & CH_2 \\ \parallel & \parallel \\ CH & CH \\CH_2CHCH_2CHCH_2CH- \\ -CH_2CHCH_2Si(OC_2H_5)_3 \end{array}$	Polybutadiene SSP-055 TRIETHOXYSILYL MODIFIED POLY-1,2-BUTADIENE, 50% in toluene viscosity: 100-200 cSt. coupling agent for EPDM resins [72905-90-9] TSCA HMIS: 2-4-1-X store <5°	3500-4500 100g/\$60.00		0.90 2.0kg/\$78	30.00
$\begin{array}{ccc} CH_2 & CH_2 \\ CH & CH \\ CH & CH \\CH_2CHCH_2CHCH_2CH- \\ CH_2CH_2Si(OC_2H_5)_3 \end{array}$	SSP-056 TRIETHOXYSILYL MODIFIED POLY-1,2-BUTADIENE, 50% in volatile silicone viscosity: 100-200 cSt. primer coating for silicone rubbers [72905-90-9] TSCA HMIS: 2-3-1-X store <5°	3500-4500	100g/\$68.00	0.93	,
CH ₂ CH CH CH CH ₂ CHCH ₂ CHCH ₂ CH- CH ₂ CHCH ₂ CHCH ₂ CH- CH ₂ CH ₂ Si(OC ₂ H ₅) ₂ CH ₃	SSP-058 DIETHOXYMETHYLSILYL MODIFIED POLY-1,2-BUTA- DIENE, 50% in toluene viscosity: 75-150 cSt. water tree resistance additive for crosslinkable H HMIS: 2-4-1-X store <5°		adding 100g/\$86.00	0.90	
-(CH ₂ CH) _m (CH ₂ CH) _n (CH ₂ CH = CHCH ₂) _p – CH ₂ CH ₂ Si(OC ₂ H ₅) ₃	SSP-255 (30-35%TRIETHOXYSILYLETHYL)ETHYLENE- (35-40% 1,4-BUTADIENE) - (25-30% STYRENE) ter HMIS: 2-3-1-X viscosity: 20-30 cSt.	4500-5500 rpolymer, 50%	o in toluene 100g/\$86.00		

Reactive Polydimethylsiloxane Oligomers

Code		Molecular	Specific		
Cour	Viscosity	Weight	Gravity	Price/100g	Price/1kg
DMS-K05	3 - 6	425-600	1.00	\$55.00	\$358.00
DMS-K13	20-50	2000-4000	0.99	\$120.00	
DMS-K26	500-800	15,000-20,000	0.99	\$94.00	
Dimethylaming	o Terminated PolyD	vimethylsiloxanes	CAS: [6	67762-92-9] TSCA	
Code	Viscosity	Molecular Weight	Specific Gravity	Price/100g	
DMS-N05	3 - 8	450-600	0.93	\$160.00	
Ethoxy Termin	ated PolyDimethyls	Molecular	Specific	CAS: [7085	51-25-1] TSCA
Ethoxy Termin Code	Viscosity		Specific Gravity	CAS: [708: Price/100g	51-25-1] TSCA Price/1kg
Code		Molecular			_
Code DMS-XE11	Viscosity	Molecular Weight 800-900 Visiloxanes	Gravity 0.94	Price/100g \$32.00	Price/1kg
Code DMS-XE11	Viscosity 5-10	Molecular Weight 800-900	Gravity	Price/100g \$32.00	Price/1kg \$210.00

SCA

		Molecular			Specific	Refractive	•		
Code	Viscosity	Weight	% (OH)	(OH) - Eq/kg	Gravity	Index	Price/100g	Price/3kg	Price/16kg
DMS-S12	16-32	400-700	4.5-7.5	2.3-3.5	0.95	1.401	\$19.00	\$124.00	\$496.00
DMS-S14	35-45	700-1500	3.0-4.0	1.7-2.3	0.96	1.402	\$18.00	\$117.00	\$460.00
DMS-S15	45-85	2000-3500	0.9-1.2	0.53-0.70	0.96	1.402	\$18.00	\$117.00	\$460.00

	Hydrophilic Si Polar - Non-hy		-		
	name	MW	bp/mm (mp)	D4 ²⁰	n _200
NCCH ₂ CH ₂ CH ₂ , OCH ₃ NCCH ₂ CH ₂ CH ₂ , Si OCH ₃	SIB1057.5 BIS(3-CYANOPROPYL)DIMETHOXYSILANE C ₁₀ H ₁₈ N ₂ O ₂ Si highly polar monomer for silicones HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with v [92779-73-2] HMIS: 3-2-1-X	226.35 vater/moisture	180-2°/1 5.0g/\$112.00	0.985	
CH ₃ O CH ₃ O CH ₃ Si(CH ₂) ₃ O(CH ₂ CHO) _n (CH ₂) ₃ Si(CH ₃ CH ₃ O CH ₃ O		sins	:: >110°C (>230°F	1.00 F) 2.0kg/\$2	1.452 ²⁵ 288.00
	SIB1824.9 1,3-[BIS(3-TRIETHOXYSILYLPROPYL)POLY- ETHYLENOXY]-2-METHYLENEPROPANE 3 C ₅₀ H ₁₀₄ O ₂₀ Si ₂ (average) vinyl functional hydrophilic dipodal coupling av HMIS: 2-2-1-X	1113.5 gent for pro	tein immobilizatio 1.0g/\$292.00	'n	
$N \equiv C - CHCH_2CH_2, CH_3$	SIC2436.0 (3-CYANOBUTYL)DIMETHYLCHLOROSILANE C ₇ H ₁₄ CINSi	175.73	80-4°/1	0.993	
H ₃ C Cl	HMIS: 3-2-1-X	25g/\$40.0	0	100g/\$1	30.00
CH ₃ N≡C−CHCH ₂ CH ₂ ,Cl Si H ₃ C Cl	SIC2437.0 (3-CYANOBUTYL)METHYLDICHLOROSILANE <i>4-(DICHLOROMETHYLSILYL)-2-METHYLBUTYRONITH</i> C ₆ H ₁₁ Cl ₂ NSi [71550-62-4] TSCA HMIS: 3-2-1-X	196.17 <i>RILE</i> 25g/\$40.0	63°/0.3	1.104 100g/\$1	120.00
$N \equiv C - CHCH_2CH_2, OCH_3$ $H_3C \xrightarrow{Si} OCH_3$	SIC2437.5 (3-CYANOBUTYL)METHYLDIMETHOXY- SILANE C ₈ H ₁₇ NO ₂ Si [793681-94-4] TSCA HMIS: 3-2-1-X	187.32	77°/1.5 :: 93°C (199°F) 25g/\$88.00	0.947	1.421325
$N \equiv C - CHCH_2CH_2, CI$	SIC2438.0 (3-CYANOBUTYL)TRICHLOROSILANE $C_5H_8CI_3NSi$ [163155-56-4] HMIS: 3-2-1-X	216.57 25g/\$39.0	61-3°/0.2 0	1.220 100g/\$1	1.4690 ²⁵ 27.00
$ \begin{array}{c} CH_{3} \\ N \equiv C - CHCH_{2}CH_{2}, OCH_{3} \\ H_{3}CO & OCH_{3} \end{array} $	SIC2439.0 3-CYANOBUTYLTRIETHOXYSILANE C ₁₁ H ₂₃ NO ₃ Si HMIS: 2-2-1-X	245.39	25g/\$62.00		
$N = C - CH_2CH_2, CI$ H_3C	SIC2440.0 2-CYANOETHYLMETHYLDICHLOROSILANE C ₄ H ₇ Cl ₂ NSi monomer for polar silicones used in GC phas HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moistur [1070-18-4] TSCA HMIS: 3-2-1-0	es	60-2°/4 :: 60°C (140°F) s 25g/\$123.00	1.2015	1.455025
$N \equiv C - CH_2 CH_2 SiCl_3$	SIC2442.0 2-CYANOETHYLTRICHLOROSILANE C ₃ H ₄ Cl ₃ NSi ΔHvap: 11.2 kcal/mole vapor pressure, 85°: 12mm HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moistur	re, protic solvent		-	-
	[10731-22-3] TSCA HMIS: 3-2-1-0-X	10g/\$27.0	U	50g/\$10	18.00

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
$ = C - CH_2CH_2 - Si - OCH_2CH_3 $	SIC2445.0 2-CYANOETHYLTRIETHOXYSILANE C ₉ H ₁₉ NO ₃ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [919-31-3] TSCA HMIS: 2-2-0-X	flashpoint:	224-5° oral rat, LD50: 5 86°C (186°F) 100/\$49.00		•
$N \equiv C - CH_2 CH_2 Si(OCH_3)_3$	SIC2446.0 2-CYANOETHYLTRIMETHOXYSILANE C ₆ H ₁₃ NO ₃ Si γc of treated surface: 34 dynes/cm crosslinker for moisture-cure silicone RTVs HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w. [2526-62-7] TSCA HMIS: 3-2-1-X	175.26 flashpoint:	112°/15 79°C (174°F)	1.079 100g/\$1	1.4126
$\equiv C - CH_2CH_2CH_2CH_2S_1 - N(CH_3)_2$ CH(CH_3)_2 CH(CH_3)_2	SIC2451.0 3-CYANOPROPYLDIISOPROPYLDIMETHYL- AMINOSILANE 4-{DIMETHYLAMINOBIS(1-METHYL C ₁₂ H ₂₆ N ₂ Si stable cyanofunctional bonded phase HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [163794-91-0] TSCA HMIS: 3-2-1-X		96-8°/0.2 L <i>JBUTANENITRILL</i> 10g/\$127.00	0.89 E	1
$N \equiv C - CH_2CH_2CH_2CH_2S_1 - CI$	SIC2452.0 3-CYANOPROPYLDIMETHYLCHLOROSILANE 4-(CHLORODIMETHYLSILYL)BUTYRONITRILE C ₆ H ₁₂ CINSi coupling agent for antibodies ¹ . 1. S. Falipou et al, Bioconjugate Chem., Am. C HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/mois [18156-15-5] TSCA HMIS: 3-2-1-X	Chem. Soc., ⁻	108-9°/15 85°C (185°F) 1989 nts	0.986 100g/\$1	1.4460
$N \equiv C - CH_2CH_2CH_2S_1 - CH_3$	SIC2453.0 3-CYANOPROPYLMETHYLDICHLOROSILANE C ₅ H ₉ Cl ₂ NSi see also SIC2448.0 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/mois [1190-16-5] TSCA HMIS: 3-2-1-X	flashpoint:	79-82°/1 oral, rat, LD50: ; 92°C (198°F) ^{nts}	-	
$V = C - CH_2CH_2CH_2Si - CH_3$	SIC2453.5 3-CYANOPROPYLMETHYLDIMETHOXYSILANE C ₇ H ₁₅ NO ₂ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w HMIS: 3-2-1-X	173.29	82-3°/3		1.4235
$I = C - CH_2CH_2CH_2S_i - CI$	SIC2454.0 3-CYANOPROPYLTRICHLOROSILANE C ₄ H ₆ Cl ₃ NSi see also SIC2449.0 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/mois	202.54 flashpoint:	93-4°/8 75°C (167°F)	1.302	1.465
$= C - CH_2CH_2CH_2S_1 - OC_2H_5$	[1071-22-3] TSCA HMIS: 3-2-1-X SIC2455.0 3-CYANOPROPYLTRIETHOXYSILANE C ₁₀ H ₂₁ NO ₃ Si viscosity: 2.3 cSt HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w. [1067-47-6] TSCA HMIS: 3-2-1-X	25g/\$24.00 231.37 TOXICITY- flashpoint:	79-80°/0.6 oral rat, LD50: 2 74°C (165°F)		1.4174 g
$= C - CH_2CH_2CH_2S_i - OCH_3$	SIC2456.0 3-CYANOPROPYLTRIMETHOXYSILANE C ₇ H ₁₅ NO ₃ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [55453-24-2] TSCA-L HMIS: 3-2-1-X	189.29 ater/moisture 10g/\$30.00	90-2°/7	1.026 ²⁵ 50g/\$14	1.4167
NC(CH ₂) ₁₁ SiCl ₃	SIC2456.3 11-CYANOUNDECYLTRICHLOROSILANE C ₁₂ H ₂₂ Cl ₃ NSi long-chain organofunctional silane HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [724460-16-6] HMIS: 3-2-1-X	314.76 e, water, protic s	162-4°/1 olvents 5.0g/\$155.00	1.075	

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Hydrophilic Silane Properties

Polar - Hydrogen Bonding

	name	MW	bp/mm (mp)	D 4 ²⁰	$\mathbf{n}_{\mathrm{D}}^{20}$
$\begin{array}{c} O & OCH_3 \\ II & I \\ CH_3CNCH_2CH_2CH_2Si - OCH_3 \\ I & I \\ H & OCH_3 \end{array}$	SIA0006.0 ACETAMIDOPROPYLTRIMETHOXYSILANE $C_8H_{19}NO_4Si$ [57757-66-1] HMIS: 3-2-1-X	221.33	162-5°/2-3 10g/\$120.00		1.4410
CH ₃ COCH ₂ CH ₂ CH ₃ CH ₃ COCH ₂ CH ₂ Si —Cl	SIA0010.0 ACETOXYETHYLDIMETHYLCHLOROSILANE C ₆ H ₁₃ ClO ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18306-45-1] HMIS: 3-2-1-X	•	108-9°/50 63°C (145°F) ^{solvents} 25g/\$61.00	1.03125	1.430125
$CH_{3}COCH_{2}CH_{2}Si - CH_{3}CH_{3}CH_{2}CH_{2}Si - CH_{3}CH_{$	SIA0015.0 ACETOXYETHYLMETHYLDICHLOROSILANE C ₅ H ₁₀ Cl ₂ O ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18163-34-3] TSCA HMIS: 3-2-1-X		117°/62 65°C (149°F) ^{solvents} 25g/\$55.00	1.17725	1.439025
$CH_{3}COCH_{2}CH_{2}Si - Cl$	SIA0020.0 ACETOXYETHYLTRICHLOROSILANE C ₄ H ₇ Cl ₃ O ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [18204-80-3] TSCA HMIS: 3-2-1-X		143°/70 82°C (180°F) solvents	1.272 ²⁵ 100g/\$1	1.4427 ²⁵ 66.00
$\begin{array}{c} O & OC_2H_5 \\ II & I \\ CH_3COCH_2CH_2Si - OC_2H_5 \\ OC_2H_5 \end{array}$	SIA0025.0 ACETOXYETHYLTRIETHOXYSILANE C ₁₀ H ₂₂ O ₅ Si >280° rearranges to acetoxytriethoxysilane w/ 1. K. Ezbiansky et al, in "Chemical Process. of Dielecti HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w. [22538-45-0] HMIS: 2-2-1-X	rics, Insulator			1.410 Proc. 2000.
O OCH ₃ H CH ₃ COCH ₂ CH ₂ Si – OCH ₃ OCH ₃	SIA0030.0 ACETOXYETHYLTRIMETHOXYSILANE, 95% C ₇ H ₁₆ O ₅ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [72878-29-6] HMIS: 3-3-1-X	208.29 ater/moisture	108-9°/27 25g/\$48.00	1.061	
CH ₃ COCH ₂ Si –OCCH ₃ CH ₃ COCH ₂ Si –OCCH ₃ CH ₃	SIA0040.0 ACETOXYMETHYLDIMETHYLACETOXY- SILANE C ₇ H ₁₄ O ₄ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w. [5833-57-8] HMIS:3-2-1-X		66-9°/7 63°C (145°F) 25g/\$72.00	1.0420	1.4388
$\begin{array}{c} O & OC_2H_5 \\ II & I \\ CH_3COCH_2Si - OC_2H_5 \\ OC_2H_5 \end{array}$	SIA0050.0 ACETOXYMETHYLTRIETHOXYSILANE C ₉ H ₂₀ O ₅ Si hydrolyzes to form stable silanol solutions in n HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with we [5630-83-1] HMIS: 2-2-1-X			1.042 ²⁵ 100g/\$1	
O OCH ₃ H CH ₃ COCH ₂ Si – OCH ₃ OCH ₃	SIA0055.0 ACETOXYMETHYLTRIMETHOXYSILANE, 95% C ₆ H ₁₄ O ₅ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with we [65625-39-0] TSCA-L HMIS: 3-3-1-X		190-1° 56°C (133°F))	1.085 50g/\$18	0.00
O OCH ₃ II CH ₃ CO(CH ₂ CH ₂ O) - G-9(CH ₂) ₃ Si - OCH ₃ OCH ₃	SIA0078.0 2-[ACETOXY(POLYETHYLENEOXY)- PROPYL]TRIETHOXYSILANE 95% HMIS: 2-1-1-X	500-700	25g/\$78.00	1.04	

PLEASE INQUIRE ABOUT BULK QUANTITIES

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
O Cl CH ₃ COCH ₂ CH ₂ CH ₂ Si −CH ₃ Cl	SIA0090.0 ACETOXYPROPYLMETHYLDICHLORO- SILANE C ₆ H ₁₂ Cl ₂ O ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [5290-24-4] TSCA HMIS: 3-2-1-X		142°/73 85°C (185°F) ^{solvents} 25g/\$58.00	1.15125	1.443425
O OCH ₃ CH ₃ COCH ₂ CH ₂ CH ₂ Si —OCH ₃ I OCH ₃	SIA0100.0 ACETOXYPROPYLTRIMETHOXYSILANE C ₈ H ₁₈ O ₅ Si γc of treated surface: 37.5 dynes/cm HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [59004-18-1] HMIS: 3-1-1-X		92°/2 93°C (200°F)	1.062 100g/\$6	1.4146 2.00
O II CH ₃ COCH ₂ (CH ₂) ₁₀ SiCl ₃	SIA0114.0 11-ACETOXYUNDECYLTRICHLOROSILANE C ₁₃ H ₂₅ Cl ₃ O ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture HMIS: 3-1-1-X		147-9°/1 >110°C (>230°F) solvents 10g/\$85.00	1.084	
O O II II CH ₃ CONCH ₂ CNHCH ₂ CH ₂ CH ₂ Si(OCH ₃) ₃	$\begin{array}{l} SIA0120.0 \\ (N-ACETYLGLYCYL)-3-AMINOPROPYL-\\ TRIMETHOXYSILANE \\ C_{10}H_{21}N_2O_6Si \\ amino \ acid-tipped \ silane \\ HYDROLYTIC \ SENSITIVITY: 7 \ Si-OR \ reacts \ slowly \ with \ ward HMIS: 3-2-1-X \end{array}$	293.37	5.0g/\$152.00		
CH ₃ CH ₃ H ₂ N(CH ₂ CHO) ₂ CH ₂ CHNHCH ₂ CH ₂ CH ₂ Si(OCH ₃) ₃	SIA0599.4 N-3-[(AMINO(POLYPROPYLENOXY)]AMINO- PROPYLTRIMETHOXYSILANE 60-65% contains 30-35% amine terminated polypropylene coupling agent with film-forming capability HMIS: 2-2-1-X		eneoxy units 25g/\$76.00	0.984	1.4508
C – O(CH ₂) ₃ Si(OCH ₃) ₃	$\label{eq:sigma} \begin{array}{l} SIB0959.0\\ BENZOYLOXYPROPYLTRIMETHOXYSILANE\\ C_{13}H_{20}O_5Si\\ \text{HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with water [76241-02-6] TSCA-L HMIS: 3-2-1-X \end{array}$	284.38 ater/moisture	145°/0.2 25g/\$68.00	1.104	1.4806
O CH ₂ -C-CH ₂ -O CH ₂ -C-CH ₂ -O CH ₂ H CH ₂ CH ₂ H CH ₂	SIB1815.1 1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2- DECYLOXYPROPANE C ₁₉ H ₃₈ O ₃ Cl ₆ Si ₂ dipodal C ₁₈ analog w/buried hydrophilicity HMIS: 3-1-1-X	583.40	190-200°/0.4 10g/\$124.00	1.158	
$\begin{array}{c c} c \\ c$	SIB1815.3 3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE C ₂₀ H ₄₀ O ₃ Cl ₆ Si ₂ dipodal hydrophobic surface treatment with bur HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture HMIS: 3-1-1-X		hilicity for chromat	1.13 tography	,
$\begin{array}{ccc} & & & & & \\ & & & \\ & & & & \\ & & & \\ & & & & \\ & & & \\ & & & & \\ & & &$	SIB1824.82 BIS[N,N'-(TRIETHOXYSILYLPROPYL)AMINO- CARBONYL]POLYETHYLENE OXIDE (10-15 EO) dipodal hydrophilic silane [178884-91-8] TSCA HMIS: 1-1-1-X	1000-1200) 25g/\$60.00	1.085	
СН ₃ СН ₂ O СН ₃ СН ₂ O-Ş ⁱ =CH ₂ CH ₂ CH ₂ CH ₂ O(CH ₂ CH ₂ O) СH ₃ CH ₃ O-Ş ⁱ =CH ₂ CH ₂ CH ₂ CH ₂ CH ₂ CH ₃ CH ₃ CH ₃ CH ₃ CH ₃ CH ₄ CH ₃ CH ₂ O CH ₃ CH ₂ O	SIB1824.84 BIS(TRIETHOXYSILYLPROPYL)POLY- ETHYLENE OXIDE (25-30 EO) HMIS: 2-1-1-X	1400-1600) 25g/\$104.00		

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SiB 1827.0 SiB 1827.0 High CH,		name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
CHUDIST SIGCULD [69952-89-2] HILLS 21-1X 25g/\$14.00 ICC_H,O),SICH_CH_CH_CH_N_N_C-CF SIBJOLT REFHOXYSILYL/PROPYL/UREA, 60%, 488.73 0.923 III,CL,OL,SICH_CH_CH_R, N),C-CF SIBJOLT REFHOXYSILYL/PROPYL/UREA, 60%, 488.73 0.923 III,CL,OL,SICH_CH_CH_R, N),C-CF SIBJOLT REFHOXYSILYL/PROPYL/UREA, 60%, 488.73 0.923 IIII,CL,OL,SICH_CH_CH_R SIBJOLT REFHOXYSILYL/PROPYL/UREA, 60%, 488.73 0.923 IIIII,CL,OL,SICH_CH_CH_R SIBJOLT REFHOXYSILYL/PROPYL/UREA, 60%, 488.73 1000g/\$110.00 IIIIIIIIIIIIIIIIIIIIIIIIIIIIIIIIIIII	CH_2 CH_2	$\begin{array}{l} \text{BIS}[3\text{-}(\text{TRIETHOXYSILYL})\text{PROPYL}]\text{THIO-}\\ \text{UREA tech -90}\\ \text{C}_{19}\text{H}_{44}\text{N}_2\text{O}_6\text{SSi}_2\\ \text{forms films on electrodes for determination of} \end{array}$	mercury ¹ .			
H DBIS[3-(TRIETHOXYSILYL)PROPYLJUREA, 60%, 468,73 0.923 (IC_H,O),SICH_CH,CH,CH, 2, N)_CCE In ethanolic Gaspannic Control Contrel Control Control Control Contrel Control Control Control Contr			1999	25g/\$134.00		
(CH,0),SICH,CH,CH, H + H + H + H + H + H + H + H + H + H +		BIS[3-(TRIETHOXYSILYL)PROPYL]UREA, 60% in ethanol C ₁₉ H ₄₄ N ₂ O ₇ Si ₂ HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa	flashpoint: ater/moisture			10.00
(CH ₃ O ₃)SICH ₂ CH ₂ CH ₂ [14418-53-6] TSCA HMIS: 3:2-1:X 25g/S20.00 100g/\$65.00 (CH ₃ O ₂)C(CH ₂)H ₃ O ₁ = CL (CH ₃)C(CH ₂)H ₃ O ₁ = CL (CH ₃) SIC2065.0 0.950 1.4483** 0.950 1.4483** (CH ₃ OC(CH ₂)H ₃ O ₁ = CL (CH ₃) CH ₃ OC(CH ₂)H ₃ O ₁ = CL (CH ₃) SIC2067.0 0.950 1.4483** 0.950 1.4483** (CH ₃ OC(CH ₂)H ₃ O ₁ = CCH ₃ CH ₃ CCO ₂ SI (CH ₃ OCCH ₂ CH ₃)H ₃ O ₁ = CCH ₃ SIC2067.0 100g/\$420.00 50g/\$168.00 (CH ₃ OC(CH ₂)H ₃ O ₁ = CCH ₃ CH ₃ CCO ₂ SI (CH ₃ OCCH ₂ CH ₃ S ₁) = CCH ₃ SIC2067.0 100g/\$120.00 50g/\$168.00 (CH ₃ OC(CH ₂)H ₃ O ₁)CO ₁ = CCH ₃ CH ₃ CCO ₂ SI (CH ₃ OCCH ₂ CH ₃ S ₁) = CCH ₃ SIC2067.0 100g/\$120.00 50g/\$204.00 (CH ₃ OC(CH ₂)H ₃ O ₁)CO ₁ = CCH ₃ CH ₃ CCO ₂ SI (CH ₃ OCCH ₂)H ₃ O ₁)CO ₁ = CCH ₃ SIC2067.0 10g/\$251.10 50g/\$204.00 (CH ₃ OCCH ₂ CH ₂ S ₁ = CCH ₃ CH ₃ CCH ₂ CH ₂ S ₁ = CCH ₃ SIC2067.0 10g/\$251.10 50g/\$204.00 (CH ₃ OCCH ₂ CH ₂ S ₁ = CCH ₃ CH ₃ CCH ₂ CH ₂ S ₁ = CCH ₃ SIC2067.0 10g/\$21.12 98-9/25 1.187* 1.4439** (CH ₃ OCCH ₂ CH ₂ S ₁ = CCH ₃ CH ₃ CCH ₂ CH ₂ S ₁ = CCH ₃ SIC207.0 21.54 90-2'25 1.325 <t< td=""><th></th><td>SIB1835.5 BIS(TRIMETHOXYSILYLPROPYL)UREA, 95%</td><td>384.58 flashpoint:</td><td>>110°C (>230°F)</td><td>-</td><td>10.00</td></t<>		SIB1835.5 BIS(TRIMETHOXYSILYLPROPYL)UREA, 95%	384.58 flashpoint:	>110°C (>230°F)	-	10.00
$ \begin{array}{c} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3}OC(CH_{2})_{10}S_{1}^{2} - CI \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3}OC(CH_{2})_{10}S_{1}^{2} - CI \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} CH_{3} \\ OC(CH_{2})_{10}S_{1}^{2} - CI \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} CCH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} CCH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} CCH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} CCH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} CCH_{3} CCH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} CCH_{3} CCH_{3} \end{array} \\ \end{array}{} \begin{array}{c} 0 \\ CH_{3} CCH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} CH_{3} CH_{3} \end{array} \\ \\ \begin{array}{c} CH_{3} CCH_{3} CCH_{3} \end{array} \\ \end{array}{} \begin{array}{c} CH_{3} CH_{3} CH_{3} \end{array} \\ \\ \end{array}{} \begin{array}{c} CH_{3} CH_{3} CH_{3} \end{array} \\ \\ \begin{array}{c} CH_{3} CCH_{3} CH_{3} \end{array} \\ \\ \begin{array}{c} CH_{3} CH_{3} CH_{3} \end{array} \\ \\ \begin{array}{c} CH_{3} CH_{3} CH_{3} \end{array} \\ \\ \begin{array}{c} CH_{3} CH_{3} CH_{3} \end{array} \\ \\ \begin{array}{c} CH_{3} CH_{3} CH_{3} CH_{3} \end{array} \\ \\ \\ \begin{array}{c} CH_{3} CH_{3} CH_{3} CH_{3} CH_{3} \end{array} \\ \\ \\ \begin{array}{c} CH_{3} CH_{3} CH_{3} CH_{3} CH_{3} \end{array} \\ \\ \\ \begin{array}{c} CH_{3} CH_{3$	1	[18418-53-6] TSCA HMIS: 3-2-1-X			100g/\$6	5.00
CH3 Integration digatorial bigatorial share Org-Chain organounculous Sig2363 O CH3 Integration Sig2363 O CH3 Integration Sig2363 CH3 Sig2363 Integration Sig2363 CH3 Sig2363 CH3 Sig2364 CH4 Sig2364 CH4 Sig2364 CH4 Sig2364 CH4 Sig2364 Sig2364 Sig2364 Sig2364 Sig2364 Sig2364 Sig2364 Sig2364 Sig2364	$\begin{array}{c} O & CH_3 \\ H & CH_3OC(CH_2)_{10}Si & -Cl \end{array}$	10-(CARBOMETHOXY)DECYLDIMETHYL- CHLOROSILANE			0.950	1.448325
$ \begin{array}{c} \begin{array}{c} \begin{array}{c} 0 \\ CH_{3}OC(CH_{2})_{10}S_{1}^{-} - OCH_{3} \\ CH_{3}OCCH_{2}CH_{2}S_{1}^{-} - CH_{3} \\ CH_{3}OCCH_{2}CH_{2}CH_{2}CH_{2}CH_{2}CH_{2}CH_{2}CH_{2}CH_{2}CH_{2}CH_{2}CH_{2}CH_{2}C$	•	Iong-chain organofunctional silane HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture			50g/\$16	8.00
Photochic Bevisition P, 7 Short reads slowly with water/moisture Tog/\$51.00 50g/\$204.00 PHOROCH 2012 Sic2068.0 2-(CARBOMETHOXY)ETHYLMETHYL- 201.12 98-9°/25 1.187°° 1.4439°° PLNC-CH_2CH_2Si - CH CI Sic2070.0 2-(CARBOMETHOXY)ETHYLTRICHLORO 221.54 90-2°/25 1.325 1.448 METHYL/3-TRICHLOROSILVPROPONATE/ Ifashpoint: > 43°C (>110°F) 1.325 1.448 METHYL/3-TRICHLOROSILVPROPONATE/ Ifashpoint: > 43°C (>110°F) 1.325 1.448 Sic2072.0 2-(CARBOMETHOXY)ETHYLTRICHOROSILVPROPONATE/ Ifashpoint: > 43°C (>110°F) 1.069 1.410 Sic2072.0 2-(CARBOMETHOXY)ETHYLTRIMETHOXY- 208.29 1.069 1.410 Sic2072.0 2-(CARBOMETHOXY)ETHYLTRIMETHOXY- 208.29 1.069 1.410 <	$CH_3OC(CH_2)_{10}S_1 - OCH_3$	10-(CARBOMETHOXY)DECYLDIMETHYL- METHOXYSILANE $C_{15}H_{32}O_3Si$	288.50	130°/0.3	0.903	1.4394
$ \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} C_{H_{3}OCCH_{2}CH_{2}Si} - CH_{3} \\ CH_{3}OCCH_{2}CH_{2}Si} - CH_{3} \\ \end{array} \end{array} \\ \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} C_{I} \\ CH_{3}OCCH_{2}CH_{2}Si} - CH_{3} \\ CI \\ \end{array} \end{array} \end{array} \\ \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} C_{I} \\ CH_{3}OCCH_{2}CH_{2}Si} - CI \\ CI \\ \end{array} \end{array} \end{array} \\ \begin{array}{c} \begin{array}{c} \begin{array}{c} C_{I} \\ CH_{3}OCCH_{2}CH_{2}Si} - CI \\ CI \\ \end{array} \end{array} \end{array} \\ \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} CI \\ CH_{3}OCCH_{2}CH_{2}Si} - CI \\ CI \\ \end{array} \end{array} \end{array} \\ \begin{array}{c} \begin{array}{c} \begin{array}{c} Sic2070.0 \\ 2-(CARBOMETHOXY)ETHYLTRICHLORO- \\ 221.54 \\ OCH_{3}OCCH_{2}CH_{2}Si - CI \\ CI \\ \end{array} \end{array} \\ \begin{array}{c} \begin{array}{c} Sic2070.0 \\ 2-(CARBOMETHOXY)ETHYLTRICHLORO- \\ 221.54 \\ OCH_{3}OCCH_{2}CH_{2}Si - CI \\ \end{array} \\ \begin{array}{c} \begin{array}{c} Sic2070.0 \\ 2-(CARBOMETHOXY)ETHYLTRICHLORO- \\ 221.54 \\ OCH_{3}OCCH_{2}CH_{2}Si - CI \\ \end{array} \\ \begin{array}{c} \begin{array}{c} Sic2070.0 \\ 2-(CARBOMETHOXY)ETHYLTRICHLORO- \\ 221.54 \\ OCH_{3}OCCH_{2}CH_{2}Si - CI \\ \end{array} \\ \begin{array}{c} \begin{array}{c} Sic2070.0 \\ 2-(CARBOMETHOXY)ETHYLTRICHLORO- \\ 221.54 \\ OCH_{3}OCCH_{2}CI \\ \end{array} \\ \begin{array}{c} \begin{array}{c} Sic2070.0 \\ 2-(CARBOMETHOXY)ETHYLTRICHLORO- \\ 221.54 \\ OCH_{3}OCCH_{2}CI \\ \end{array} \\ \begin{array}{c} \begin{array}{c} Sic2070.0 \\ 2-(CARBOMETHOXY)ETHYLTRICHLORO- \\ 221.54 \\ OCH_{3}OCCH_{2}CI \\ \end{array} \\ \begin{array}{c} \begin{array}{c} Sic2070.0 \\ 2-(CARBOMETHOXY)ETHYLTRICHLORO- \\ 221.54 \\ OCH_{3}OCCH_{2}CI \\ \end{array} \\ \begin{array}{c} \begin{array}{c} Sic2070.0 \\ 2-(CARBOMETHOXY)ETHYLTRIMETHOXY \\ 208.29 \\ Sic2072.0 \\ 2-(CARBOMETHOXY)ETHYLTRIMETHOXY \\ \end{array} \\ \begin{array}{c} \begin{array}{c} Sic2072.0 \\ 2-(CARBOMETHOXY)ETHYLTRIMETHOXY \\ Sic2072.0 \\ \\ \begin{array}{c} Sic2072.0 \\ 2-(CARBOMETHOXY)ETHYLTRIMETHOXY \\ Sic2072.0 \\ \\ Sic2072.0 \\ 2-(CARBOMETHOXY)ETHYLTRIMETHOXY \\ Sic2072.0 \\ \\ \begin{array}{c} Sic2072.0 \\ 2-(CARBOMETHOXY)ETHYLTRIMETHOXY \\ Sic2072.0 \\ Sic2072.0 \\ Sic2072.0 \\ Sic2072.0 \\ Sic2072.0 \\ \\ $	Ch ₃			0	50g/\$20	94.00
$ \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c}$	CH ₃ OCCH ₂ CH ₂ Si –CH ₃	2-(CARBOMETHOXY)ETHYLMETHYL- DICHLOROSILANE, 95% C ₅ H ₁₀ Cl ₂ O ₂ Si HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture	flashpoint:	52°C (126°F)	1.18725	1.443925
$ \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c}$				209,000.00		
$ \begin{array}{c} Cl \\ HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture, protic solvents \\ 18147-81-4] TSCA HMIS: 3-3-1-X 25g/$36.00 100g/$117.00 \\ \hline \\ SlC2072.0 \\ 2-(CARBOMETHOXY)ETHYLTRIMETHOXY- 208.29 \\ SlC2072.0 \\ 2-(CARBOMETHOXY)SILYLPROPIONATE) \\ SlC2072.0 \\ 2-(CARBOMETHOXY)ETHYLTRIMETHOXY- 208.29 \\ SlC2072.0 \\ 2-(CARBOMETHOXY)SILYLPROPIONATE) \\ SlC2072.0 \\ 2-(CARBOMETHOXY)ETHYLTRIMETHOXY- 208.29 \\ 1.069 1.410 \\ SlC2072.0 \\ 2-(CARBOMETHOXYSILYLPROPIONATE) \\ SlC2072.0 \\ 2-(CARBOMETHOXYSILYLPROPINATE) \\ SlC2072.0 \\ 2-(CARBOMETHOXYSILYLPROPINATE) \\ SlC2072.0 \\ 2-(CARBOMETHOXYSILYLPROPYLUREA 488.83 \\ 0.924^{25} 1.4521^{25} \\ 2-6^{2}H_{56}N_{2}O_{4}Si \\ forms hydrophobic phases with embedded hydrophilicity \\ HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moisture \\ SlC2072.0 \\ 2-(CARBOMETHOXYSILYLPROPYLUREA 488.83 \\ 0.924^{25} 1.4521^{25} \\ 3-(CARBOMETHOXYSILYLPROPYLUREA 488.83 \\ 3-(CARBOMETHOXYSILYLPROPYLUREA 488.83 \\ 3-(CARBOMETHOXYSILYLPROPYLUREA 488.83 $		2-(CARBOMETHOXY)ETHYLTRICHLORO- SILANE, 95% contains ~ 20% 1-(carbomethox <i>METHYL(3-TRICHLOROSILYLPROPIONATE)</i>	xy)ethyltrich	lorosilane isomer	1.325	1.448
$\begin{array}{c} O \\ H \\ H \\ CH_{3}OCCH_{2}CH_{2}CH_{2}CH_{2}CH_{2}CH \\ OCH_{3} \\ OCH_{3} \\ CH_{4}CH_{2}CH$	Ċl	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture			100g/\$1	17.00
[/6301-00-3] HMIS: 3-3-1-X 10g/\$88.00 [/6301-00-3] HMIS: 3-3-1-X 10g/\$88.00 SID4465.0 N,N-DIOCTYL-N'-TRIETHOXYSILYLPROPYLUREA 488.83 0.924 ²⁵ 1.4521 ²⁵ CH_5CH_5CH_5CH_5CH_5CH_5CH_5CH_5CH_5CH_5	$CH_3OCCH_2CH_2Si - OCH_3$	2-(CARBOMETHOXY)ETHYLTRIMETHOXY- SILANE, 95% contains ~ 20% 1-(carbomethoxy)e METHYL(3-TRIMETHOXYSILYLPROPIONATE)	ethyltrimetho		1.069	1.410
CH_3CH_2CH_2CH_2CH_2CH_2CH_2CH_2CH_2CH_2CH_2	00113	[76301-00-3] HMIS: 3-3-1-X		10g/\$88.00		
[259727-10-1] HMIS: 2-2-1-X 25g/\$82.00	N-C-N(CH ₂) ₃ Si(OC ₂ H ₅) ₃	N,N-DIOCTYL-N'-TRIETHOXYSILYLPROPYLUREA C ₂₆ H ₅₆ N ₂ O ₄ Si forms hydrophobic phases with embedded hydro HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mo	philicity		0.92425	1.452125
		[259727-10-1] HMIS: 2-2-1-X		25g/\$82.00		

	name	MW I	bp/mm (mp)	D420	n _D ²⁰
CH ₃ OCH ₂ CH ₂ O(CH ₂) ₁₁ SiCl ₃	SIM6491.5 METHOXYETHOXYUNDECYLTRICHLOROSILANE C ₁₄ H ₂₉ Cl ₃ O ₂ Si forms self-assembled monolayers with "hydrophi HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture HMIS: 3-2-1-X		145-9°/1.25 solvents 5.0g/\$76.00	1.07	
CH ₃ O ⁻ (CH ₂ CH ₂ O) ₆₋₉ ⁻ (CH ₂) ₃ SiCl ₃	SIM6492.66 2-[METHOXY(POLYETHYLENEOXY)PROPYL]- TRICHLOROSILANE, 90% CH ₃ O(C ₂ H ₄ O) ₆₋₉ C ₃ H ₆ Cl ₃ Si forms hydrophilic surfaces provides protein antifouling surface ¹ . 1. F. Cecchet et al., Langmuir, <i>22</i> , 1173, 2006 HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/me [36493-41-1] HMIS: 3-2-1-X		10g/\$76.00	1.13	1
CH ₃ O-(CH ₂ CH ₂ O)-(CH ₂) ₃ Si(OCH ₃) ₃	SIM6492.7 2-[METHOXY(POLYETHYLENEOXY)PROPYL]- TRIMETHOXYSILANE, 90% CH ₃ (OC ₂ H ₄) ₆₋₉ (CH ₂) ₃ OSi(OCH ₃) ₃ reduces non-specific binding of proteins HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [65994-07-2] TSCA HMIS: 2-2-1-X	viscosity: 2	(-8°)mp 88°C (190°F) 9 cSt	1.076 100g/\$24	1.403
$CH_{3}O^{-}(CH_{2}CH_{2}O) _{9.12} (CH_{2})_{3}Si(OCH_{3})_{3}$	SIM6492.72 2-[METHOXY(POLYETHYLENEOXY)PROPYL]- TRIMETHOXYSILANE, 90% $CH_3(OC_2H_4)_{9-12}(CH_2)_3Si(OCH_3)_3$ [65994-07-2] TSCA HMIS: 2-2-1-X	596-725 flashpoint: 25g/\$76.00	88°C(190°F)	1.09 100g/\$24	47.00
CH ₃ OCH ₂ CH ₂ CH ₂ Si(OCH ₃) ₃	SIM6493.0 3-METHOXYPROPYLTRIMETHOXYSILANE C ₇ H ₁₈ O ₄ Si HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [33580-59-5] HMIS: 3-2-1-X		98-9°/40 53°C (127°F)	0.995 100g/\$1 ⁻	10.00
CH ₃ O (CH ₂ CH ₂ O) ₃ -(CH ₂) ₃ SiCl ₃	$\begin{tabular}{lllllllllllllllllllllllllllllllllll$	339.71	140°/0.2 10g/\$122.00	1.163	
CH ₃ O-(CH ₂ CH ₂ O) ₃ -(CH ₂) ₃ Si(OCH ₃) ₃	SIM6493.4 METHOXYTRIETHYLENOXYPROPYLTRI- METHOXYSILANE C ₁₃ H ₃₀ O ₇ Si forms polymeric proton-conducting electrolytes 1. J. Ritchie et al, Chem. Mater., <i>18</i> , 504, 2006 [132388-45-5] HMIS: 3-2-1-X		148°/0.3 10g/\$128.00	1.034	
O-CH2CH2OCH2CH2CH2Si(OCH2CH3)3	SIT8186.0 (2-TRIETHOXYSILYLPROPOXY)ETHOXY- SULFOLANE, 95% C ₁₅ H ₃₂ O ₇ SSi forms hydrophilic surfaces HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist [502925-40-8] HMIS: 2-2-1-X	384.56 ure	190-4°/0.4 10g/\$64.00	1.122	
$(CH_3O)_3SiCH_2CH_2CH_2 CH_2 CH_2CH_2Si(OCH_3)_3$	SIT8717.0 TRIS(3-TRIMETHOXYSILYLPROPYL)ISO CYANURATE, 95% C ₂₁ H ₄₅ N ₃ O ₁₂ Si ₃ HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with water [26115-70-8] TSCA HMIS: 2-1-1-X	viscosity: 32		1.170 2.0kg/\$3	1.4610
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Hydrophilic Silane Properties Hydroxylic

	, , j a. (ολγίιο			
	name	MW	bp/mm (mp)	D 4 ²⁰	n _{D}^{20}
HOCH ₂ CH ₂ NCH ₂ CH ₂ CH ₂ Si(OEt) ₃ HOCH ₂ CH ₂	SIB1140.0 BIS(2-HYDROXYETHYL)-3-AMINOPROPYL- TRIETHOXYSILANE, 62% in ethanol C ₁₃ H ₃₁ NO ₅ Si contains 2-3% hydroxyethylaminopropyltriethoxy urethane polymer coupling agent employed in surface modification for preparation 1. G. McGall et al, Proc. Nat'l Acad. Sci., 93, 135 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [7538-44-5] TSCA HMIS: 3-4-0-X	specific w silane of oligonucl 5, 1996.		0.92 2m²/g 100g/\$§	1.409 ²⁵ 98.00
(CH ₃ O) ₃ SiCH ₂ CH ₂ CH ₂ NCH ₂ CH ₂ OH CH ₂ CH ₂ NCH ₂ CH ₂ OH (CH ₃ O) ₃ SiCH ₂ CH ₂ CH ₂	$\label{eq:sigma_state} \hline $$ SIB1142.0 $$ N,N'-BIS(HYDROXYETHYL)-N,N'-BIS-$$ (TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE $$ C_{18}H_{44}N_2O_8Si_2$$ [214362-07-9] $$ HMIS: 3-4-1-X $$ The second state of the state of t$		methanol 11°C(52°F) 25g/\$66.00	0.985	r
$\begin{array}{c} & & & & & & & & & & & & & & & & & & &$	SIB1824.2 BIS-[3-(TRIETHOXYSILYLPROPOXY)- 2-HYDROXYPROPOXY]POLYETHYLENE OXIDE 68 HMIS: 2-4-1-X	700-800 5% in metha	anol 25g/\$74.00		
	SIB1824.4 2,2-BIS(3-TRIETHOXYSILYLPROPOXY- METHYL)BUTANOL, 50% in ethanol C ₂₄ H ₅₄ O ₉ Si ₂ for solid state synthesis of oligonucleotides HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w HMIS: 2-4-1-X		10g/\$136.00	0.899	
HO–(CH ₂ CH ₂ O) $-$ (CH ₂) ₃ Si(OCH ₂ CH ₃) ₃	SIH6188.0 [HYDROXY(POLYETHYLENEOXY)PROPYL]- TRIETHOXYSILANE, (8-12 EO) 50% in ethanol HMIS: 2-4-1-X	500-550	0.889 25g/\$78.00	1.401	
HOCH ₂ CH ₂ NCH ₂ CH ₂ CH ₂ Si(OCH ₃) ₃ H ₃ C	SIH6172.0 N-(HYDROXYETHYL)-N-METHYLAMINO-PROPYLTRIMETHOXYSILANE, 75% in methanol $C_9H_{23}NO_4Si_{HMIS: 3-4-1-X}$		16°C (61°F)	0.99 100g/\$1	1.417 79.00
$\begin{array}{c} & \bigcirc C_2H_5 \\ & HO^{-}CH_2^{-}Si^{-}OC_2H_5 \\ & & OC_2H_5 \\ & & \downarrow^{+} \\ & & \bigcirc C_2H_5 \\ & HO^{-}CH_2^{-}Si^{-}O^{-}CH_2^{-}Si^{-}OC_2H_5 \\ & & OC_2H_5 \\ & & OC_2H_5 \\ \end{array}$	SIH6175.0 HYDROXYMETHYLTRIETHOXYSILANE, 50% in ethanol <i>TRIETHOXYSILYLMETHANOL</i> C ₇ H ₁₈ O ₄ Si contains equilibrium condensa hydrolysis yields analogs of silica- hydroxymet 1. B. Arkles, US Pat. 5,371,262, 1994.	194.31 ation oligom thylsilanetric	ol polymers ¹ .	0.866	
$\begin{array}{c} O \\ C - NH(CH_2)_3 Si(OC_2H_5)_3 \\ H - OH \\ HO - H \\ H - OH \end{array}$	$\begin{tabular}{lllllllllllllllllllllllllllllllllll$		25g/\$96.00 8°C (46°F)	0.951	
	[104275-58-3] HMIS: 2-4-1-X SIT8189.5 N-(3-TRIETHOXYSILYLPROPYL)-4-HYDROXY- BUTYRAMIDE $C_{13}H_{29}NO_5Si$ anchoring reagent for light-directed synthesis of 1. G. McGall et al, J. Am. Chem. Soc., <i>119</i> , 5081	, 1997.	ss¹.	100g/\$9	1.4533
(C ₂ H ₅ O) ₃ Si CH ₂ H(OCH ₂ CH ₂) ₄₋₆ OCNHCH ₂ CH ₂ O	[186543-03-3] HMIS: 2-2-1-X SIT8192.0 N-(TRIETHOXYSILYLPROPYL)-O-POLY- ETHYLENE OXIDE URETHANE, 95% $C_{10}H_{22}NO_4SiO(CH_2CH_2O)_{4-6}H$ contains some bis(urethane) analog hydrophilic surface modifier stabilizes Si ₃ N ₄ aqueous colloids ¹ . 1. J. Yanez et al, J. Eur. Ceram. Soc., <i>18</i> , 1993, 1 HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist	ture	75-125 cSt	50g/\$12	1.454025
	[74695-91-3] HMIS: 2-1-1-X	25g/\$16.00) 100g/\$52.00	2kg/\$72	0.00

Hydrophilic Silane Properties

Ionic-Charge Inducible

	Ionic-Charge muucible				
	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
$\overbrace{\begin{tabular}{ c c c c c c c } &H & CI^{-} & H \\ &H & I \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & & & \\ & & $	SIB0957.0 (2-N-BENZYLAMINOETHYL)-3-AMINOPROPYL- TRIMETHOXYSILANE, hydrochloride 50% in meth C ₁₅ H ₂₈ N ₂ O ₃ Si.HCl amber liquid [623938-90-9] TSCA HMIS: 3-3-1-X	nanol	:: 9°C (48°F) 0	0.942 100g/\$5	1.4104
(CH ₃ O) ₃ SiCH ₂ CH ₂ CH ₂ N-CH ₃ (CH ₃ O) ₃ SiCH ₂ CH ₂ CH ₂	SIB1835.0 BIS(3-TRIMETHOXYSILYLPROPYL)- N-METHYLAMINE C ₁₃ H ₃₃ NO ₆ Si ₂ HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [31024-70-1] HMIS: 2-1-0-X	355.58 flashpoint	175°/10 :: 106°C (223°F)	1.023 100g/\$	1.4300
O OH III I Na ^{+ -} OCCH ₂ CH ₂ Si—O ⁻ Na ⁺ I OH	SIC2263.0 CARBOXYETHYLSILANETRIOL, SODIUM SALT, 25% in water C ₃ H ₆ O ₅ Na ₂ Si HYDROLYTIC SENSITIVITY: 0 forms stable aqueous solut [18191-40-7] HMIS: 2-0-0-X	196.14 pH:12-12	.5	1.17 ²⁵	
CISO ₂ —CH ₂ CH ₂ SiCl ₃	SIC2415.0 2-(4-CHLOROSULFONYLPHENYL)ETHYLTRI- CHLOROSILANE, 50% in methylene chloride $C_8H_8CI_4O_2SSi$	338.11		1.37	
Solid Phase Extraction (SPE) columns with benzenesulfonic	contains 30% free sulfonic acid analog and small ar employed in preparation of solid phase extraction co HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture [79793-00-3] TSCA HMIS: 4-2-2-X	olumns	s	ensation p 100g/\$1	
acid functionalized silica are utilized to analyze urine samples for amino acids and drugs of abuse.	SIC2415.4 2-(4-CHLOROSULFONYLPHENYL)ETHYLTRI- CHLOROSILANE, 50% in toluene C ₈ H ₈ Cl ₄ O ₂ SSi contains 30% free sulfonic acid analog and small ar			1.08 ensation p	products
of abuse.	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with water/moisture [79793-00-3] TSCA HMIS: 4-4-2-X	e, protic solvent 25g/\$52.0		100g/\$1	69.00
CISO ₂ —CH ₂ CH ₂ Si(OCH ₃) ₃	SIC2417.0 2-(4-CHLOROSULFONYLPHENYL)ETHYLTRI- METHOXYSILANE, 50% in methylene chloride C ₁₁ H ₁₇ CIO ₅ SSi contains free sulf treated silica acts as etherification catalyst ¹ . treatment of surface oxidized PMDSO support			1.30 ²⁵	
	1. B. Sow et al, Microporous & Mesoporous M 2. B. Wang et al, Micro Total Analysis Systems [126519-89-9] HMIS: 3-2-1-X		2., Roy Soc. Cher	n., 297, p 100g/\$2	
$CH_{3}(CH_{2})_{9}$ $+$ $CH_{3}(CH_{2})_{9}$ $CH_{2}CH_{2}CH_{2}CH_{2}Si(OCH_{3})_{3}$	TITDHOLI TIC SENSITIVITT. 7 SI-OH TEACIS SIOWIY WILL W	e) ₃	:: 13°C (55°F)	0.863	1.4085
CH ₃ CH ₂ CH ₃ CH ₂ CH ₃ CH ₂ NCH ₂ Si - OCH ₂ CH ₃ OCH ₂ CH ₃	[68959-20-6] TSCA HMIS: 3-4-0-X SID3395.4 DIETHYLAMINOMETHYLTRIETHOXYSILANE C ₁₁ H ₂₇ NO ₃ Si catalyst for neutral cure 1-part RTVs HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w	249.43	25g/\$49.00 74-6°/3	0.9336 ²	^₅ 1.4142 ²⁵
OCH ₂ CH ₃	[15180-47-9] HMIS: 2-2-1-X	vater/moistule	25g/\$49.00		

	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
CH ₃ CH ₂ CH ₃ CH ₂ NCH ₂ CH ₂ CH ₂ Si(OCH ₃) ₃	SID3396.0 (N,N-DIETHYL-3-AMINOPROPYL)TRI- METHOXYSILANE $C_{10}H_{25}NO_3Si$	235.40 flashpoint:	120°/20 100°C (212°F)	0.934	1.423
Ch ₃ Ch ₂	HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with w [41051-80-3] TSCA HMIS: 2-2-1-X	ater/moisture 25g/\$62.00)	100g/\$2	202.00
Cl ⁻ CH ₃ CH ₃ (CH ₂) ₁₇ ⁺¹ N ⁻ (CH ₂) ₃ Si(OCH ₃) ₃ CH ₃ CH ₃	 SIO6620.0 OCTADECYLDIMETHYL(3-TRIMETHOXYSILYL- PROPYL)AMMONIUM CHLORIDE, 60% in methano C₂₆H₅₈CINO₃Si contains 3-5% Cl(CH₂)₃Si(OMe)₃ employed as lubricant/anti-static surface treatment orients liquid crystals dispersion/coupling agent for high density magnet application as immobilizeable antimicrobial report 1. H. Vincent in "Chemically Modified Oxide Surface 2. W. White et al in "Silanes, Surfaces & Interfaces' HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with wa [27668-52-6] TSCA HMIS: 3-4-0-X 	flashpoint: nt etic recordin ted ² . ces," ed. D. L wed. D. Leyc	eyden, Gordon & B len, Gordon & Brea		6, p. 107.
CH ₂ CH ₂ SCH ₂ CH ₂ CH ₂ CH ₂ Si - OCH ₃ OCH ₃	SIP6926.2 2-(2-PYRIDYLETHYL)THIOPROPYLTRI- METHOXYSILANE C ₁₃ H ₂₃ NO ₃ SSi chelates metal ions [29098-72-4] HMIS: 3-2-1-X	301.48	156-7°/0.25 10g/\$118.00	1.089	1.498
N CH ₂ CH ₂ SCH ₂ CH ₂ CH ₂ CH ₂ Si - OCH ₃ OCH ₃	$\begin{tabular}{lllllllllllllllllllllllllllllllllll$	301.48 pKa: 4.8 paration usi	160-2°/0.2	1.09	1.5037
	charge induction chromatography (HCIC) [198567-47-4] HMIS: 3-2-1-X		10g/\$124.00	_	
CH ₂ -CH ₂ -Si(OCH ₂ CH ₃) ₃	SIP6928.0 2-(4-PYRIDYLETHYL)TRIETHOXYSILANE C ₁₃ H ₂₃ NO ₃ Si see also SIT8396.0 HYDROLYTIC SENSITIVITY: 7 Si-OR reacts slowly with water [98299-74-2] HMIS: 3-2-1-X	269.43 amber liqu r/moisture	105°/0.9 id 10g/\$119.00	1.00	1.4624 ²⁴
CH ₂ CH ₂ SiCl ₃	SIT8157.0 2-[2-(TRICHLOROSILYL)ETHYL]PYRIDINE C ₇ H ₈ Cl ₃ NSi	240.59 fuming soli	280°-decompos (207°)mp d, moisture sensitiv		
N CH2CH2SICI3	HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [17082-69-8] TSCA HMIS: 3-2-1-X		solvents	100g/\$1	46.00
CH ₂ CH ₂ SiCl ₃	SIT8158.0 4-[2-(TRICHLOROSILYL)ETHYL- PYRIDINE, 15-20% in toluene C ₇ H ₈ Cl ₃ NSi see also SIT8396.0 2-(TRIMETHOXYSILYLETH employed in polypyridine self-assembled monola 1. S. Paulson et al, J. Chem. Soc. Chem. Comm., HYDROLYTIC SENSITIVITY: 8 reacts rapidly with moisture [17082-70-1] TSCA HMIS: 3-4-1-X	IYL)PYRIDI yers¹. , <i>21</i> , 1615,	; extremely moistu NE 1992. solvents	0.93 re sensiti 100g/\$9	
		209/929.00		1009/\$5	

	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
$\sum_{N \searrow N = CH_2CH_2CH_2CH_2Si = OC_2H_5} OC_2H_5 OC_2H_5$	SIT8187.5 N-(3-TRIETHOXYSILYLPROPYL)- 4,5-DIHYDROIMIDAZOLE <i>3-(2-IMIDAZOLIN-1-YL)PROPYLTRIETHOXYSILANE</i> C ₁₂ H ₂₆ N ₂ O ₃ Si utilized in HPLC of metal chelates ¹ . forms proton vacancy conducting polymers w/su ligand for molecurlarly imprinting silica w/ chymo 1. T. Suzuki et al, Chem. Lett, 881, 1994. 2. V. De Zea Bermudez et al, Sol-Gel Optics II, S 3. M. Markowitz et al, Langmuir, 1989. HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist [58068-97-6] TSCA HMIS: 2-1-1-X	viscosity: 5 Ilfonamides t trypsin trans SPIE Proc. 7	by sol-gel ² . ition state analog ³ 1 <i>728</i> , 180, 1992.		.452 0.00
O II HOSCH ₂ CH ₂ CH ₂ Si(OH) ₃ O	SIT8378.3 3-(TRIHYDROXYSILYL)-1-PROPANE- SULFONIC ACID 30-35% in water C ₃ H ₁₀ O ₆ SSi HYDROLYTIC SENSITIVITY: 0 forms stable aqueous solut [70942-24-4] TSCA HMIS: 3-0-0-X	202.26 pH: <1 tions 25g/\$51.00	(-62°)	1.12 100g/\$ 16	6.00
O H ₃ PO(CH ₂) ₃ Si(OH) ₃ O Na ⁺	SIT8378.5 3-TRIHYDROXYSILYLPROPYLMETHYL- PHOSPHONATE, SODIUM SALT, 42% in water C ₄ H ₁₂ NaO ₆ PSi contains 4-5% methanol, sodium HYDROLYTIC SENSITIVITY: 0 forms stable aqueous solur [84962-98-1] TSCA HMIS: 1-2-0-X	methylphos		1.25 500g/\$64.	00
$\begin{array}{c} H_{3}C \\ H_{3}C^{-N^{+}} \\ H_{3}C' \\ \end{array} \\ \begin{array}{c} C \\ \end{array} \\ \end{array} \\ \begin{array}{c} C \\ \end{array} \\ \end{array} \\ \begin{array}{c} C \\ \end{array} \\ C \\ \end{array} \\ \begin{array}{c} C \\ \end{array} \\ C \\ \end{array} \\ \begin{array}{c} C \\ \end{array} \\ C \\ \end{array} \\ \begin{array}{c} C \\ \end{array} \\ C \\ \end{array} \\ \begin{array}{c} C \\ C \\ \end{array} \\ C \\ C \\ \end{array} \\ \begin{array}{c} C \\ C \\ C \\ \end{array} \\ \begin{array}{c} C \\ C \\ C \\ \end{array} \\ \begin{array}{c} C \\ C \\ C \\ C \\ \end{array} \\ \begin{array}{c} C \\ C $	SIT8395.0 N-(TRIMETHOXYSILYLETHYL)BENZYL-N,N,N- TRIMETHYLAMMONIUM CHLORIDE, 60% in meth- C ₁₅ H ₂₈ CINO ₃ Si candidate for exchange resins and extraction pha HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist HMIS: 3-3-1-X	flashpoint: : ses	25°C (77°F) 25g/\$80.00	0.966	
CH ₂ CH ₂ Si(OCH ₃) ₃	SIT8396.0 2-(TRIMETHOXYSILYLETHYL)PYRIDINE C ₁₀ H ₁₇ NO ₃ Si see also SIP6928.0 HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist [27326-65-4] HMIS: 3-2-1-X		105°/0.3 >110°C (>230°F)	1.06 1 50g/\$164.	.4755 00
H ₂ NCH ₂ CH ₂ HNCH ₂ CH ₂ NH CH ₂ CH ₂ (CH ₃ O) ₃ SiCH ₂	SIT8398.0 (3-TRIMETHOXYSILYLPROPYL)DIETHYLENE- TRIAMINE tech-95 C ₁₀ H ₂₇ N ₃ O ₃ Si HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist [35141-30-1] TSCA HMIS: 3-1-1-X	Yc of treate	114-8°/2 137°C (279°F) ad surface: 37.5 dy 0		.4590 COMMERCIAL 8.00 L
Na^+OOCCH_2 $CH_2COO^-Na^+$ NCH_2CH_2N Na^+OOCCH_2 CH_2 CH_2 $(CH_3O)_3SiCH_2$	SIT8402.0 N-(TRIMETHOXYSILYLPROPYL)ETHYLENE- DIAMINE TRIACETIC ACID, TRISODIUM SALT, 45° C ₁₄ H ₂₅ N ₂ Na ₃ O ₉ Si essentially silanetriol, contair chelates metal ions HYDROLYTIC SENSITIVITY: 0 forms stable aqueous solur [128850-89-5] TSCA HMIS: 2-0-0-X	462.42 % in water ns NaCl		1.26 100g/\$133	
H_2N , CI^- $C=S^+$ $-CH_2CH_2CH_2Si(OCH_3)_3$ H_2N	SIT8405.0 N-(TRIMETHOXYSILYLPROPYL)ISOTHIO- URONIUM CHLORIDE, 50% in water <i>TRIHYDROXYPROPYLCARBAMIDOTHIOIC ACID HYDRO</i> C ₇ H ₁₉ CIN ₂ O ₃ SSi antimicrobial activity reported HYDROLYTIC SENSITIVITY: 0 forms stable aqueous solur [84682-36-0] TSCA HMIS: 2-0-0-X	274.84 essentially <i>OCHLORIDE</i> pH: 6			.441
$\begin{array}{c} C_4H_9 ^{-} Br \\ C_4H_9 - \underbrace{N}_{l} - CH_2CH_2CH_2Si(OCH_3)_3 \\ C_4H_9 \end{array}$	SIT8412.0 N-TRIMETHOXYSILYLPROPYL-N,N,N-TRI- n-BUTYLAMMONIUM BROMIDE, 50% in methanol C ₁₈ H ₄₂ BrNO ₃ Si immobilizable phase transfer catalyst HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/moist HMIS: 3-4-1-X	flashpoint:	11°C (52°F) 25g/\$89.00	0.92	
	(215) 547-1015 FAX: (215) 547-2484	www.geles	st.com		69

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	name	MW	bp/mm (mp)	D4 ²⁰	n _D ²⁰
$\begin{array}{c} C_{4}H_{9} {{}{}{}{}{}{}{\overset$	SIT8414.0 N-TRIMETHOXYSILYLPROPYL-N,N,N-TRI- n-BUTYLAMMONIUM CHLORIDE, 50% in methano C ₁₈ H ₄₂ CINO ₃ Si contains 3-5% chloropropyltrimethoxysilane and HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mois HMIS: 3-4-1-X	flashpoin I Bu ₃ NH⁺Cl	t: 11°C (52°F) 25q/\$81.00	0.88	
$\begin{array}{c} CH_3 \ Cl \\ H_3C - N \ - N \ CH_2CH_2CH_2Si(OCH_3)_3 \\ I \\ CH_3 \end{array}$	SIT8415.0 N-TRIMETHOXYSILYLPROPYL-N,N,N-TRI- METHYLAMMONIUM CHLORIDE, 50% in methano <i>N,N,N-TRIMETHYL-3-(TRIMETHOXYSILYL)-1-PROPANA</i> C ₉ H ₂₄ CINO ₃ Si employed for bonded chromatographic phases anti-static agent used to treat glass substrates employed in elect see also SIT8395.0 HYDROLYTIC SENSITIVITY: 7 reacts slowly with water/mois [35141-36-7] TSCA HMIS: 2-4-1-X	flashpoin roblotting	t: 16°C (61°F)	0.927 2.0kg/\$3	1.3966 390.00

Polymeric Hydrophilic Silanes

Polymeric Amine

	name	MW bp/mm (mp)	D ₄ ²⁰ n _D ²⁰
. 55	SSP-060 TRIMETHOXYSILYLPROPYL MODIFIED (POLYETHYLENIMINE) 50% in isopropanol visc: 125-175 cSt employed as a coupling agent for polyamides ¹ . in combination with glutaraldehyde immobilizes 1. B. Arkles et al, SPI 42nd Composite Inst. Pro 2. S. Cramer et al, Biotech. & Bioeng., <i>33(3)</i> , 34 [136856-91-2] TSCA HMIS: 2-4-1-X	oc., 21-C, 1987	0.92 ed 2.0kg/\$364.00
$\begin{pmatrix} H \\ N + CF \\ n \end{pmatrix} \begin{pmatrix} H \\ N \\ n \end{pmatrix}_{n} \begin{pmatrix} H \\ N \\ N \end{pmatrix}_{4n}$ Si(OCH ₃) ₂ OCH ₃	[136856-91-2] TSCA HMIS: 2-4-1-X SSP-065 DIMETHOXYMETHYLSILYLPROPYL MODIFIED (POLYETHYLENIMINE) 50% in isopropanol visc: 100-200 cSt primer for brass [1255441-88-5] TSCA HMIS: 2-4-1-X	1500-1800 ~20% of nitrogens substitut 100g/\$38.00	0.92 ed 2.0kg/\$494.00
		164	

Water-borne Aminoalkyl Silsesquioxane Oligomers										TSCA
H with the		Functional	Ν	Aolecular	Weight %	Specific				
s la contra	Code	Group	Mole %	Weight	in solution	Gravity	Viscosity	pН	Price/100g	3kg
15 15th of ou	WSA-7011	Aminopropyl	65-75	250-500	25-28	1.10	5-15	10-10.5	\$29.00	\$435.00
2-0 VIV	WSA-9911*	Aminopropyl	100	270-550	22-25	1.06	5-15	10-10.5	\$24.00	\$360.00
115-195 John III	WSA-7021	Aminoethylaminopropyl	65-75	370-650	25-28	1.10	5-10	10-11	\$29.00	\$435.00
H- CH- CH- Of Lan	WSAV-6511**	Aminopropyl, vinyl	60-65	250-500	25-28	1.11	3-10	10-11	\$35.00	\$480.00
4 ² C	*CAS [29159-3	7-3] **[207308-27-8]								
EUght										

Aqueous exposure of treated surfaces converts Epoxy-Silanes to Hydrophilic-Diols

Epoxy Functional Silanes

	Epoxy Functional Silanes - Trialkoxy			
OCH2CH2Si(OC2H5)3		288.46 114-7°/0.4 flashpoint: 104°C (220°F)	1.015 1.4455	
\sim	C ₁₄ H ₂₈ O ₄ Si [10217-34-2] tsca hmis: 2-1-1-X	25g/\$14.00 100g/\$46.00	2.0kg/\$320.00	
OCH ₂ CH ₂ Si(OCH ₃) ₃	ring epoxide more reactive than glycidoxyprop UV initiated polymerization of epoxy group wit forms UV-cureable coating resins by controller 1. J. Crivello et al, Chem. Mater. 9, 1554, 1997	h weak acid donors. d hydrolysis¹. 7.	dynes/cm 7 m²/g	COMMERCIAL
0	[3388-04-3] TSCA HMIS: 3-1-1-X	100g/\$24.00 2.0kg/\$270.00	18kg/\$1044.00	
CH ₂ CH ⁻ CH ₂ CH ₂ CH ₂ CH ₂ CH ₂ CH ₂ CH ₂ CH ₃ O-Si-OCH ₃ OCH ₃	SIG5840.0 (3-GLYCIDOXYPROPYL)TRIMETHOXYSILANE 3-(2,3-EPOXYPROPOXY)PROPYLTRIMETHOXYSILANE C ₉ H ₂₀ O ₅ Si coupling agent for epoxy composites employed in [2530-83-8] TSCA HMIS: 3-1-1-X	236.34 120°/2 (<-70°)mp TOXICITY- oral rat, LD50: 8,4 electronic "chip" encapsulatior 100g/\$16.00 2.0kg/\$138.00	1.	
$CH_2CH - CH_2$ O $CH_2CH_2CH_2$ $CH_2CH_2CH_2$ $CH_3CH_2O - Si - OCH_2CH_3$ OCH_2CH_3	SIG5839.0 (3-GLYCIDOXYPROPYL)TRIETHOXYSILANE C ₁₂ H ₂₆ O ₅ Si [2602-34-8] TSCA HMIS:3-2-1-X	278.4 124°/3 flashpoint: 144°C (291°F) 25g/\$38.00 100g/\$124.00	1.00 1.425 2.0kg/\$580.00	-
о СH ₂ CH ₂ CH ₂ CH ₂ СH ₂ CH ₂ CH ₂ CH ₃ O-Si-OCH ₃ OCH ₃	SIG5840.1 (3-GLYCIDOXYPROPYL)TRIMETHOXYSILANE 99+% 3-(2,3-EPOXYPROPOXY)PROPYLTRIMETHOXYSILANE $C_9H_{20}O_5Si$ [2530-83-8] TSCA HMIS: 3-1-1-X	236.34 120°/2 (<-70°)mp TOXICITY- oral rat, LD50: 8,4 25g/\$180.00 in fluoropoly		DEVELO
H ₂ C — CHCH ₂ CH ₂ CH ₂ CH ₂ CH ₂ Si(OC ₂ H ₅) ₃	SIE4675.0 5,6-EPOXYHEXYLTRIETHOXYSILANE C ₁₂ H ₂₆ O ₄ Si [86138-01-4] HMIS: 3-2-1-X	262.42 115-9°/1.5 flashpoint: 99°C (210°F) 10g/\$89.00	0.96025 1.425425	DEVELOPMENTAL
	Epoxy Functional Silanes - Dialkoxy	160.		
$CH_2CH_2CH_2CH_2$ $CH_2CH_2CH_2$ $CH_2CH_2CH_2$ $C_2H_5O_5i-OC_2H_5$	SIG5832.0 (3-GLYCIDOXYPROPYL)METHYLDIETHOXY- SILANE C ₁₁ H ₂₄ O ₄ Si	248.39 122-6°/5 TOXICITY- oral rat, LD50: > flashpoint: 122°C (252°F) viscosity: 3.0 cSt	0.978²⁵ 1.431 •2000mg/kg	COMMERCIAL
ĊH ₃	employed in scratch-resistant coatings for eyeglas [2897-60-1] TSCA HMIS: 2-1-1-X	25g/\$38.00 100g/\$124.00	2.0kg/\$580.00	4L
CH_2CHCH_2 CH_2CHCH_2 $CH_2CH_2CH_2$ CH_3O-i-OCH_3$	SIG5836.0 (3-GLYCIDOXYPROPYL)METHYLDIMETHOXY- SILANE C ₉ H ₂₀ O ₄ Si	220.34 100°/4 flashpoint: 105°C (221°F)	1.02 1.43125	D
CH ₃	relative hydrolysis rate vs. SIG5840.0: 7.5:1 [65799-47-5] TSCA-L HMIS: 3-1-1-X	25g/\$50.00	100g/\$162.00	EVELC
CH ₂ CH ₂ CH ₂ CH ₂ O CH ₂ CH ₂ CH ₂ CH ₃ -Si-CH ₃	Epoxy Functional Silanes - Monoalkoxy SIG5825.0 (3-GLYCIDOXYPROPYL)DIMETHYLETHOXY- SILANE C ₁₀ H ₂₂ O ₃ Si	218.37 100°/3 flashpoint: 87°C (189°F)	0.950 1.433725	DEVELOPMENTAL
OC ₂ H ₅	[17963-04-1] TSCA HMIS: 3-2-1-X	10g/\$40.00	50g/\$160.00	_

Silyl Hydrides

Silyl Hydrides are a distinct class of silanes that behave and react very differently than conventional silane coupling agents. Their application is limited to deposition on metals (see discussion on p. 17). They liberate hydrogen on reaction and should be handled a with appropriate caution.

	name	MW	bp/mm (mp)	D 4 ²⁰	n _D ²⁰
$CH_3(CH_2)_{10}CH_2S_1$ -H	SID4629.6 DODECYLSILANE C ₁₂ H ₂₈ Si forms SAMS on gold surfaces 872-19-5 HMIS: 2-2-1-X	200.44	80°/7 10g/\$78.00	0.7753	1.438025
CH ₃ (CH ₂) ₁₆ CH ₂ -Si-H H	SIO6635.0 n-OCTADECYLSILANE C ₁₈ H ₄₀ Si contains 4-6% C ₁₈ isomers forms self-assembled monolayers on titanium ¹ . 1. A. Fadeau et al, J. Am. Chem. Soc., <i>121</i> , 1218 [18623-11-5] TSCA HMIS: 2-1-1-X		195°/15 (29°)mp 110°C (>230°F)	0.794 100g/\$18	50.00
H CF ₃ CF ₂ CF ₂ CF ₂ CF ₂ CF ₂ CF ₂ CH ₂ CH ₂ CH ₂ Si H	SIT8173.0 (TRIDECAFLUORO-1,1,2,2-TETRA- HYDROOCTYL)SILANE $C_8H_7F_{13}Si$ provides vapor-phase hydrophobic surfaces on t [469904-32-3] HMIS: 3-3-1-X	378.22 itanium, gold,	75°/251.446 silicon 10g/\$190.00	1.3184	
$H_2C = CH(CH_2)_8CH_2S_i -H$	SIU9048.0 10-UNDECENYLSILANE C ₁₁ H ₂₄ Si HMIS: 2-3-1-X	184.40	2.5g/\$180.00	0.78	
	2,2		nol	<u>,</u> g	

MethylHydrosiloxane homopolymers are used as water-proofing agents, reducing agents and as components in some foamed silicone systems.

CH ₃	$/ H \setminus CH_3$
	-Si-O-Si-CH ₃
ĊH ₃	$\dot{C}H_3$ /n $\dot{C}H_3$

	polyMethylHydrosiloxanes, Trimethylsiloxy terminated			ylHydrosiloxanes, Trimethylsiloxy terminated Tg: -119° V.T.C: 0.50				CAS: [63148-57-2] TSCA		
COMMERCIAL	Code	Viscosity	Molecular Weight	Mole % (MeHSiO)	Equivalent Weight	Specific Gravity	Refractive Index	Price/100g	Price/3 kg	
WER	HMS-991	15-25	1400-1800	100	67	0.98	1.395	\$14.00	\$96.00	
INIO:	HMS-992	25-35	1800-2100	100	65	0.99	1.396	\$19.00	\$134.00	
0	HMS-993	35-45	2100-2400	100	64	0.99	1.396	\$24.00	\$168.00	

Surface Modification with Silanes: What's not covered in "Hydrophobicity, Hydrophilicity and Silane Surface Modification"?

Silanes which are expected to form covalent bonds after deposition onto surfaces are discussed in the Gelest brochure entitled **"Silane Coupling Agents: Connecting Across Boundaries"** Aminosilanes which are important in some hydrophilic surface treatments are covered in detail.

Further Reading

Silane Coupling Agents - General References and Proceedings

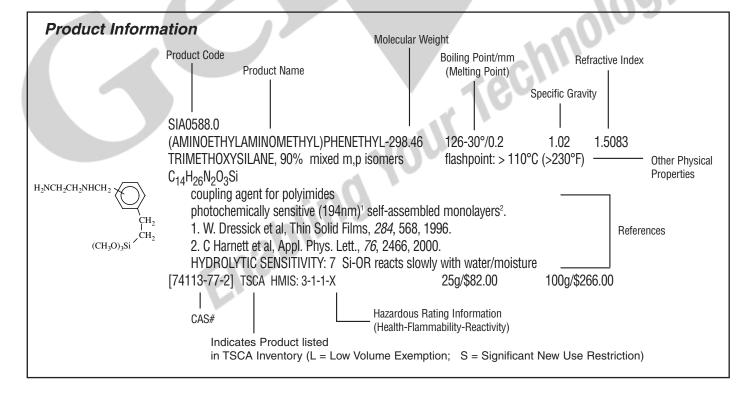
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Cover background photo: Fluoroalkylsilane treated multi-color red granite is both hydrophobic and oleophobic.

> The Stenocara beetle, an African desert species, harvests water that adsorbs on superhydrophilic bumps on its back, then transfers droplets into superhydrophophic channels that lead to its mouth.



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